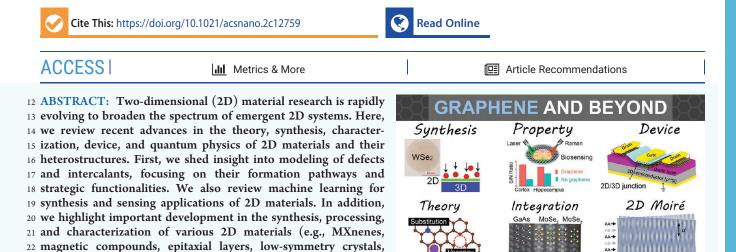
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Recent Advances in 2D Material Theory, Synthesis, Properties, and Applications

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24 materials. Next, we discuss the optical and phonon properties of
25 2D materials controlled by material inhomogeneity and give examples of multidimensional imaging and biosensing equipped
26 with machine learning analysis based on 2D platforms. We then provide updates on mix-dimensional heterostructures using
27 2D building blocks for next-generation logic/memory devices and the quantum anomalous Hall devices of high-quality
28 magnetic topological insulators, followed by advances in small twist-angle homojunctions and their exciting quantum
29 transport. Finally, we provide the perspectives and future work on several topics mentioned in this review.

30 **KEYWORDS:** 2D Materials, Epitaxial Growth, Doping, Theory, Moiré Engineering, Strain Engineering, Biosensing, Machine Learning, 31 Magnetic and Topological Properties, Multidimensional Heterostructures

32 INTRODUCTION

³³ Two-dimensional materials (2D materials) are thermodynami-³⁴ cally stable as atomically or molecularly thin layered structures ³⁵ and exhibit properties different from their bulk counterparts. ³⁶ From the seminal papers^{1,2} to current 2D materials research, it is ³⁷ evident that graphene, hexagonal boron nitride (hBN), 2D ³⁸ transition metal dichalcogenides (TMDs),³ and metal carbides ³⁹ and nitrides (MXenes)⁴ are currently the most common ⁴⁰ building blocks in this field. In the past decade, magnetic 2D ⁴¹ materials,⁵ 2D metals,⁶ layered topological insulators (TIs),⁷ ⁴² and 2D moiré van der Waals (vdW) heterostructures⁸ are at the

23 etc.) and discuss oxidation and strain gradient engineering in 2D

front lines of research in this material family. Additionally, more $_{43}$ have been theoretically predicted to exist and await exploration.⁹ $_{44}$ 2D materials and their heterostructures cover an extensive range $_{45}$

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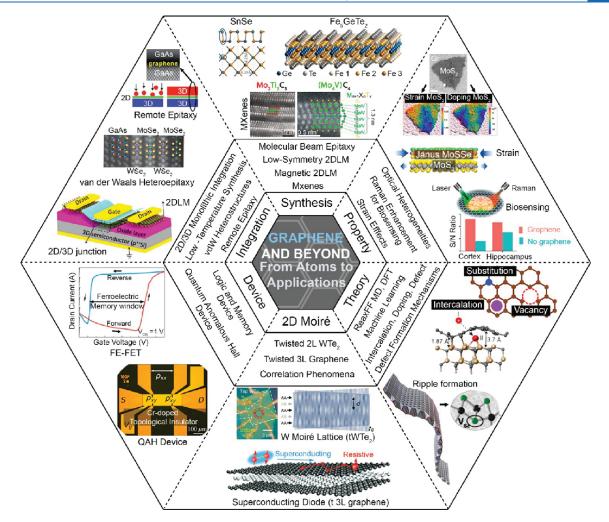


Figure 1. Overview of the scope of this review. We focus on the recent advancements in the field of two-dimensional layered materials (2DLM) learned from the Graphene and Beyond workshop at the Pennsylvania State University in 2022. The topics relevant to 2DLM in this review cover the fields of theory, synthesis and processing, material properties, material Integration, device study, and twisted 2D heterostructures.

46 of properties from metals to semimetals, semiconductors, 47 insulators, and TIs that can be tailored through layer number, 48 surface morphology, strain engineering, heterostructures, and 49 emerging material processing. Besides their pristine form, 50 heterogeneities such as impurities, dopants, structural defects, disorders, and interfaces may be controlled through substitu-51 tional doping and defect engineering to engineer electronic 52 structures, induce magnetization, and trigger quantum phenom-53 ena in host materials.¹⁰ As a result, 2D materials are a rich 54 platform for a broad spectrum of research from theory to next-55 generation (opto)electronics, fundamental physics, sensors, 56 57 energy, and artificial intelligence and machine learning. The 58 substantial interest in this field is reflected in the publication 59 record: The number of publications relevant to 2D materials has 60 increased from merely \approx 1900 in 2004, to \approx 9000 in 2013, and 61 over 49,000 in 2021.^{11,12} As 2D materials science and 62 technology expands with this spectacular pace, it is necessary 63 to connect experts with different disciplines in conferences or 64 workshops frequently to enhance synergy and work together 65 toward a promising future in this field. This review reflects the 66 views of a group of theoretical and experimental experts on 67 advanced 2D materials interdisciplinary efforts as summarized in 68 Figure 1.

Initially, we will discuss the theoretical aspect of 2D materials, 69 including predicting properties introduced by defects and 70 impurities in 2D materials, large-scale computations with 71 reactive force field potentials to understand growth and 72 intercalation mechanisms, and artificial intelligence (AI) and 73 machine learning (ML) in 2D material research. Calculations 74 and theoretical modeling are more important than ever to guide 75 the search for 2D materials useful for energy applications and 76 future devices and to deconvolute complicated growth and 77 processing steps. In subsequent sections focused on material 78 synthesis, we discuss some 2D materials that can be synthesized 79 in large area or quantity, including MXenes prepared by 80 chemical exfoliation of MAX-phase crystals and synthesis and 81 doping of TIs and TMDs using molecular beam epitaxy (MBE) 82 and metalorganic chemical vapor deposition (MOCVD). 83 Additionally, low-symmetry SnS crystals, magnetic Fe, GeTe₃ 84 (n = 3-5) layered materials, magnetically doped TMDs, and 85 utilization of intermediate 2D layers for remote epitaxy are 86 discussed.

Further, we examine 2D material characterization and 88 applications, including optical properties of asymmetric 2D 89 materials, 2D surfaces for biosensing, and strain engineering for 90 tuning their band structures. Thanks to Se-S ion exchange¹³ and 91 confinement heteroepitaxy¹⁴ techniques, structurally asymmet-92

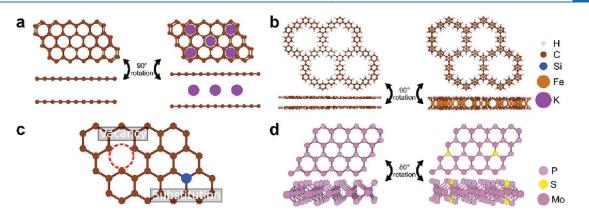


Figure 2. Modeling intercalation, defects, and doping in 2D materials. (a) Bilayer graphene before (left) and after (right) intercalation. The figure includes a top view (top) and a side view (bottom). (b) "All-benzene" 2D-COF before (left) and after (right) intercalation. Intercalated atoms are placed at the centroid of each benzene ring. The figure includes a top view (top) and a side view (bottom). (c) Defective graphene layer showing a vacancy and a silicon substitution. (d) Pristine (left) and S-doped (right) MoP. The figure includes a top view (top) and a triclinic view (bottom).

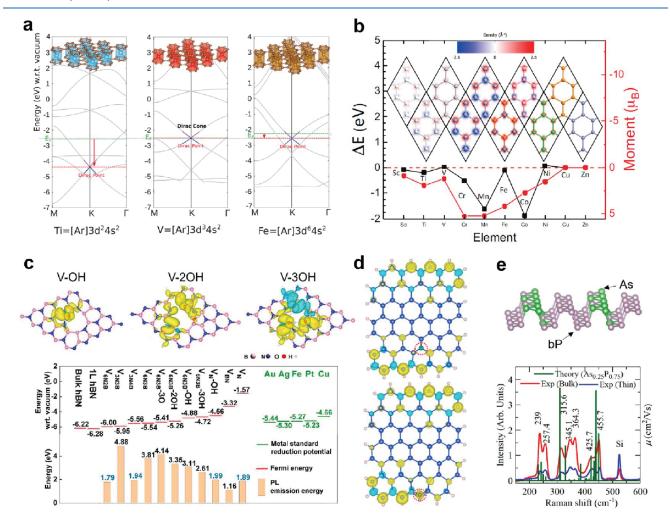


Figure 3. Theory-predicted properties of functionalized 2D materials. (a) The shifted Dirac points of BLG with Ti/V/Fe intercalants relative to pristine BLG with inserted structures. Reproduced with permission from ref 20. Copyright 2018 American Chemical Society. (b) The magnetic moment and energetic ground states of various TM-intercalated BLG. Reproduced with permission under a nonexclusive license to distribute from ref 22. Copyright 2019 arXiv. (c) The spin density of BN with functionalized vacancies, and the shifting Fermi energy of d-BNs with distinct type, size, and functional groups of the vacancies. Reproduced with permission under a Creative Commons CC-BY 4.0 License from ref 34. Copyright 2021 Elsevier. (d) The spin density relies on the position of carbon dopant(s) within MLS. Reproduced with permission from ref 39. Copyright 2020 American Chemical Society. (e) The distribution of As dopants within b-P and its theoretical Raman spectra relative to experimental counterpart. Reproduced with permission from ref 40. Copyright 2019 Royal Society of Chemistry.

93 ric 2D materials, such as Janus monolayers (e.g., SeMoS and 94 SMoSe) and 2D metals (e.g., Ga and In) confined in graphene/ 95 SiC interface, can be realized and studied optically by Raman 96 spectroscopy, optical measurements, second harmonic gener-97 ation, etc. Because of their atomic thickness and high surface-to-98 volume nature, both their phonon and band structure are very 99 sensitive to slight changes in electron doping and strain when 100 they interface with other materials, which serve as the 101 foundation for scalable sensing.

Finally, we summarize efforts on the physics and devices of 102 103 relevant quantum materials grown via MBE and bulk crystal 104 growth. First, we show some of recent progress in mixed-105 dimensional heterostructures, including 2D materials combined 106 with single metal atoms or quantum dots (so-called zero-107 dimensional materials, 0D) into 0D/2D platforms for sensing and electronic doping and hybrid 2D/3D electronic material 108 109 integration for logic and memory devices. Second, we highlight 110 Mn₂Bi₂Te₄—an emerging intrinsic magnetic TI—and its ferro-111 and antiferromagnetic properties. Third, we provide an overview 112 on the quantum anomalous Hall effect in magnetically doped 113 TIs and its metrological applicability without an external 114 magnetic field. Then, we review two emerging 2D homo-115 junctions made of and their unique moiré physics: graphene 116 trilayer with each layer twisted by $\approx 1-2^{\circ}$ and T_{d} -WTe₂ bilayer 117 with each layer twisted by $\approx 5^{\circ}$. Due to the rapid advancement of 118 this field, this review only summarizes the most recent 119 breakthroughs in 2D materials discussed at the 2022 Penn 120 State Graphene and Beyond Workshop. At the end of the review, 121 we provide perspectives and future works. While discussions on 122 earlier works are not provided, they can be found in our prior 123 reviews.^{11,12,15,16}

124 **DISCUSSION**

1. Theory and Computation. 1.1. Modeling Intercala-125 126 tion, Defects, and Doping in 2D Materials. Theoretical 127 calculations are not only tools for designing future materials 128 but also for modifying their properties. In layered compounds, 129 some of the most powerful engineering techniques to tailor 130 material properties—which we will emphasize in this section are intercalation, doping, and defects (Figure 2). In this 131 132 subsection, we will give an overview on computational predictions of intercalation and defect engineering in 2D 133 134 materials, highlighting their potential impact on next-generation technologies by tailoring structural, electronic, optoelectronic, 135 136 magnetic, and catalytic properties.

1.1.1. Intercalation. Monolayer graphene (MLG) possesses 137 138 several attractive material features; however, the lack of property 139 tunability and limited chemical space limits its progress. By 140 contrast, bilayer graphene (BLG), constructed by stacking two MLGs, is an effortless form to drastically expand the electronic 141 142 flexibility of 2D carbon-based systems. Moreover, BLG allows 143 for intercalation as a viable technique to perform material modification (Figure 2a). Unlike doping and adsorption, 144 145 intercalation is the attempt to control material properties via 146 taking advantage of the vdW-regulated space between BLG 147 layers. What is more open-ended, few-layer graphene (FLG) can 148 provide scenarios for investigating staging and cointercalation, 149 especially in the realm of electrodes for energy storage.^{17,18}

Regarding electronic properties, graphene-based materials to decorated with intercalants were found to present a controllable position of Dirac point from the Fermi level.¹⁹ This provided a usa way to discover candidates for various semiconductor technologies such as integrated circuits. Pakhira et al.²⁰ systematically simulated 2D 155 slab and bulk BLG systems intercalated with a series of transition 156 metal (TM) via density functional theory (DFT) calculations. 157 Their calculations predict high thermodynamic stability and 158 Dirac cone tunability in the intercalated systems, as shown in 159 Figure 3a. Since the electrons distributed near the Fermi energy 160 f3 can drastically affect the position of the Dirac point, distinguish-161 ing the electron density around the Fermi level becomes 162 significant. Their results also indicate that the main electron 163 density contributions around the Fermi level derive from the p_z 164 subshell of carbon and 3*d* subshells of intercalated TMs. 165 Controlling the type and concentration of TMs within BLG 166 indeed offers an interesting approach to modulating electric 167 properties. 168

Furthermore, the shift in the chemical potential of graphene 169 caused by atomic intercalants was considered for inducing 170 superconductivity.²¹ The intercalation of alkali and alkaline 171 metals within few-layer graphene (FLG), whose p band 172 crossings at the Fermi energy contribute to superconducting 173 behavior, was well-studied. Inspired by this, Lucht et al.²² 174 implied that the hybridization of d bands deriving from TMs 175 could have a similar mechanism to construct superconductive 176 systems. By comparing established superconducting systems 177 with their theoretical results of first-row TM-intercalated BLG in 178 the aspects of lattice constant and interlayer band energy, they 179 found that Sc, Ti, and V are promising intercalants to promote 180 superconductivity. The d orbital electrons of these intercalants 181 were believed to constrain the interlayer band energies below the 182 Fermi level via the interaction with p orbitals of graphene, 183 inducing superconductive behavior. On the other hand, other 184 TMs with more d orbital electrons did not present super- 185 conductivity, as they alleviated such hybridization by having 186 more paired electrons, enlarging the interlayer distance to an 187 inappropriate level for superconductivity. Other parameters, 188 such as number of layers, concentration of TMs, or even 189 cointercalation, could be starting points for sharpening the 190 mechanism and precise property modulation in graphene and 191 other 2D materials. 192

Moreover, structures that interacted with TMs were proven to 193 display noticeable magnetic properties due to the coupling of 194 their d orbital electrons with graphene.²³ The study by Lucht et 195 al.²² also simulated how the magnetic features of BLG were 196 influenced by several TM-intercalants, further defining their 197 corresponding magnetic ground states. Briefly, in Figure 3b, Cr, 198 Mn, and Co were found to have larger magnetic moments while 199 Cu and Zn have moments approaching zero. These differences 200 in their magnetic moments stem from the number of unpaired 201 electrons. For instance, Zn has fully occupied orbitals, resulting 202 in a lack of d-s p^2 hybridization when interacting with graphene. 203 In addition, among first-row TMs, V and Ni are the only two 204 having ferromagnetic configurations and the remaining first-row 205 TMs are antiferromagnetic. BLG with TM intercalants is, after 206 all, a pioneer in magnetic alteration. 2.07

Another family of materials where TM-intercalation was 208 predicted to yield promising electronic properties is 2D covalent 209 organic frameworks (2D-COFs), which are porous crystalline 210 materials comprised of organic bridging linkers. The structural 211 features of 2D-COFs are shown in Figure 2b. These compounds 212 have become increasingly popular in the past two decades due to 213 their porous architecture, high surface area, and unique 214 tunability.²⁴ These properties have led to various use-cases, 215 including catalysis,²⁵ energy storage,²⁶ molecular sensors,²⁷ and 216 biomedical applications.²⁸ What makes 2D-COFs stand out is 217

218 that their monomers are covalently bonded in a 2D sheet, with 219 almost perfect "eclipsed" stacking due to π - π out-of-plane 220 interactions, generating 1D columns that are ideal for charge and 221 exciton transport.

The electronic properties of 2D-COFs are traditionally 2.2.2 223 modified by changing the organic linkers that make up the 224 layers²⁹ or modifying the length of their chains.³⁰ However, this 225 generally does not solve the main issue for their application as 226 porous electronic materials: e.g., intrinsically low conductivity 227 and charge-carrier mobility. Nevertheless, there is potential to 228 bypass these problems by intercalating the 2D-COF layers with 229 transition metals (see Figure 2b), which yields electronic 230 properties that range from insulating to conducting.^{31,32} Pakhira 231 et al.³¹ showed that the systematic addition of Fe in the centroid 232 of the COF rings produced a drastic change to the Fermi level 233 and band morphology of these structures. For example, they 234 found that a pure triazine-benzene-boroxine COF's insulating 235 behavior (2.6 eV indirect band gap) is modified to a 236 semiconductor (1.18 eV direct band gap) with the addition of 237 Fe atoms at the centroid of all rings in the unit cell. Furthermore, 238 the band structures show a reversal in the conduction band 239 curvature and a change in the relative position of the Fermi level. 240 Intercalated 2D-COF architectures presented band gaps as small 241 as ≈ 0.3 eV and as large as ≈ 2.6 eV, with several intermediate 242 values. In addition, through vibrational analysis, these materials 243 were also predicted to be thermodynamically stable. Their 244 excellent electronic tunability and dynamic stability present an 245 interesting opportunity to use layered COFs as nanoporous 246 electronics and optoelectronics.

Intercalation can also be used to achieve higher reactivity 247 248 during catalysis. One reaction of great interest is "water splitting" 249 (also known as oxygen evolution reaction). Carrying out this 250 reaction efficiently could decrease the current cost of hydrogen 251 for fuel cells, attacking one of society's current issues: clean-252 energy production. A promising 2D material that stands out for 253 this application is birnessite: a layered, ion-intercalated 254 manganese oxide. Birnessite acts by mimicking plant's photo-255 system II. This natural system captures solar energy to oxidize 256 water, a reaction that occurs in the Oxygen Evolution Center: a 257 cubane-like structure comprised of Mn₄O₈Ca. Birnessite has a 258 similar structure, composed of ion-intercalated MnO₂ tetrahe-259 dra. Birnessite intercalated with different cations was theoret-260 ically studied by Lucht et al.³³ who discovered that Sr, Ca, B and 261 Al-intercalated birnessites have valence bands with a band 262 alignment suitable for water splitting. In addition to its water-263 splitting capabilities, bulk birnessite intercalated with boron has 264 a direct band gap of about 2 eV, which has suitable properties for 265 light-capture. An analysis of monolayer birnessite further 266 revealed that Mg and Sr-intercalations present an indirect-to-²⁶⁷ direct band gap transition when reducing the bulk to a slab, with 268 direct band gap energies of 2.19 and 2.69 eV, respectively, which 269 are also suitable for light capture. The theoretically predicted 270 band alignments and band gaps for birnessite predict its ability 271 to perform both oxygen evolution and light capture simulta-272 neously, which could lead to materials that can carry out 273 photocatalytically activated oxygen evolution, comprising a step 274 toward achieving artificial photosynthesis.

1.1.2. Defects. Defects are generally seen as undesired, as it is usually difficult to control and predict their effect on materials' properties. However, for 2D materials, defects such as vacancies, dopants, and substitutions are effective methods to alter and fine-tune materials' properties. Vacancies, in particular, can usual induce an electric potential that reshapes the electron

distribution, and further changes the materials' electric and 281 chemical properties (Figure 2c). For example, Lei et al.³⁴ 282 activated chemically inert BN via the decoration of vacancies, 283 which could be applied to the reduction of metal cations for the 284 hydrogen evolution reaction (HER). Based on their DFT 285 calculation, a high spin density, which can represent unpaired 286 electrons or free radicals, was surrounding the vacancies; this 287 indicates vacancy-induced reactivity. Most interestingly, the 288 Fermi energy level of defective-BN (d-BN) could be finely 289 shifted from -6.28 to -1.57 eV by controlling the type, size, and 290 functional groups (functionalization) of the vacancies as shown 291 in Figure 3c. Overall, localized free radicals and a tunable band 292 alignment could aim to achieve several metal reductions (Fe, Cu, 293 Au, Ag, and Pt) with different redox potentials. Aside from d- 294 BN, other defective 2D materials that have been predicted as 295 excellent electrocatalysts for hydrogen evolution include MoS₂ 296 with S vacancies, 35 PtSe₂ with Pd/Pt substitutions, 36 and 297 MoSi₂N₄ with nitrogen vacancies. 37 All these examples require 298 defects to boost their electrochemical activity for hydrogen 299 evolution, making defects essential to engineer properties of 2D 300 materials.

On the other hand, doping is the introduction of a small 302 amount of impurities into a material. Doping is well-known for 303 aiding in the design of field-effect transistors (FETs), as it can 304 help calibrate 2D materials' electric features, such as electronic 305 transport, with dilute concentrations of dopants.³⁸ Recent 306 studies showed that 2D materials' properties affected by the 307 introduction of dopants were not only dependent upon the 308 concentration of dopants (which had been widely studied in the 309 past), but also on the atomic position of impurities in the 310 structure. A first-principle study³⁹ in 2020 defined how the 311 structures and properties including band gap, formation energy, 312 and magnetism were influenced by the position of carbon 313 dopant(s) within monolayer Si (MLS), as shown in Figure 3d. 314 Silicon-carbon substitution at the edge sites was found to be 315 more energetically preferable, interestingly, these substitutions 316 generated high neighboring spin density around the doping site. 317 Also, the authors found that reducing the distance between two 318 dopants leads to a more distorted and unstable geometry of 319 carbon-doped MLS. More significantly, they concluded that if a 320 doping site breaks the symmetry of the whole structure more, 321 more band degeneracies can be broken, inducing a larger band 322 gap. Apart from the substitution site of a dopant, its distribution 323 can determine advanced features for electronics as well. For 324 instance, Pradhan et al.⁴⁰ unveiled a certain distribution of As 325 dopants within black phosphorus (b-P) that could contribute to 326 not only an appropriate band gap for FETs, but also an 327 anisotropic fast carrier mobility, which can range from 300 to 328 600 cm^2 V⁻¹ s⁻¹. In order to define such As dopant 329 arrangements, they took advantage of theoretical techniques 330 to compute the Raman spectra of designed models, and find the 331 structure that agreed with their experimental Raman results, as 332 shown in Figure 3e. To some degree, the clustering of As atoms 333 is more stable and presents an anisotropic transport property 334 that is gate-voltage dependent for 25% arsenic doped b-P. 335 Finally, another doped 2D material that has shown promising 336 properties is S-doped MoP (Figure 2d). Through theoretical 337 and experimental results, it was found that the addition of S 338 atoms in MoP leads to a smaller band gap (0.67 eV in S-doped 339 MoP compared to 2.18 and 2.07 eV for pure MoS₂ and MoP, 340 respectively), and high electron mobility near the Fermi level 341 due to rectification of electron accumulation at the conduction 342 and valence bands.⁴¹ These properties are highly favorable for 343

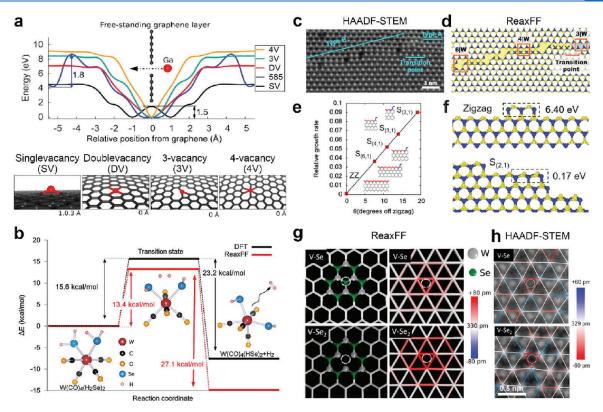


Figure 4. Examples of ReaxFF applications to 2D materials. (a) Ga diffusion through a free-standing defective graphene. The graph shows a potential energy barrier for Ga diffusion into defective graphene sites: SV, DV, 5-8-5, 3 and 4 V at 0 Å. Ga diffusion realizes from right to left in the graph The images at the bottoms show the most stable Ga adsorption on SV at 1.03 Å, DV at 0 Å, 3 V at 0 Å, and 4 V model at 0 Å, respectively. Adapted with permission from ref 46. Copyright 2022 Elsevier. (b) ReaxFF and DFT predicted reaction pathway for hydrogen release from the $W(CO)_4(H_2Se)_2$ molecule. Adapted with permission from ref 43. Copyright 2019 Elsevier. (c) ADF-STEM image showing type A and B GBs, as well as the transition point between them. (d) ReaxFF MD simulation equilibrated at 300 K of the structure shown in (c). (e) Computed relative growth rate of the slanted edge structures with respect to the sulfur-terminated zigzag (ZZ) edge as a function of slanted angle, θ . S(2,1), S(3,1), S(4,1), and S(6,1) are the slanted edges characterized by the translational vector (n, 1) of the 2H-WS₂ lattice, where n is the number of the zigzag units along the a1 direction, and a 2-component vector contains only one zigzag unit in the GB of interest (f) Illustrations of the formation energy for adding atoms (enclosed in the dashed rectangular boxes) onto the reference sulfur terminated ZZ and S(2,1) slanted edges, respectively. Adapted with permission from ref 51. Copyright 2021 American Chemical Society. (g) Ball-stick representations and W–W bond displacement maps of V-Se and V-Se₂ point defects based on ReaxFF methods. (h) HAADF-STEM images with overlaid maps of the distances between neighboring W atoms of V-Se and V-Se₂. In (g_1 h) The vacancies are marked by dotted white circles. Adapted with permission from ref 44. Copyright 2020 American Chemical Society.

344 hydrogen evolution catalysis. Cluster model computations also 345 elucidate the amount of dopant with the best catalytic activity. In 346 particular, the authors found that a small percentage of S dopant 347 (5% S) in MoP leads to a more favorable HER rate-limiting 348 (Volmer) step during the reaction, compared to 10% S-doped 349 MoP, pure MoS₂, and pure MoP.

1.2. High-Speed and Large-Scale Modeling for 2D 350 351 Materials Based on ReaxFF. Understanding the effect of 352 operating conditions such as temperature, pressure, flow rate, and gas-composition on 2D material growth kinetics is 353 challenging. Modeling and simulation can improve the atomic-354 level understanding of the morphology and characteristics of a 355 resultant structure and thus enhance the ability for better control 356 of the complex growth process of 2D materials. The ReaxFF 357 reactive force field, originally developed by van Duin et al.,⁴² is a computationally efficient means that captures the covalent bond 359 360 breaking and reforming by updating the bond order at each molecular dynamic iteration, in contrast to nonreactive 361 362 potentials. Therefore, ReaxFF molecular dynamics (MD) 363 simulations are highly effective in capturing detailed chemical 364 events, reaction pathways, and product formation during gas-365 phase and gas/condensed phase simulations, for systems up to

 $\approx 10^6$ atoms and for time scales not accessible to first-principles 366 based techniques. This ReaxFF potential can simulate the 367 nucleation and growth and intercalation of 2D materials, which 368 involves both gas-phase and surface interactions, as a function of 369 local chemical environment, helping in predicting effective 370 growth protocol.⁴³⁻⁴⁶ It features vdW interactions which 371 particularly enables the simulation of multilayer vdW hetero- 372 and homostructures.^{44,46} Additionally, ReaxFF provides ther- 373 modynamic and kinetic insight into fundamental solid-phase 374 phenomena observed in 2D materials such as atomic 375 intercalation, grain boundary (GB), defect formation and 376 diffusion, stress induced lattice distortions, morphological 377 evolution of 2D domains as a function of local chemical 378 environment during the growth. Also, ReaxFF differs from the 379 so-called "first generation" reactive force fields such as 380 Tersoff^{47,48} and Brenner⁴⁹ by applying a significantly longer- ₃₈₁ ranged bond-order relationship, which makes it possible to 382 achieve accurate reaction kinetics. The ReaxFF framework has 383 been successfully applied to a wide range of 2D systems⁵⁰⁻⁵² and 384 their defect formation, growth mechanisms and character- 385 ization, as shown in the following examples. 386

1.2.1. Kinetics of Ga Intercalation through Graphene. 387 388 Nayir et al.^{46,52} used a combination of ReaxFF- and DFT-based 389 simulations to study defects in graphene, which can act as 390 pathways for Ga intercalation into the interface between 391 graphene and SiC. The results show that the sizes of vacancy 392 defects ranging from single carbon vacancy (SV) to multiple 393 carbon vacancy (3 and 4 V) can affect the thermodynamic and 394 kinetic preference of intercalant between the adsorption on 395 graphene surface or the intercalation at the interface. For 396 example, the diffusion of a relatively large Ga atom through small 397 sized defects (<3 V) is kinetically hindered, where Ga 398 encounters a kinetic barrier. However, the potential energy of 399 the system monotonically decreases as Ga approaches to 400 graphene with larger sized defects (>double vacancy, DV) and 401 the diffusion through graphene layer is nearly barrierless (Figure 402 4a). This suggests that defect engineering provides an effective 403 way to lower the temperature required for intercalation, by 404 consequence, energy savings and cost reduction during 2D 405 material intercalation.

1.2.2. MOCVD Growth of WSe₂. A combination of ReaxFF-406 407 and DFT-based chemical kinetic models developed by Xuan et 408 al.⁴³ provides a fundamental insight into kinetic properties of 409 elementary reaction pathways leading to the WSe₂ formation 410 from $W(CO)_6$ and H_2Se precursors. During MOCVD at 411 elevated temperatures, CO ligands will dissociate from $W(CO)_6$ 412 and H₂Se will rapidly fill in the ensuing vacancies in W-carbonyl, 413 resulting in intermediate $W(CO)_x(H_2Se)_y$ molecules. Contin-414 uous H₂ release from the WCO_x(H₂Se)_y is a key event that could 415 determine the growth rate of 2D WSe₂. The model in Figure 4b 416 shows that H₂ release from $W(CO)_4(H_2Se)_2$ with a kinetic 417 energy barrier of 13.4 kcal/mol at the ReaxFF results in a more 418 stable product, $W(CO)_4(HSe)_2$. The reverse reaction may also 419 occur, as pure H₂ environment is used in the process. However, 420 for $W(CO)_4(HSe)_2+H_2 \rightarrow W(CO)_4(H_2Se)_2$, the barrier for the 421 reverse reaction is higher, 27.1 kcal/mol in ReaxFF. Based on 422 simulations, these reactions are generally exothermic with a 423 lower activation energy than their reverse reactions, indicating 424 that H₂ release is thermodynamically favorable. After all H₂ and 425 CO ligands are released from the intermediate molecules, stable 426 2D WSe₂ films can grow on substrates.

1.2.3. Grain Boundary and Defects in 2D TMDs. Hickey et 427 428 al.⁵¹ uncovered invisible translational defect arrays in nearly 429 single-orientation, coalesced monolayer WS₂ films with high-430 angle annular dark field (HAADF) scanning transmission 431 electron microscopy (STEM) imaging and used ReaxFF MD 432 simulations at 300 K to create the same irregular translational 433 GB (Figure 4c,d). There are two types of GBs: one has vacancy 434 line defects, and the other adopts a rectangular arrangement of 435 W atoms, 4IW, at the boundary and is stabilized by 6IW rings that 436 cause steps in the GB. The latter is comprised of the slanted $_{437}$ edges with angles within the range of 0 to 30° , deviated from the 438 zigzag edge. The ReaxFF MD calculations show that the kink 439 concentration significantly affects the stability of slanted edges as 440 shown in Figure 4e,f where the growth rate is linearly correlated to the kink concentration. In a Sulfur-rich environment, given 441 442 the high-cost energy required for the first nucleus formation, the 443 most stable ZZ structure, whose edge atoms are passivated by 444 Sulfur atoms, is the slowest to grow while the slanted edge with a 445 highest kink concentration is expected to grow fastest. The 446 analysis in the aforementioned work indicates that growth of the 447 S-ZZ edge requires a long time to complete its linear formation. 448 Therefore, even though the slanted edges are less stable edge 449 structures and should disappear quickly during the growth

process according to the growth conditions, shorter growth time 450 or slower flow rate of the gas-phase precursors, most likely, may 451 not allow flakes to complete their zigzag linear formation, thus, 452 grains with the slanted edges may survive during the growth to 453 meet at the GB. 454

The ReaxFF reactive potential was used to simulate point 455 defects in a 2D WSe₂ to study their influence on local strain. 456 Figure 4g presents the atomic configurations and the ReaxFF- 457 based bond displacement maps of single Se vacancy (V_{Se}) and 458 double Se vacancy (V_{Se2}) in WSe₂. The loss of Se of two defect 459 types drives bond contraction between adjacent W atoms and 460 reduces W–W distances by about 15 and 24%, respectively, as 461 the unsaturated W atoms marked by red triangles radially 462 contract toward the chalcogen vacancies in the maps. These 463 strain effects are consistent with STEM imaging, which shows 464 that the distances between three W atoms adjacent to the V_{Se} 465 and V_{Se2} are contracted by approximately 10 and 18%, 466 respectively, in good agreement with the ReaxFF results.

1.3. Artificial Intelligence and Machine Learning in 2D 468 Materials Research. In recent years, exploiting artificial 469 intelligence (AI), machine learning (ML), data mining, and 470 other data-driven approaches has steadily grown its presence in 471 various aspects of 2D materials research. With traditional 472 materials development commonly taking 1-2 decades to 473 develop from conception to completion,⁵³ a different approach 474 for the creation of 2D materials research needed to be 475 considered to reduce research time. On the one hand, the 476 Materials Genome Initiative has provided a strong impetus for 477 creating databases and screening methods for materials with 478 specific functionalities. On the other hand, rapid progresses in 479 Industry 4.0 provides matured methods for instruments and 480 data-science to meld seamlessly to streamline manufacturing 481 and other complex industrial processes. Given the advent of 482 easy-to-use ML tools,⁵⁴ these emerging statistical approaches 483 have been utilized to speed up material development 484 processes-even reducing some experimental optimizations 485 down to just 8 h.55 We next describe recent developments in 486 various aspects of 2D materials research where applications of 487 ML can accelerate and/or enable scientific and technological 488 advances.

1.3.1. Machine Learning in 2D Material Theory. With the 490 availability of high-performance computing, data mining, 491 pattern recognition, and other search algorithms are being 492 used frequently to computationally "discover" materials, 493 including 2D materials. These theoretical works in 2D materials 494 have led to collaborative efforts to provide shareable DFT 495 information using databases.⁵⁶ More importantly, such share- 496 able resources have led to a standardization of processes for the 497 community-effectively establishing generally accepted struc- 498 tures of data. These standardized data structures allow for the 499 sharing of data across many different platforms in DFT, which is 500 conducive to the integration of ML algorithms. Applying the 501 data from these databases, many groups have effectively utilized 502 ML to predict physical properties of a lattice structure,⁵⁷ 503 replicated electron scattering in a DFT+U model,⁵⁸ and even 504 exploited crystal graph convolutional neural networks to study 505 nearly 45,000 2D structures to discover compositions suitable 506 for photovoltaics.⁵⁹ Advancing this field forward, Suzuki et al.⁶⁰ 507 have developed methods for achieving machine-learned 508 exchange correlation (XC) functionals for time-dependent 509 DFT (TD-DFT) calculations using neural networks. Given 510 that XC inaccuracies have been a consistent issue in DFT, XC 511 functionals derived from experimental data and fit through ML 512

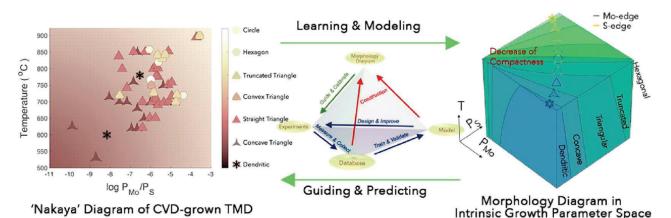


Figure 5. Proposed ML framework for understanding the correlation between the ratio of precursors in this case partial pressure of Mo versus S sources in a CVD reactor, and the resulting shape of the grown crystal. Reproduced with permission from ref 80. Copyright 2020 Elsevier.

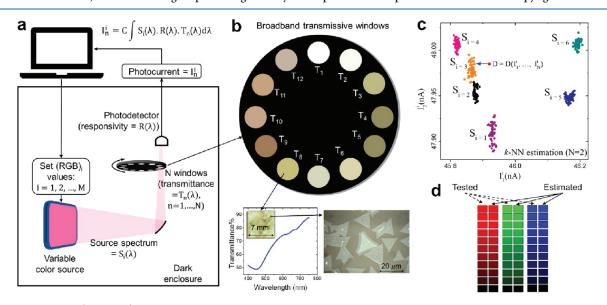


Figure 6. Artificial eye (or, A-Eye), an instrument that uses a nondispersive method for achieving accurate classification, reproduction, and spectral estimation of color by exploiting engineered variations in optical transmittances of 2D materials. (a) Schematics of data collection system in dark enclosure. The RGB colors are generated via a python code on a screen, the generated lights are allowed to pass through a set of transmissive windows, one at a time; then the transmitted lights are collected by the single photodetector. The signals are collected with the same computer. The measured photocurrent is related to the generated incident spectrum, the transmittance of the window, and the responsivity of the photodetector, via the given formulas. (b) Transmissive windows mounted on a disk (top). Transmittance curve and real-size optical image of one of a typical transmissive window made of CVD-grown TMDs, as well as microscopic image from a segment of this transmissive window (bottom). (c) Application of *k*-nearest neighbor (*k*-NN) method with k = 1, where only two transmissive windows (n = 1, 2 out of N) and five groups of data ($S_{i=1-5}$) are shown. For each *i*, an N-dimensional data point $S_i = S_i(I_{1j}^i, I_{2j}^i, ..., I_N^i)$ for RGB₁ is generated and stored. The data points with similar colors group together in the training set. Here, $S_i = 3$ is the nearest neighbor class for the test sample $D = D(I_{1j}^i, I_{2j}^i, ..., I_N^i)$. (d) A small set of tested single colors, red, green, and blue (left columns in each column pair), with their corresponding estimated colors (right columns in each column pair), using the methods outlined in panels (a)–(c). Adapted and modified with permission from ref 81. Copyright 2022 Elsevier.

s13 algorithms stand to serve the long-standing issue of unders14 standing unknown systems, potentially without the need for s15 energy convergence, drastically reducing computational time s16 while increasing accuracy of simulations. In keeping with the s17 recent progress with magic-angle moiré superlattice engineering, s18 ML approaches are being blended with theory and computas19 tional approaches to achieve high-throughput searches of s20 multiply stacked, multiangle 2D materials with specific, desired s21 properties.⁶¹ With increasing computing powers, more difficult s22 and also more accurate calculations of functionalities will s23 become achievable, thanks to the growing collaboration s24 between computational physicists and data scientists. 1.3.2. Machine Learning in 2D Material Synthesis. Utilizing 525 ML in the synthesis of 2D materials may not only be considered 526 useful but also a requirement for future discoveries. Predictable 527 synthesis of 2D materials depends on precise control over a 528 combination of experimental parameters. In micromechanical 529 exfoliation techniques, 2D flakes (e.g., graphene) are usually 530 transferred onto a flat substrate from a bulk crystal (like 531 graphite). In this case, the shape and size of both the bulk source 532 and the transferred 2D layer are random. This randomness 533 makes developing/training machine-learning algorithms that 534 could assist fabrication of identical 2D layers a considerable 535 challenge. In this case, ML approaches are more useful for 536

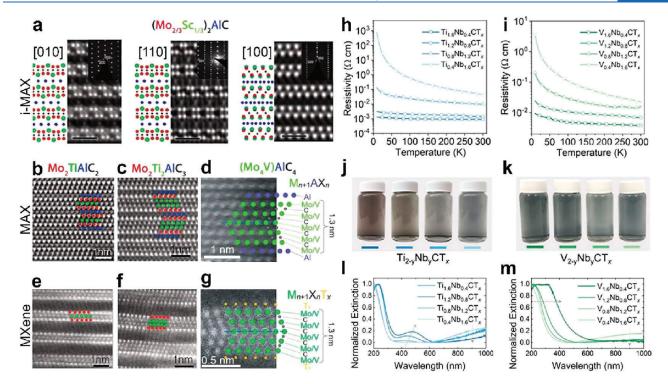


Figure 7. Structures and properties of MXenes. (a) High-resolution scanning transmission electron microscopy (HRSTEM) and corresponding selected area electron diffraction (SAED) patterns of $(Mo_{2/3}Sc_{1/3})_2AIC$ i-MAX phase along the [010], [110], and [100] crystal orientation, together with schematics based on a monoclinic C2/*c* symmetry. The red, green, blue, and black spheres in the schematics are Mo, Sc, Al, and C, respectively. (b) HRSTEM of Mo₂TiAlC₂, (c) Mo₂Ti₂AlC₃, and (d) Mo₄VAIC₄ MAX phases. STEM images of (e) Mo₂TiC₂T_x, (f) Mo₂Ti₂C₃T_x, and (g) Mo₄VC₄T_x MXenes. For the panels (b, c, e, f), the blue, red, and green spheres represent Al, Mo, and Ti, respectively. For the panels (d, g), the green, blue and orange spheres represent Mo/V, Al and surface terminations T_x. Images in (d) and (g) demonstrate a herringbone-type structure with an atomic schematic and mirror plane shown by solid circles on the right and a dashed line, respectively. Reproduced (adapted) with permission from ref 97. Copyright 2021 Elsevier. (h, i) The temperature dependent electrical properties of (h) Ti_{2-y}Nb_yCT_x and (i) $V_{2-y}Nb_yCT_x$. (j, k) The optical properties of solid-solution (j) Ti_{2-y}Nb_yCT_x and (k) $V_{2-y}Nb_yCT_x$ colloidal solutions in deionized water. In all three systems, the gradual change in color resulting from the different stoichiometries can be observed. (l, m) The quantitative UV-vis spectra normalized to a maximum extinction of 1 of the (l) Ti_{2-y}Nb_yCT_x and (m) $V_{2-y}Nb_yCT_x$ systems. For all systems, multiple features are visible with a nonlinear shift in the absorbance with changes in the composition. Reproduced (adapted) with permission from ref 96. Copyright 2020 American Chemical Society.

537 automated searching specific candidates in from a dense 538 ensemble of mixed-thickness flakes. For example, masked convolutional neural networks techniques applied to optical 539 microscopy images can provide high-probability identification of 540 various monolayer flakes (e.g., graphene, hBN, MoS₂, and 541 WTe₂) from a collection of flakes of various thicknesses 542 exfoliated onto a flat SiO₂/Si substrate.⁶² In contrast, chemical 543 544 vapor deposition (CVD), MOCVD, plasma-enhanced CVD, 545 MBE, sputtering or other reactor-based synthesis of 2D 546 materials can have a larger range of controllable parameters in 547 their 2D crystal growth recipes (e.g., temperature, pressure, flow rate of carrier and reactant gases, ramp-rates, and several other 548 design of experimental or DoE parameters). Here, trial-and-549 error approaches to optimize the DoE parameters for a specific 550 type of outcome (i.e., crystal quality, yield, reproducibility, or 551 large-area coverage, etc.) for each type of reactor can be daunting. Traditional DoE methods, $^{63-65}$ even with Latin-552 553 hypercube sampling (LHS),⁶⁶ require a large input of samples to 554 be useful. Because of this, Bayesian Optimization $(BO)^{67-71}$ 555 with Gaussian Processes (GP) tends to be the preferred method 556 557 of experimental optimization of materials due to its ability to 558 work with smaller sample sizes. While this technique has yielded 559 promising results from previous research, 72-77 a shortfall of this 560 approach is the computational requirements associated with it. A

computational training cost of $O(N^3)$ with BO of GP⁷⁸ is not 561 technically very challenging but it would be preferable to have a 562 training cost of O(N) for lower budget research groups, which 563 will require a creative shift from BO to simpler feedforward 564 Neural Networks (NN).⁷⁹ Since NNs typically require large data 565 sets for training, one approach could be to simplify the problem 566 into smaller subsets of problems. For example, the objective of 567 one subset could be to find correlations between the ratio of 568 precursor material P_x/P_y to the resulting shape of the flakes, i.e., 569 triangular, polygonal, or dendritic, as was suggested in a recent 570 perspective on 2D materials,⁸⁰ with the idea articulated in Figure 571 fs 5. A second subset of machine-learning guided experiments 572 f5 could then aim to find correlations between the DoE parameters 573 (precursor quantity, temperature, flow rate, ramp-rate, growth 574 duration, etc.), and the resulting *in situ* conditions of P_x/P_y at the 575 growth surface. Finally, a third set of ML-guided experiments 576 will then need to find correlations between shapes of seed 577 crystals versus their propensity for eventually growing into large- 578 area, uniform, and/or high-quality 2D layers on a given 579 substrate, depending on the required target outcome. A 580 combination of these three kinds of ML-guided experiments is 581 likely going to help provide the best correlation between DoE 582 parameters and final 2D material outcomes. 583

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1.3.3. Machine Learning Used with 2D Materials. In 584 585 contrast to utilizing ML to discover 2D materials, 2D materials 586 have recently been used in conjunction with, and even as, ML 587 algorithms. It has been shown recently that the optical 588 transmittance of TMDs can be exploited to allow for accurate 589 light source color identification by training an ML model to 590 identify wavelengths based off measurements from the single-591 cell silicon photodetector with an accuracy of 99%—effectively 592 drastically reducing the cost of accurate color identification 593 systems⁸¹ (Figure 6). Given that most modern cameras utilize 594 Bayer filters over complementary metal-oxide-semiconductor 595 (CMOS) sensors, it takes four Si photodiodes to measure the 596 color of a single pixel in a modern camera. It is then feasible to 597 presume that using this ML technique with TMDs filters could 598 possibly reduce camera sensor surface area by one-quarter, while 599 retaining similar light intensity response and color accuracy. In 600 recent years, many researchers have also shown the viability of 601 using 2D materials themselves to develop hardware-based 602 neuromorphic systems.⁸² Mennel et al.⁸³ even developed an 603 Artificial Neural Network (ANN) for identifying images-604 allowing for low-power training cost and ultrafast analysis-605 boasting some computations as fast as 50 ns. According to 606 Mennel, this time is only limited due to the onboard clock. 607 Given these emerging technologies, the future of ML for 2D 608 material development may, intriguingly, be done so by 2D 609 materials.

2. Synthesis and Processing. 2.1. MXenes with Multiple 610 611 M-Elements: Composition-Structure-Property Relation-612 ships. MXenes are an emergent, and potentially the largest, 613 class of 2D materials discovered to date.⁸⁴ This class of transition 614 metal carbides, nitrides, and carbonitrides has the general 615 formula $M_{n+1}X_nT_x$ where M is an early transition metal (Ti, V, 616 Nb, Ta, etc.), X is C and/or N, T_x represents the surface ⁶¹⁷ functional groups (typically O, OH, F, and Cl), and n = 1-4.⁸ 618 MXenes are produced by a top-down synthesis approach where 619 M_{n+1}AX_n (MAX;⁸⁶ A is typically Al, but can be Si or Ga) phase 620 precursors are selectively etched via wet HF-containing 621 mixtures,⁸⁷ molten salt,⁸⁸ halogenation,⁸⁹ and others.⁹⁰ MXenes 622 have been widely studied due to their desirable properties, such 623 as hydrophilicity (soluble in water with no additives or 624 surfactants),⁹¹ ease of processing (able to be used in any 625 conventional water-based route, e.g., spray coating, dip coating, ⁶²⁶ vacuum filtration),⁹¹ scalability (no change in properties as ⁶²⁷ batch size is increased),^{92,93} and desirable optical (tunable 628 plasmon resonance, optical response in visible region, electro-629 chromic nature),^{94–96} electrical (>20,000 S/cm conductivity, 630 metallic-like response to cryogenic temperatures, magnetic 631 transitions),^{94,96,97} and mechanical properties (around 0.4 TPa 632 Young's modulus from solution processed materials).^{97,98} Due 633 to these properties, MXenes have found widespread use in a 634 variety of fields, including electrochemical energy storage,99 635 electromagnetic interference shielding,¹⁰⁰ medicine,^{101,102} en-636 vironmental remediation, ^{103,104} additives to composites, 637 etc.^{105,106} To date, more than 30 stoichiometric MXenes have 638 been discovered, in addition to a theoretical infinite number of 639 solid-solution MXenes. In addition to single-M MXenes, there 640 are broadly three classes of multi-M MXenes: i-MXenes (in-641 plane ordered divacancy MXenes; Figure 7a), ordered double 642 transition metal MXenes (out-of-plane ordered MXenes; Figure 643 7b,c,e,f), and solid-solution MXenes (Figure 7d,g).

structures occur due to the difference in atomic size between M' 647 and M". The most common i-MAX phases are 648 $(Mo_{2/3}Sc_{1/3})_2AlC$ (Figure 4a)¹⁰⁷ or $(Mo_{2/3}Y_{1/3})_2AlC$,¹⁰⁸ but 649 there a number of others have also been produced.^{109,110} These 650 materials, when etched, can lead to two different structures, 651 either $(Mo_{2/3}Sc_{1/3})_2CT_x$ or $Mo_{4/3}CT_x$, depending on the 652 etchant time and concentration.¹¹¹ This leads to a benefit, 653 where the effect of controlled defects in MXenes can be studied. 654 The i-MXenes have positive and negative properties-due to 655 the highly defective nature, these MXenes tend to be more 656 chemically active, especially for catalysis.¹¹⁰ However, due to 657 their defective nature, they also tend to be less stable.¹¹² For 658 example, $Mo_{4/3}CT_x$ has a volumetric (gravimetric) capacitance 659 of 1153 F cm⁻³ (339 F g⁻¹),¹⁰⁷ which is $\approx 65\%$ higher than 660Mo₂CT_x. Further studies have shown that the enhanced 661 capacitance and energy density of Mo4/3CTx comes at the 662 expense of lower stability and a faster discharge rate.¹¹³

2.1.2. Out-of-Plane Ordered MXenes. Out-of-plane ordered 664 MXenes have two elements that do not intermix in the M layers 665 (Figure 7b,c,e,f), such as $Mo_2Ti_2C_3T_x$, $Mo_2TiC_2T_x$, 666 $Mo_2ScC_2T_{x'}^{114}$ or $Cr_2TiC_2T_{x'}^{4}$ For these, the Cr (or Mo) is 667 on the outer layer with Ti (or Sc) on the inner layer. These 668 MXenes are beneficial because they offer unique chemistries that 669 cannot be easily attained in single-M MXenes.^{115,116} Moreover, 670 it was shown that the inner layer affects the electronic properties 671 of the outer layer transition metal.¹¹⁷ This class of MXenes also 672 has different properties than single-M MXenes, such as modified 673 plasmon resonance.⁹⁵ $Mo_2TiC_2T_x$ has a transverse surface 674 plasmon resonance at 476 nm, whereas $Ti_3C_2T_r$ is at 780 nm. 675 Based on this, $Mo_2TiC_2T_x$ should have a higher free electron 676 density, but experimentally this has not been confirmed, 677 electrical conductivity points to the opposite (≈ 1500 S/cm for 678 $Mo_2TiC_2T_x$ against >20,000 S/cm for $Ti_3C_2T_x$),¹¹⁸ $Cr_2TiC_2T_x$ 679 was also shown to be unique among MXenes; it is the only 680 MXene that was experimentally shown to have a magnetic 681 transition resulting from the MXene itself.¹¹⁶

2.1.3. Solid-Solution MXenes. Solid-solution MXenes have 683 uniform, random mixing of the two M elements within their 684 entire structure (Figure 7d,g). There have been a number of 685 solid-solution MXenes synthesized already, including 686 $Ti_{2-y}Nb_yT_{x}^{96}Nb_{2-y}V_yT_{x}^{96}Ti_{2-y}V_yT_{x}^{96}Ti_{3-y}Ta_yTa_{x}^{119}$ $Mo_{4-y}V_yT_{x}^{120}Nb_{4-y}Zr_yT_{x}^{121}Nb_{4-y}Ti_yT_{x}^{121}$ and 688 $Mo_4VC_4T_{x}^{85}$ it is noteworthy that this class of MXenes is the 689 only one that spans n = 1-4 to date. This is noteworthy: for 690 MXenes, the only case where n = 4 observed to date was a solid- 691 solution MXene, Mo₄VC₄T_x.⁸⁵ This MXene is stable only at a 692 narrow compositional range, a variance of 5% in either direction 693 of the M element causes impurity MAX phases to form. It also 694 has a structure unlike other MAX/MXene—it is twinned at the 695 middle M-site, a structural motif that has never been observed 696 before. Moreover, in terms of properties it is also exceptional, it 697 has a higher thermal stability than any other MXene, is resistant 698 to the electron-withdrawing effect of organic intercalants, and 699 has low optical absorbance over the entire studied range (out to 700 near-infrared).85 701

In solid-solution MXenes, some properties appear to be 702 linearly related to the chemistry, while others are nonlinear. The 703 conductivity is one property that monotonically varies with the 704 chemistry. Typically, Nb₂CT_r has a low conductivity (≈ 25 S/ 705 cm), while V₂CT_x and Ti₂CT_x are substantially higher (>1000 706 S/cm).^{95,122,123} As the Nb content in Ti_{2-y}Nb_yCT_x and 707 $V_{2-y}Nb_yCT_x$ increases, the conductivity correspondingly 708 decreases (Figure 7h,i).^{96,123} This trend continues over the 709

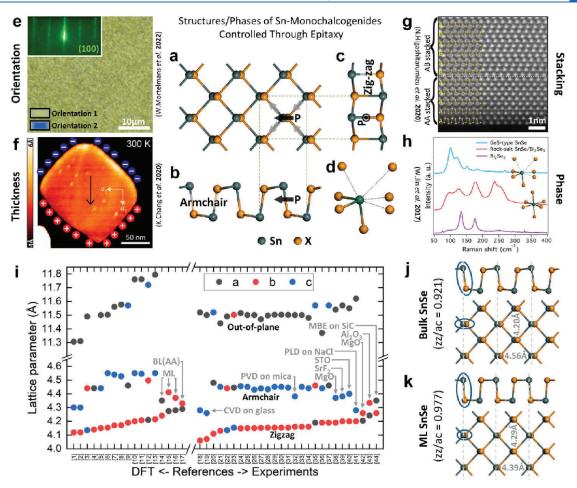


Figure 8. Controlling the structure and phase of Sn monochalcogenides through epitaxy. (a) Top view showing the in-plane unit cell in dashed lines, orientation of the polar bonds, and the net in-plane polarization within a single sheet. (b, c) Visualizing the in-plane armchair and zigzag directions. (d) The SnSe₇ coordination polyhedron. Reproduced with permission from ref 134. Copyright 2022 American Chemical Society. (e–h) Demonstrations of structure and phase control through epitaxy: (e) eliminating twin domains. Reproduced with permission from ref 134. Copyright 2022 American Chemical Society. (f) realizing ferroelectricity in monolayers. Reproduced with permission from ref 135. Copyright 2020 American Chemical Society. (g) making a multilayer, polar crystal with metastable layer stacking. Reproduced with permission under a Creative Commons CC-BY 4.0 License from ref 136. Copyright 2020 Springer Nature. (h) Making a topological crystalline insulator by stabilizing the rock-salt phase. Reproduced with permission under a Creative Commons Attribution 4.0 International license from ref 137. Copyright 2017 American Physical Society. (i) Reported lattice constants ordered from smallest to largest along the armchair direction and separated into results reported by theory (left) and experiments (right). Gray arrows give more information on the simulated/measured samples. (j, k) Cross-section and plan-view images of SnSe simulated by DFT for the case of (j) bulk and (k) monolayer. The armchair lattice constants are visualized using gray dashed lines, and the reduced in-plane anisotropy in the monolayer case is highlighted using blue ovals. Note that there is no consensus in the literature on crystal indexing.

710 entire compositional range, and all films show similar temper-711 ature response. But, interestingly there are a variety of properties 712 that are not linearly related to the composition. For single-M 713 MXenes, there is a single plasmon resonance peak that is related 714 to the free electron density of the MXene, and is affected by the 715 etching/delamination approach.⁹⁶ While, for solid-solution 716 MXenes (Figure 7j,k), there are instead two plasmon resonance 717 peaks (Figure 7l,m). Using $Ti_{2-\nu}Nb_{\nu}CT_{x}$ as an example, there is 718 one peak around 550 nm (similar to Ti_2CT_x) and a second in the 719 near IR region (similar to Nb_2CT_x), but both are slightly shifted, 720 due to the interactions of the metals with each other.⁹⁷ This is 721 due to the modification of the electronic states of the metals due 722 to the other metal, as was recently shown with electron energy 723 loss spectroscopy (EELS)¹²⁴ in addition to computational 724 predictions.⁹⁷ Interestingly, the same trend with EELS does not 725 occur with $Nb_{2-\nu}V_{\nu}CT_{x\nu}$ meaning that the interactions depend 726 on the specific metals themselves. Thus, to fully understand and predict the specific properties that solid-solution MXenes will 727 have, it is imperative to continue fundamental studies. 728

The electrochemical performance of solid-solution MXenes 729 also benefits from the multiple chemistries.^{120,125} For certain 730 MXenes, such as Ti₂CT_x and V₂CT_x, they have high capacitance, 731 but are unstable. Nb₂CT_x is highly stable but has lower 732 capacitance. Thus, combining the two can alleviate the negatives 733 of both chemistries. For Ti_{2-y}Nb_yCT_x and V_{2-y}Nb_yCT_x, the 734 cyclic voltammograms (CVs) are directly related to the MXene 735 chemistry. Depending on the specific chemistry, the volumetric 736 (gravimetric) capacitance ranged from 680 to 1070 F cm⁻³ 737 (245–490 F g⁻¹) in 3 M H₂SO₄.¹²⁵ Interestingly, in some cases, 738 middle compositions outperformed both extremes in capaci- 739 tance: V_{1.2}Nb_{0.8}CT_x and Ti_{1.6}Nb_{0.4}CT_x outperformed Ti₂CT_x, 740 V₂CT_x, or Nb₂CT_x in these studies. This implies that some 741 synergistic effect is occurring within solid-solution MXenes, 742 giving them enhanced performance. A similar case where a 743

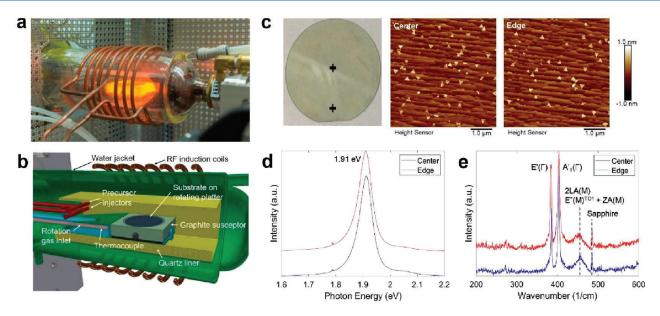


Figure 9. MOCVD for epitaxial 2D TMD semiconductors. (a) photo and (b) schematic of horizontal cold wall MOCVD reactor used for TMD growth. (c) Surface morphology of MoS_2 monolayer grown on 2" c-plane sapphire at center and edge of the wafer (locations indicated by + in photo). Room temperature (d) PL and (e) Raman spectra obtained at the center and edge of the wafer show spatially uniform monolayer thickness across the wafer.

744 middle composition outperforms other extremes was also 745 observed in $Mo_{4-v}V_vC_3T_x$.

2.2. Controlling the Structure and Phase of Low-Symmetry 746 2D Materials. Low-symmetry 2D materials with in-plane 747 748 anisotropic crystal structures possess a distinct functionality 749 because of their in-plane direction-dependent properties. Lowsymmetry 2D materials include black phosphorus, certain 750 TMDs including rhenium disulfide (ReS_2) and diselenide 751 (ReSe₂), and monochalcogenides of the group IV elements Ge 752 and Sn.^{126,127} Here, we focus on the Sn monochalcogenide 753 semiconductors SnSe and SnS. Their crystal structure resembles 754 a perturbed rock-salt, with ferroelectric and ferroelastic 755 distortions and substantial phonon anharmonicity, which 756 make these materials interesting for ferroelectrics, thermo-757 758 electrics, and photonics.^{128–130} The orthorhombic, ground state 759 crystal structure is thermodynamically adjacent to different 760 phases with higher symmetry and distinct properties, suggesting 761 the possibility of facile phase control and phase-change 762 functionality.¹³

We visualize the crystal structure in Figure8a-d. The top view 763 764 (Figure 8a) illustrates the shape and symmetry of the in-plane 765 unit cell. The in-plane unit cell is a rectangle with dissimilar lattice constants ranging from 3.9 to 4.5 Å, depending on the 766 chalcogen and crystal thickness. Each 2D sheet in the crystal 767 structure contains two layers of atoms (Figure 8j,k), and the out-768 of-plane lattice constant is perpendicular to the layers, forming 769 the overall orthorhombic crystal structure. The arrangement of 770 771 Sn-Se bonds, distorted from the high-symmetry rock-salt structure (Figure 8j), results in net polarization along the longer in-plane armchair direction.¹³² The unit cell contains two sheets 772 773 with opposing polarity (called AB stacking), so that the crystal is 774 antiferroelectric and centrosymmetric (i.e., nonpolar). In Figure 775 776 8d we visualize the SnSe₇ coordination polyhedron, with both 777 short-bonds and long-bonds within each 2D sheet, and longer 778 bonds linking the sheets.¹³³

The properties and functionality exclusive to these lowr80 symmetry 2D materials can be accessed by controlling the

structure and phase through epitaxial growth (Figure 8e-h). 781 The ferroelastic distortion that creates the distinction between 782 armchair and zigzag directions leads to a system of 90° twin 783 boundaries, across which these directions (and their associated 784 anisotropic properties) exchange. Mortelmans et al.¹³⁴ showed 785 that these 90° twins in SnSe can be eliminated by epitaxial 786 growth on a substrate with a rectangular and lattice-matched in-787 plane unit cell (Figure 8e), making possible large-area thin films 788 with uniform in-plane anisotropy. Chang et al.¹³⁵ demonstrated 789 through epitaxial growth on 6H-SiC(0001) that monolayers of 790 SnSe are indeed polar (Figure 8f), and exhibit in-plane 791 ferroelectricity at room temperature. The antiferroelectric, AB- 792 stacked crystal structure implies that polar crystals can only be 793 achieved in the monolayer limit. However, Higashitarumizu et 794 al.¹³⁶ observed AA stacking in multilayer SnS crystals grown on 795 mica, thereby realizing polar and ferroelectric SnS beyond the 796 monolayer limit, with intriguing possibilities for the optical and 797 optoelectronic properties (Figure 8g). Jin et al.¹³⁷ demonstrated 798 that this nonequilibrium rock-salt phase can be stabilized 799 through epitaxial film growth (Figure 8h). These results 800 highlight that a multitude of structures and phases can be 801 accessed through epitaxy, creating possibilities for fundamental 802 study and device technology.

Within the orthorhombic ground state structure, the in-plane 804 lattice constants and the measure of in-plane anisotropy are 805 remarkably sensitive to crystal thickness and likely also growth 806 conditions. A review of SnSe lattice constants reported by theory 807 (left) and experiments (right) is provided in Figure 8i. The data 808 are ordered from smallest (4.12 Å for theory, 4.06 Å for 809 experiment) to largest (4.29 Å for theory, 4.26 Å for experiment) 810 lattice constant along the zigzag direction. From the presented 811 theoretical work, we see that the lattice constants in the zigzag 812 and armchair directions approach closer to each other in 813 monolayer and bilayer SnSe, compared to the bulk.^{138,139} In 814 other words, on decreasing the crystal thickness, the in-pane 815 symmetry approaches square, bringing the crystal closer to the 816 rock-salt structure. This trend is confirmed by experimenta 817

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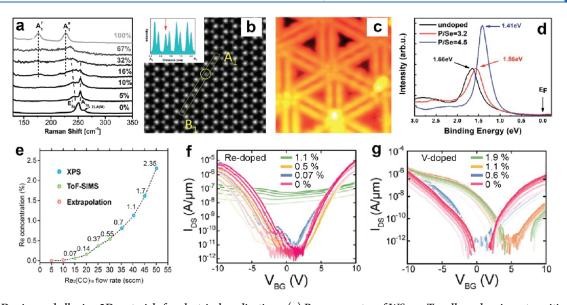


Figure 10. Doping and alloying 2D materials for electrical applications. (a) Raman spectra of WSe_(2-x)Te_x alloys showing a transition from the semiconducting 2H phase to the semimetallic 1T' phase as a function of increasing Te concentration. Adapted from ref 161. Copyright 2019 IOP Publishing Ltd. (b) ADF-STEM image and corresponding intensity profiles along the boxed region showing a P atom sitting at a Se site. (c) STM image of P-doped MoSe₂ (sample bias: -1.0 V, size: $10 \times 10 \text{ mm}^2$). The hexagonal structure of MoSe₂ remained intact after doping. (d) UPS of the undoped, lightly doped (P/Se flux ratio ≈ 3.2), and heavily doped (P/Se ≈ 4.5)-doped MoSe₂, showing a p-type behavior. Panels (b)–(d) were adapted with permission from ref 162. Copyright 2020 John Wiley & Sons, Inc. (e) The doping concentration of Re in WSe₂ from X-ray photoemission spectroscopy (XPS), secondary ion mass spectrometry (SIMS), and extrapolated points are plotted as a function of Re₂(CO)₁₀ flow rate during WSe₂ growth. (f) Transfer characteristics of pristine and Redoped WSe₂ field-effect transistors. While ambipolar conduction in the pristine and lightly Redoped WSe₂ films is demonstrated, at higher Re concentrations device performance is degraded due to the increasing impurity scattering. Panels (e) and (f) were adapted and modified with permission from ref 164. Copyright 2020, Wiley-VCH. (g) Transfer characteristics of the pristine WSe₂ film at different drain voltages (1–5 V) display ambipolar conduction. However, the n-branch degrades as V concentration increases and transistors gradually become p-type. All transistors were on 50 nm ALD Al₂O₃. Reproduced with permission from ref 165. Copyright 2021, Wiley-VCH.

⁸¹⁸ observations on thin films grown using CVD and physical vapor ⁸¹⁹ deposition (PVD), compared to measurements on thicker films ⁸²⁰ and bulk crystals.^{140,141} The out-of-plane lattice constant ⁸²¹ generally increases along with increasing in-plane lattice ⁸²² constants.

In Figure 8j,k we present DFT simulations that illustrate and 823 824 quantify the tendency of SnSe to have reduced in-plane anisotropy for thinner crystals. Bulk SnSe has in-plane lattice 825 constants of 4.20 and 4.56 Å, in a ratio of 0.921; results for 2D 826 SnSe are 4.29 and 4.39 Å, in a ratio of 0.977. This approach 827 toward square symmetry manifests as a reduced staggering, and 828 Sn-Se out-of-plane bonds that approach perpendicular relative 829 to the layers (highlighted by blue ovals), which reduces the in-830 plane polarization (Figure 8a) control of SnX structure and 831 phase through epitaxy may enable a range of useful applications. 832 The in-plane ferroelastic distortion of single-crystal thin films 833 834 can be used for "domain change" applications, whereby the 835 armchair and zigzag directions are switched (exchange of short-⁸³⁶ and long-bonds within the plane) on a picosecond time scale by 837 pulsed light, leveraging the dielectric anisotropy to realize a diffusionless, martensitic, nonthermal, nonresonant switching 838 process.¹⁴² Such "domain change" functionality could be useful 839 for low-injection-loss optical phase control in photonic integrated circuits.¹⁴³ Ferroelectric monolayer and AA-stacked 840 841 multilayer crystals could be used for electro-optic phase 842 843 modulation, nonlinear optics, and concepts in ferroelectric 844 nonvolatile memory.¹⁴⁴ The topological crystalline insulator 845 phases could enable high-responsivity infrared optical detec-846 tors.¹⁴⁵ Control of crystal anisotropy could also enable

fundamental understanding and applications of thermoelec- ⁸⁴⁷ tricity in SnX materials, for waste heat energy harvesting.¹⁴⁶ ⁸⁴⁸

2.3. Epitaxial Growth of Wafer-Scale TMD Monolayers by 849 MOCVD. Epitaxial TMD monolayers (MoS_2, WS_2, WSe_2) at the 850 wafer scale is of significant interest for device applications. 851 MOCVD is a promising approach for TMD growth as it enables 852 the use of high substrate temperatures (700-1000 °C) and 853 chalcogen/metal ratios $(10^3 - 10^5)^{147,148}$ that are beneficial for $_{854}$ epitaxy. In addition, the flow rate of precursors can be 855 modulated during growth to enhance the surface diffusion of 856 metal-containing species and control the lateral growth rate of 857 TMD domains.¹⁴⁷ C-plane sapphire has emerged as a promising 858 substrate for TMD epitaxy due to its crystallographic 859 compatibility and good chemical stability in the CVD environ- 860 ment. In addition, steps on the sapphire surface can be used to 861 induce a preferred alignment of TMD domains resulting in a 862 significant reduction in inversion domains in the films.^{149,150} 863

MOCVD growth of wafer-scale TMDs has been carried out 864 using a cold-wall horizontal quartz tube reactor that includes an 865 induction-heated rotating SiC-coated graphite susceptor as 866 shown in Figure 9a,b, which is available in the Penn State 2D 867 f9 Crystal Consortium facility.¹⁵¹ The precursors used include 868 metal hexacarbonyls ($Mo(CO)_6$ and $W(CO)_6$) and hydrides 869 (H_2Se and H_2S) with H_2 as the carrier gas. The cold wall 870 geometry, reduced reactor pressure (50-200 Torr) and separate 871 gas injectors are beneficial to reduce the extent of gas phase 872 prereactions that occur between the carbonyls and hydrides.⁴³ 873 Epitaxial growth of monolayer MoS_2 ,¹⁵² WS_2 ,¹⁵³ and WSe_2 .¹⁵⁴ 874 on 2" c-plane sapphire miscut $\pm 0.2^{\circ}$ toward the m-axis has been 875 demonstrated at growth temperatures in the range of 800–1000 876

f10

⁸⁷⁷ °C. For example, epitaxial MoS_2 films grown under these ⁸⁷⁸ conditions consist of a uniform monolayer across the entire 2" ⁸⁷⁹ diameter wafer with small triangular bilayers at a surface ⁸⁸⁰ coverage of <15% (Figure 9c). Undulations in the surface ⁸⁸¹ morphology of the monolayer arise from the steps on the ⁸⁸² sapphire surface. Room temperature photoluminescence (PL) ⁸⁸³ spectra (Figure 9d) obtained at the center and the edge of the 2" ⁸⁸⁴ sapphire contain an emission peak at 1.91 eV associated with the ⁸⁸⁵ A exciton of 1L MoS₂.¹⁵⁵ Raman spectra (Figure 9e) obtained at ⁸⁸⁶ the center and edge of the wafer show the characteristic modes ⁸⁸⁷ for 1L MoS₂. All of these results indicate the quality and ⁸⁸⁸ monolayer thickness can be uniform across the entire wafer.

The availability of wafer-scale MOCVD-grown epitaxial TMD monolayers films has enabled a variety of studies that benefit from high quality large area films that can be readily transferred off the growth substrates for device fabrication and testing. This includes benchmarking studies of FET performance,¹⁵⁶ 2D memtransistors for Baynesian networks,^{157,158} large area vdW superlattices,¹⁵⁹ localized quantum emitters,¹⁵⁹ and 2D photodetectors for biomimetic sensing platforms.¹⁶⁰

2.4. Substitutional Doping and Alloying 2D Materials for 897 898 Device Applications. Ion implantation is a standard semi-899 conducting technique to achieve small-depth channel post-900 growth electronic doping on Si using energetic ion beams. However, the high energy beams in traditional ion implantation 901 techniques will lead to significant damage for 2D materials and 902 903 would require postimplantation thermal annealing to recover crystallinity. Bottom-up doping or alloying of 2D materials can 904 be achieved through MBE and MOCVD in a homogeneous and 906 repeatable fashion by codelivery and control of multiple source 907 materials and their flux ratios. First, in an attempt to demonstrate 908 the potential of MBE to grow TMD alloys at back-end-of-line 909 (BEOL) temperatures (\leq 550 °C) and highlight relevant 910 challenges, Barton et al.¹⁶¹ reported WSe_(2-x)Te_x alloys grown 911 at T = 250 °C. For Te < 14%, a stable alloy in the 912 semiconducting 2H phase was achieved while for Te > 79% a 913 semimetallic 1T' phase was found to be stable. Interestingly, for 914 Te in the range of 14 to 79% a miscibility gap was observed 915 which resulted in a phase separation between two different alloys 916 having different crystal structures and composition, as shown by 917 Raman data in Figure 10a. The metallic alloys can be very useful 918 to make low resistance contacts by increasing the film 919 conductivity significantly.

Recently, substitutional doping of TMDs has been gaining 920 921 popularity for a variety of applications. Xia et al.¹⁶² 922 demonstrated phosphorus (P) doping in a monolayer of 923 MoSe₂ by codepositing P, Mo, and Se on a variety of substrates 924 to tune the electrical conductivity. As shown in Figure 10b, P 925 substitution at the Se sites was confirmed through annual dark 926 field scanning transmission electron microscopy (ADF-927 STEM).¹⁶² The cluster setup of the MBE system, combining 928 scanning tunneling microscopy (STM) and ultraviolet photo-929 electron spectroscopy (UPS), allowed them to perform in-depth 930 characterization without exposing the samples to air. As confirmed by STM (Figure 10c), P doping did not affect the 931 932 hexagonal structure or inversion domain boundaries of the 933 MoSe₂, nor generated any apparent P clusters within or on the 934 surface of the MoSe₂. In contrast to other reports where dopants 935 prefer to segregate at domain boundaries,¹⁶³ very uniform 936 doping was achieved. UPS measurements showed a clear p-type 937 behavior where the valence band maxima gradually moved 938 closer to the Fermi level $(E_{\rm F})$ as a function of P doping (Figure 939 10d).¹⁶² To have such fine control over tuning the electrical

conductivity and $E_{\rm F}$ through doping is highly desirable to control 940 the threshold voltages and ON-current density in TMD-based 941 transistors. 942

Recently, controllable substitutional doping of TMDs with 943 transition metal elements during MOCVD for modulating 944 TMDs-based transistors has been demonstrated. Kozhakhmetov 945 et al. 164,165 introduced $\mathrm{Re}_2(\mathrm{CO})_{10}$ and $\mathrm{V}_2(\mathrm{C}_5\mathrm{H}_5)_2$ during WSe $_2~$ 946 growth to substitute W with Re and V for n- and p-type doping, 947 respectively. Furthermore, by controlling carrier gas flow going 948 through the bubblers of precursors that provide dopants, dopant 949 concentrations can be tuned the parts per million to the 950 percentage level in WSe₂ (Figure 10e). Furthermore, to 951 understand the impact of dopant types and concentrations on 952 the transport of 2D WSe₂, Kozhakhmetov et al.^{164,165} 953 established the relationship between dopant concentration and 954 transfer characteristics for both Re- and V-doped WSe2 using 955 back-gate-FET (BGFET). The pristine WSe₂ BGFETs exhibit 956 ambipolar transfer characteristics and remain the same until 957 both Re and V concentrations exceed 1%. While standard 958 semiconductor doping level for Si is at the ppm level (<0.1%), 959 the doping for 2D semiconductors is relatively ineffective due to 960 the quantum confinement effect and reduced dielectric 961 screening.¹⁶⁶ This could be alleviated by encapsulation with 962 high- κ dielectric materials,¹⁶⁶ alloying TMDs with high dopant 963 concentrations,¹⁶⁷ or few-layer thick TMDs. Nevertheless, 964 contrary to high energy ions or high temperature diffusion 965 processes normally used in the CMOS-compatible processes, in 966 situ substitutional doping during MBE and MOCVD can 967 maintain the highest crystallinity of TMDs and control dopant 968 concentration well. 969

2.5. Native Oxide Formation of Semiconducting TMDs. 970 Like most metals in the galvanic series, and nearly all well- 971 developed semiconductors, the surfaces of TMDs are prone to 972 oxidation. Oxidation of TMDs is a long-appreciated and still 973 outstanding challenge in present-day applications of TMDs for 974 solid-state lubrication and desulfurization catalysis. In general, 975 the TMD surface is more easily oxidized as the chalcogen 976 decreases in electronegativity (descending in the periodic table) 977 from S, to Se, to Te.¹⁶⁸ Group VI compounds containing Mo 978 and W have a larger formation energy of sulfur vacancies and are 979 more stable compared to nongroup IV compounds containing 980 Hf, Zr, Ti, and Nb.¹⁶⁸ The oxidation of synthetic thin films is 981 more pronounced than that of bulk single crystals, due to 982 accelerated oxidation at random GBs, twin boundaries, and ₉₈₃ other crystallographic defects.¹⁶⁹ Control over oxidation is ₉₈₄ therefore a further reason to address the challenges of nucleation 985 and growth in TMD thin film crystal growth, for future 986 applications in microelectronics, optoelectronics, and pho- 987 tonics.¹⁷⁰

In particular, for microelectronics, the sustained academic 989 research activity and the increasing attention from industry 990 increase the urgency of understanding and controlling the 991 processing and properties of TMD native oxides. In some 992 situations, such as applications of monolayer crystals of highly 993 oxygen-sensitive compounds (e.g., $MoTe_2$, TiS_2), oxidation 994 must be avoided entirely, and therefore oxidation rates even in 995 nominally oxygen-free environments should be quantified.^{171,172} 996 In other situations, such as applications of multilayer crystals of 997 less-oxygen-sensitive compounds (e.g., WS_2 field effect tran- 998 sistors), controlled oxidation could be beneficial, and research is 999 ongoing into oxidation methods including thermal, UV/ozone, 1000 and plasma-assisted.^{173–176} The processes of TMD native 1001 oxidation are quite different, on the atomic scale, from the long- 1002

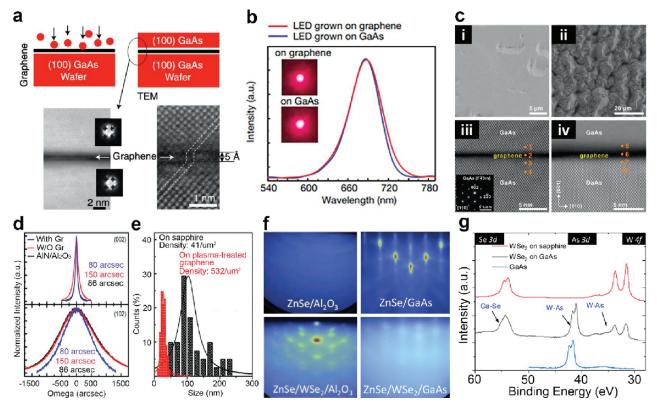


Figure 11. 2D materials as the intermediate layer of remote epitaxy. (a) Illustration of remote epitaxy of GaAs and cross-sectional TEM at GaAs/ graphene/GaAs interface. Adapted with permission from ref 178. Copyright 2019 Springer Nature. (b) Electroluminescence spectra of GaAs LEDs prepared directly on GaAs (red curve) and graphene through remote epitaxy on GaAs (blue curve). Inset shows pictures of working LEDs grown on both substrates. Adapted and modified with permission from ref 179. Copyright 2022 AIP Publishing LLC. (c) Scanning electron microscopy (SEM) (i, ii) and STEM (iii, iv) comparison of GaAs epitaxy using dry (i, iii) and wet (ii, iv) transferred graphene as an intermediate layer. The quality is significantly better on dry transferred graphene. Adapted and modified with permission from ref 180. Copyright 2021 AIP Publishing LLC. (d) X-ray diffraction rocking curves of the (002) and (102) planes for the aluminum nitride (AIN) growth on different templates. Quality is improved on the graphene template. (e) AlN nucleation and grain size comparison for direct growth on sapphire and remote epitaxy using plasma-treated graphene. Larger grain sizes on graphene enabled higher quality growth of the AlN film. (d, e) Adapted with permission from ref 181. Copyright 2020 AIP Publishing LLC. (f) Improvement in growth quality of MBE grown ZnSe by using an MBE grown 2D WSe₂ as a template. The reflection high-energy electron diffraction pattern transitions from Debye rings to streaky dots confirming better quality of the film when grown on WSe₂. (g) A comparison of ZnSe grown directly on GaAs with one grown using WSe₂ as an intermediate layer. (h) XPS comparison of ZnSe shown in panel (g). A reaction between the WSe₂ and the GaAs substrate can be clearly observed in the form of W-As and Ga-Se chemical states in the XPS. (f–h) Adapted with permission from ref 187. Copyright 2021 IEEE.

1003 studied native oxidation processes in legacy semiconductors, Si 1004 chief among them. Some of the oxides in question are volatile, 1005 such as MoO_3 that evaporates more readily than either Mo or 1006 MoS_2 . The oxides of Mo and W can form with wide variations in 1007 oxygen content, leading to wide variations in electronic 1008 conductivity, which is detrimental for dielectric functionality 1009 but may be useful for resistive switching. Further, TMD 1010 oxidation is accompanied by chalcogen loss. The expelled 1011 chalcogen may leave the system as a volatile gas (e.g., SO_2), or 1012 segregate as an additional (and likely unwanted) solid phase.

1013 A lesson learned from Si microelectronics is that, if at all 1014 possible, we should make use of semiconductor native oxides. 1015 Particularly for semiconducting TMDs for which the native 1016 oxides may be useful dielectrics (or even ferroelectrics), there is 1017 opportunity in better understanding the processing—property 1018 relationships that control dielectric response, leakage, and 1019 interface quality. For TMDs for which the native oxides have 1020 easily varied conductivity, there is opportunity in developing 1021 resistive switching functionality for memory and neuromorphic 1022 computing, or in developing native oxide electrodes. It took 1023 decades to develop SiO₂ as a reliable dielectric for Si CMOS technology. With the much wider processing and property space 1024 for TMD native oxides than for traditional semiconductors, we 1025 look forward to many years of productive research and 1026 development. 1027

2.6. Remote Epitaxy Using 2D Materials as an Inter- 1028 mediate Layer. Remote epitaxy, utilizing a 2D/3D hetero- 1029 structure, is an emerging technology that uses 2D materials as an 1030 intermediate layer to grow and later isolate single-crystal, free- 1031 standing 3D thin films in a nondestructive manner. In 2017, Kim 1032 et al.¹⁷⁷ revealed that thin films of different properties/ 1033 functionalities can be grown, exfoliated, and heterogeneously 1034 stacked as required.¹⁷⁸ As shown in Figure 11a, a thin layer of 1035 f11 graphene was used to partially screen the electrostatic potential 1036 fluctuations from the GaAs (100) substrate for homoepitaxial 1037 growth of GaAs (100).¹⁷⁷ Since the surface fluctuations of the 1038 substrate were not fully suppressed, adatoms on graphene were 1039 still able to interact with the substrate lattice to grow in an 1040 epitaxial manner with the same crystal orientation as the 1041 substrate. Additionally, unlike traditional epitaxy in which a 1042 strong bond exists between the epilayer and the substrate, the 1043 dangling bond free inert surface of graphene facilitated an easy 1044

1045 detachment of the epilayer. An advantage of remote epitaxy is 1046 that adding a graphene intermediate layer between a grown film 1047 and its host wafer does not degrade the device performance of 1048 grown films (Figure 11b).¹⁷⁹ This area that had originally started 1049 from homoepitaxy of GaAs with graphene as an intermediate 1050 layer has now expanded to a variety of epitaxial materials (e.g., 1051 GaAs,¹⁸⁰ III-N,¹⁸¹ and oxide ultrathin films¹⁸²) and inter-1052 mediate 2D layers (e.g., hBN¹⁸³ and TMDs¹⁸⁴).

Since remote epitaxy is facilitated by the intermediate 2D film, 1053 1054 the quality of this layer is one of the most important variables 1055 dictating the crystallinity of the grown epilayer. As shown in 1056 Figure 11c for remote epitaxy of GaAs, oxide formation at the 1057 substrate and interface of wet transferred graphene altered the 1058 effective distance between GaAs and the substrate to 1059 compromise the growth quality. In contrast, when GaAs was 1060 grown on dry-transferred graphene, which is less susceptible to 1061 oxidation, better quality was achieved. In a different report on 1062 remote epitaxy of GaN microcrystals, Jeong et al.¹⁸⁵ reported 1063 that when the 2D film is defective or has pinholes in it, a fraction 1064 of the grown structures could not be exfoliated and remained 1065 stuck on the substrate because of a direct covalent epitaxy 1066 through the defective region which made it difficult to reuse the 1067 substrate as well. Moreover, when there is an irregularity in the 1068 thickness of the 2D layer, such that there are regions where the 1069 thickness is greater than the critical thickness for remote 1070 interaction, epitaxy in those areas will not take place.¹⁸⁶ All these 1071 reports, consistently stress the elimination of transferred vdW 1072 layers and highlight the importance of contamination-free, 1073 uniformly grown 2D layers as the ideal pathway for reliable 1074 remote epitaxy.¹⁸⁷

Though remote epitaxy is still in its early stage of 1075 1076 development, it is already showing potential for a variety of 1077 applications such as the growth of free-standing devices, flexible 1078 electronics, and light-emitting diodes (LEDs).¹⁷⁸ In addition to 1079 this, remote epitaxy can help improve the overall growth quality 1080 of a material as well. An increase in the crystallinity and grain size 1081 of the epi-film have been observed when an intermediate 2D 1082 layer is used (Figure 11d,e).¹⁸¹ Zhou et al.^{184,187} used a MBE 1083 grown intermediate WSe₂ layer to improve the growth quality of 1084 zinc selenide (ZnSe) on sapphire at BEOL compatible 1085 temperatures (Figure 11f). ZnSe is a promising p-type 1086 semiconductor and is sought after as a channel material for 1087 BEOL transistors. The atomically thin, inert surface of WSe₂ 1088 enabled the long-range diffusion of adatoms at relatively lower 1089 temperatures to improve the crystallinity of the film. It is 1090 important to mention here that not only the quality of the 1091 intermediate layer, but the inertness of the substrate is also a 1092 critical factor to grow high quality epilayers. In contrast with the 1093 relatively chemically inert substrate sapphire, ZnSe growth on 1094 GaAs with a WSe₂ intermediate layer resulted in a degraded 1095 quality of the epilayer. Although GaAs and ZnSe are lattice 1096 matched (Figure 11g), the WSe₂ growth process reacted with 1097 the GaAs substrate, formed unwanted Ge-Se (Figure 11h), and 1098 failed to provide a pristine, dandling bond-free template for the 1099 epilayer to grow with high quality.

2.7. Challenges for Growing High-Quality 2D Materials on 3D Substrates by Thin-Film Deposition. Among the bottom-up approaches of fabricating 2D materials and structures, CVD and PVD are commonly used, as they generally produce high quality thin films with relatively simple equipment and low maintenance costs. However, for some layered materials such as TIs, MBE is preferred for its extremely high purity,¹⁸⁸ precise control on 107 doping,¹⁸⁹ and capability of creating atomically sharp interfaces¹⁹⁰ in heterostructures. Chalcogenide-based TIs like Bi₂Se₃ 1108 have hexagonal in-plane crystal structure with vdW bonds 1109 between each layer. They are of interest because their band 1110 structure comprises a bulk band gap and linear-dispersed surface 1111 states crossed within.¹⁹¹ To exploit these surface states, we need 1112 wafer-scale thin films that are atomically smooth with few 1113 defects, similar to the needs for other layered materials. Unlike a 1114 conventional 3D semiconductor system, synthesis of these 1115 layered materials proceeds by vdW epitaxy in which a vdW gap 1116 exists between the material and the substrate, relaxing the lattice-1117 matching constraint. However, the substrate still must be 1118 properly treated and growth conditions (substrate temperature, 1119 flux ratios, etc.) must be carefully chosen such that the material 1120 grows in the expected orientation.¹⁹²

Here, we will take the growth of Bi₂Se₃ by MBE as an example; 1122 however, many of the problems and solutions we discuss are 1123 applicable to other layered materials. Bi2Se3 has a crystal 1124 structure comprising sequentially covalently bonded quintuple 1125 layers (QL) of Se(1)-Bi-Se(2)-Bi-Se(1); the QLs are connected 1126to each other by vdW bonds. Bi $_2$ Se $_3$ has been successfully grown $_{1127}$ on sapphire,^{193'} GaAs,¹⁹⁴ Si,¹⁹⁵ and other substrates,^{196,197} even 1128 with considerable lattice mismatch. However, these films tend to 1129 suffer from three major types of structural defects, all of which 1130 increase electron scattering and reduce TI device quality. The 1131 first step is the formation of twin defects. Because Bi₂Se₃ has a 1132 hexagonal in-plan crystal structure, it can nucleate in two 1133 different orientations rotated by 60 degrees with respect to each 1134 other with equal probability. When these domains coalesce, 1135 dislocations arise which can lead to electron scattering. Twin 1136 defects can be mitigated by selecting more lattice-matched 1137 substrates with pregrowth treatment to align substrate step 1138 edges,^{198,199} or by using vicinal substrates with regular step 1139 edges to promote step-flow growth mode.²⁰⁰ However, vicinal 1140 substrates lead to additional difficulties as described below. 1141

The second structural defect is terraced growth, in which a 1142 second or third layer begins to grow before the first layer has 1143 finished leading to a "wedding cake" morphology. This arises 1144 due to the presence of Ehrlich-Schwoebel (ES) barriers.^{201,202} 1145 The ES barrier is the energy barrier for an adatom to cross an 1146 atomic step to a lower terrace.²⁰³ If the ES barrier is large 1147 compared to the in-plane diffusion barrier, adatoms are more 1148 likely to form a "daughter" island on incomplete "parent" island 1149 rather than move downward to fill the gap and smooth the 1150 film.²⁰⁴ The typical way to reduce the ES barrier is by using a 1151 surfactant such as Bi, In, or Sb.²⁰⁵ However, all three of these 1152 metals will incorporate into chalcogenide-based materials rather 1153 than acting as a surfactant. We instead take an alternative 1154 approach to reducing the root-mean square roughness of the 1155 film: reducing in-plane adatom diffusion. Nucleating the film at a 1156 low temperature, then growing the rest of the film at a higher 1157 temperature and/or by increasing growth rates both reduce in- 1158 plane diffusion and thereby reduce the film roughness. It is 1159 possible that other materials could be used as surfactants to 1160 further improve film morphology. 1161

Another unwelcome morphology often witnessed in TI films 1162 is the spiral growth. In conventional materials, spiral growth 1163 almost always originates from screw dislocations.²⁰⁶ For vdW 1164 materials, these types of dislocations should be mitigated by the 1165 vdW gaps. However, when the growth front of a TI domain 1166 encounters the step edge of the substrate, it can "pin" the 1167 domain. The six sides of the hexagonal in-plane Bi₂Se₃ crystal 1168 structure are not equivalent. One set of three sides grows faster 1169 than the other set due to a higher density of dangling bonds. If 1170 ¹¹⁷¹ the domain encounters a step at the wrong angle, this difference ¹¹⁷² in edge growth rate will result in spiral growth.²⁰⁷ It is possible ¹¹⁷³ that substrates with step heights equal to the thickness of a QL ¹¹⁷⁴ would reduce the spiral formation. These defects can also be ¹¹⁷⁵ mitigated by pretreating the substrate such that all the atomic ¹¹⁷⁶ steps are aligned, though challenges will still arise when domains ¹¹⁷⁷ coalesce if the substrate step height does not equal the *c*-axis ¹¹⁷⁸ lattice constant of the film.

In addition to these structural defects, Bi₂Se₃ films are often n-1179 1180 type doped due to selenium vacancies, surface oxidation, and/or 1181 band bending at the top and bottom interfaces. These unwanted 1182 carriers can pin the Fermi level above the Dirac point into the 1183 bulk conduction band, obscuring the signal from the surface 1184 states. There are several ways to mitigate the doping. A cracker ¹¹⁸⁵ source can be deployed to promote incorporation of the ¹¹⁸⁶ selenium atoms.²⁰⁸ A capping layer such as elemental ¹¹⁸⁷ selenium²⁰⁹ or other materials including oxides and polymers 1188 can be deposited on the Bi₂Se₃ surface to suppress oxygen 1189 exchange or contaminant adsorption. In addition, one can also 1190 introduce a lattice-matched trivially insulating buffer layer (e.g., 1191 $(Bi_{1-r}In_r)_2Se_3$ between the substrate and the Bi_2Se_3 film to 1192 reduce defects and band bending at the interface.²¹⁰ Through a 1193 combination of these efforts, background doping in Bi₂Se₃ films 1194 has steadily decreased such that the Fermi energy is often found 1195 in the bulk band gap. As noted above, vdW epitaxy has been 1196 widely adopted for other 2D material synthesis such as elemental 1197 2D materials like silicene,²¹¹ stanene,²¹² antimonene,²¹³ and TMDs.^{214,215} With the extremely accurate control over material 1198 1199 flux, MBE is also capable of creating functional heterostructures 1200 and superlattices based on 2D materials for optic and electronic ¹²⁰¹ applications, especially when the interface plays a critical role as ¹²⁰² in the 2D system.^{216,217} Overall, MBE growth of layered 1203 materials has progressed significantly over the past decade. 1204 Using a detailed understanding of the unique challenges and 1205 opportunities presented by vdW epitaxy, the future for MBE 1206 growth of functional vdW devices is bright.

2.8. Ternary Magnetic Layered Compounds Grown by 1207 1208 MBE. The quest for layered ferromagnets, one of the 1209 functionalities more recently pursued within the class of 2D 1210 materials, is to demonstrate a robust ferromagnetic order at 1211 room temperature. The initial question was if indeed 1212 ferromagnetism can be stabilized in the single atomic layer 1213 limit at finite temperatures. This presence of magnetic order 1214 would represent a violation of the Mermin-Wagner theorem,²¹⁸ 1215 i.e. the inability to establish any long-range magnetic order if an 1216 isotropic and finite-range Heisenberg exchange interaction is 1217 present. An alternative interpretation would be that 2D materials 1218 are simply not well captured by this theorem, and rather the 1219 highly anisotropic bond geometry inherent to 2D materials 1220 along with a finite thickness even in the single 2D layer limit 1221 would be enough to stabilize magnetic order, rendering a 1222 rigorous application of the theorem as not suitable. In any case, it 1223 is to be expected that magnetic order in 2D materials will not be 1224 very robust and potentially limited to a regime significantly 1225 lower than room temperature.

The experimental confirmation of ferromagnetism in atomi-1227 cally thin layers of the layered magnetic materials CrI_3^{219} and 1228 $Cr_2Ge_2Te_6^{220}$ in 2017 were widely considered fundamental 1229 breakthroughs, which led to an intensification of activities aimed 1230 at the further exploration of the field of 2D magnetism. 1231 Pioneering research activities have identified several vdW 1232 ferromagnets exhibiting insulating, semiconducting, and metal-1233 lic ground states, both in the form of bulk single crystals as well

as atomically thin flakes and films.²²¹ This is particularly exciting 1234 because vdW materials are considered an ideal playground for 1235 fundamental exploration of magnetic spin-on-lattice phenomena 1236 in the 2D limit, including the study of exotic magnetic ground 1237 states and magnetic phase transitions,²²² and they are also host 1238 of topologically nontrivial spin configurations (skyrmions).²²³ 1239 Aside from the exciting possibilities to explore fundamental 1240 physics questions, therefore pushing the horizon of our 1241 understanding of magnetism in 2D systems, research on these 1242 materials is also anticipated to stir up perspectives and avenues 1243 toward realization of ultracompact magnetic devices with 1244 relevance in spintronics and emerging quantum technologies. 1245 Here, one fascinating aspect is the fabrication of multifunctional 1246 vdW heterostructures by combining them and other 2D crystals 1247 like graphene and TMDs into vdW stacks, in which proximity- 1248 induced coupling effects across atomically smooth interfaces of 1249 layered materials can tailor magnetism by heterostructure 1250 design.² 1251

Most 2D ferromagnets experimentally realized and inves- 1252 tigated so far have Curie temperatures ($T_{\rm C}$) well below 300 K 1253 even in the bulk regime,^{22,5} a constraint that hinders their 1254 practical applications. Hence, there is an urgency in finding 1255 materials that can furnish long-range ferromagnetic order in a 1256 robust fashion above room temperature and within a thickness 1257 range from a few nanometers down to the single layer limit. 1258 Additionally, the 2D material of choice should allow for a 1259 straightforward, easy to control, and high-quality wafer-scale 1260 synthesis that should be stable in ambient conditions. Hence, 1261 beyond the growth of bulk single crystals and subsequent 1262 exfoliation, the utilization of thin film synthesis methods, such as 1263 MBE and CVD, is highly desirable.

The development of a precise deposition route with atomic 1265 level control is also key for assessing fundamental phenomena in 1266 these materials. This thickness range of interest, namely from 1267 few layers down to the single layer limit, seems to be difficult to 1268 access via standard exfoliation schemes in various 2D crystals 1269 including some vdW magnets. The structural and chemical 1270 stability is an additional, important aspect to advance the field 1271 toward technological realization. For example, the fast 1272 degradation commonly observed in chromium halides upon 1273 air exposure²²⁶ presents a great challenge for the development of 1274 reliable device fabrication routes. To be compatible with the 1275 envisioned device application, it is necessary to find magnetic 2D 1276 materials with superior chemical stability and robust magnetic 1277 order well above room temperature that will facilitate their 1278 realistic exploration for future technologies. 1279

TMDs with sizable free carrier concentrations, such as 1T- 1280 VSe_{2}^{227} 1T-CrT e_{2}^{228} and Fe_nGeTe_2 (3 $\ge n \ge 5$),²²⁹ show 1281 excellent prospect for the envisioned applications as they can 1282 exhibit ferromagnetic order around or even above 300 K. 1283 Recently, unique insights have been reported on the origin of 1284 magnetism in 1T-VSe2.230 It has been shown for 2D VSe2 1285 synthesized via MBE on MoS2 that postgrowth anneals 1286 promoted Se desorption, which induced the formation of a 1287 reconstructed surface. Since the magnetic signal was absent in 1288 pristine, i.e. unreconstructed, layers, the formation of 1D line 1289 defects were assumed to originate a ferromagnetic response at 1290 300 K. This suggests that alternative methods offering local 1291 control, such as focused ion beam,²³¹ could be utilized to 1292 introduce magnetic defects in a controlled fashion and with high 1293 spatial precision in the 2D lattice of 1T-VSe₂. These recent 1294 reports indicate that the development of reproducible protocols 1295 for scalable synthesis and defect creation are indeed challenging. 1296

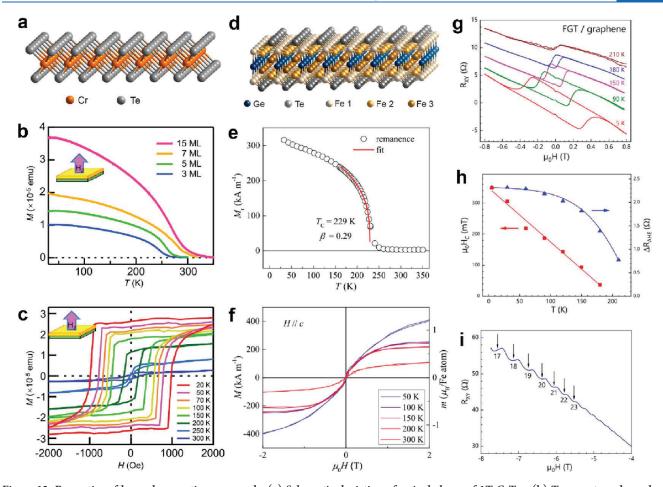


Figure 12. Properties of layered magnetic compounds. (a) Schematic depiction of a single layer of 1T-CrTe₂. (b) Temperature-dependent magnetization curves of CrTe₂ films with different thicknesses in a magnetic field of 1 kOe oriented along the out-of-plane direction. A high $T_{\rm C}$ close to room temperature was found for a trilayer. (c) Temperature-dependent magnetic hysteresis loops for a 7-layer-thick film with a magnetic field applied along the film normal. Panels (b) and (c) were reproduced with permission under a Creative Commons CC-BY 4.0 License from ref 234. Copyright 2021 Springer Nature. (d) Schematic depiction of a single layer of Fe₃GeTe₂. Temperature-dependent (e) remanent magnetization and (f) magnetic hysteresis loops of bilayer Fe₅GeTe₂ grown on c-plane sapphire by MBE. Panels (e) and (f) were reproduced with permission under a Creative Commons CC-BY 4.0 License from ref 229. Copyright 2022 Springer Nature. (g) The anomalous Hall effect (AHE) measured for Fe₃GeTe₂/Gr at different temperatures. For clarity, the resistance curves are successively shifted up by 2.5 Ω for temperatures between the negative linear slope arising from the ordinary Hall response of the free carriers in Fe₃GeTe₂/Gr. (h) Coercive field μ_0 ·H_C and saturation resistance $\Delta R_{\rm AHE}$ from the AHE contribution as a function of temperature for Fe₃GeTe₂/Gr. (i) Hall resistance $R_{\rm XY}$ in the high field limit of the Fe₃GeTe₂/Gr heterostructure showing Quantum Hall effect plateaus, indicating a high carrier mobility in Gr and thus the ability to preserve the functionality of the vdW templates after the growth of Fe₃GeTe₂ by MBE.²³⁸ The Landau level index is assigned to every plateau. Reproduced with permission under a Creative Commons Attribution 4.0 license from ref 238. Copyright 2021 IOP Publishing.

1297 On the one hand it represents a critical roadblock that needs to 1298 be overcome for the future exploration of vdW magnets, while at 1299 the same time this research area offers fertile grounds to make 1300 further ground-breaking discoveries in magnetic 2D materials. Capping layers were required to prevent unintentional 1301 oxidation and to avoid inactivation of magnetic defects.²³² 1302 Interestingly, degradation of magnetic properties upon air 1303 1304 exposure was found less critical for $1T-CrTe_{2r}^{233}$ although for 1305 long-term operation the use of capping layers seems inevitable as 1306 well. Like VSe₂, CrTe₂ assumes the conventional configuration 1307 of TMDs, schematically depicted in Figure 12a. Importantly, 1308 1T-CrTe₂ crystals were reported to exhibit Curie temperatures 1309 around 300 K in the bulk form, which remained close to room 1310 temperature for exfoliated flakes as thin as 8 nm.²²⁸ Interestingly, 1311 Zhang et al.²³⁴ observed room-temperature ferromagnetism of 1312 few-layer-thick CrTe₂ films grown by MBE on bilayer epitaxial

graphene on SiC, while $T_{\rm C}$ decreases to about 200 K when the 1313 thickness is reduced to a single layer, shown in Figure 12b,c. An 1314 intriguing aspect in the available reports is that a robust out-of- 1315 plane anisotropy was usually observed for epitaxially grown 1316 material. This is in marked difference from bulk crystals and 1317 corresponding ultrathin flakes, which always displayed an in- 1318 plane magnetic anisotropy. Specifically, Meng et al.²³⁵ reported a 1319 transition from an in-plane to an out-of-plane magnetocrystal- 1320 line easy axis in CVD-grown 1T-CrTe₂ islands for thicknesses 1321 \leq 10 nm. The origin of an out-of-plane anisotropy, which has not 1322 been observed in exfoliated flakes, has been associated with an 1323 enhanced magnetic anisotropic energy in the 2D limit, which 1324 can better resist thermal fluctuations and therefore help 1325 mediating a long-range ferromagnetic order. Further inves- 1326 tigations are required to understand these peculiar observations 1327 and existing discrepancies. Considering the rich phase diagram 1328

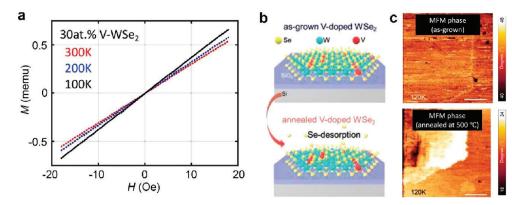


Figure 13. Quality versus magnetism in 2D TMDs. (a) Temperature dependent M versus H loops for a MBE grown, 30% V-doped 2D WSe₂ on sapphire showing the absence of any ferromagnetism at 100 K. (b) As-grown V-doped 2D WSe₂ sample grown on SiO₂/ Si was intentionally annealed to create Se vacancies. (c) Magnetic force microscopy (MFM) phase images measured at 120 K for as-grown and 500 °C annealed 0.5% V-doped WSe₂ are compared: The as-grown WSe₂ exhibits a negligible MFM phase contrast with respect to the SiO₂/Si. In contrast, the annealed WSe₂ exhibits a distinct magnetic domain contrast, confirming ferromagnetism in the annealed sample. Panels (b) and (c) were adapted and modified with permission from ref 256. Copyright 2022 John Wiley & Sons, Inc.

1329 of the Cr-Te system, which also includes the existence of stable
1330 phases with Cr atoms intercalated between chromium telluride
1331 layers,²³⁶ the existence of intermixed phases and/or thickness1332 dependent phase transitions occurring during epitaxial growth
1333 could possibly explain the differences in the magnetic properties
1334 observed so far.

The ferromagnetic metal Fe_nGeTe₂ is yet another very 1335 1336 relevant contender as a 2D material with an above room 1337 temperature ferromagnetic order. This is not only because of the 1338 high transition temperatures it can exhibit, but also due to the 1339 flexibility it offers to tailor magnetic properties via structural and 1340 chemical design within the individual vdW layers. As proposed by Seo et al., ²³⁷ a single layer of Fe_nGeTe_2 can be considered as a 1341 1342 specific material representation of a more general layered 1343 structure, in which a mechanical backbone is formed from a 1344 nonmagnetic and a chalcogen element—here Ge and Te with the chemical composition of a dichalcogen crystal-that is 1345 "filled" with magnetic elements-here Fe-that mediate the 1346 exchange interaction and ultimately originate the long-range 1347 1348 magnet order. A schematic of the atomic arrangement is shown 1349 in Figure 12d. A 3D-like network of magnetic elements confined 1350 within a 2D layer is formed in such a way that only vdW 1351 interaction are present for the interlayer interaction. Tuning the 1352 Fe content within the layers has been experimentally realized, 1353 and until now, Fe_nGeTe₂ with *n* values ranging from 3 to 5 was 1354 experimentally demonstrated.^{229,237,238}

Recently, changes in the magnetic properties as a function of 1355 1356 thickness have been assessed. The general trend confirmed by $_{\rm 1357}$ several studies is a decrease in $T_{\rm C}$ when the 2D limit is 1358 reached.^{239,240} For monolayer-thick Fe_3GeTe_2 , T_C values 1359 ranging from 20 to 126 K have been reported, depending on 1360 the measurement technique and method utilized for synthesis (either MBE growth on $Ge(111)^{239}$ or mechanical exfolia-1361 1362 tion²⁴⁰). A bilayer of Fe₅GeTe₂ grown epitaxially on c-plane 1363 sapphire exhibited a record-high T_C of around 230 K (Figure 1364 12e,f).²²⁹ Systematic studies are needed to unambiguously 1365 identify the critical thickness for $T_{\rm C}$ reduction for the different 1366 Fe_nGeTe₂ structures, as well as other contributing factors such as 1367 substrate type and capping layers. Such insights into Fe, GeTe, 1368 become even more desirable, since it exhibits good stability in 1369 air. Furthermore, electrostatic gating of Fe₃GeTe₂ using ionic 1370 liquids has demonstrated that Curie temperatures can be further

increased up to room temperature.²⁴⁰ One promising path to 1371 engineer the intrinsic magnetic properties of Fe_nGeTe₂ is by 1372 substituting Fe with transition metal elements possessing a 1373 strong magnetic moment as well. Co- and Ni-doping in 1374 Fe_{5-x}GeTe₂ bulk crystals²⁴¹ allowed for a rich variety of 1375 modifications in magnetism depending on the dopant content 1376 and type, from ferromagnetic-antiferromagnetic exchange to T_C 1377 boosting well above room temperature (Chen et al.²⁴¹ recently 1378 reported a T_C around 476 K for Ni-doped Fe₅GeTe₂ crystals). 1379 Further efforts should now be put on the realization atomically 1380 thin layers of doped Fe_nGeTe₂ with uniform intra- and interlayer 1381 dopant distribution. 1382

Progress has also been made in large-scale bottom-up growth 1383 of Fe_nGeTe_2 . MBE has so far been the method of choice for the 1384 epitaxial growth of continuous, large-area films utilizing the "3D" 1385 substrates.^{229,238,239,242} For example, c-plane sapphire has been 1386 used for the growth of Fe₅GeTe₂ epitaxial films.²²⁹ A Curie 1387 temperature of 300 K was reported, in good agreement with 1388 values obtained for bulk crystals.²⁴³ FenGeTe₂ synthesized 1389 directly on a 2D material surface has also been realized.²³⁸ A 1390 robust out-of-plane magnetic anisotropy and $T_{\rm C}$ around 220 K 1391 were measured for Fe₃GeTe₂ films grown on epitaxial graphene 1392 on SiC at relatively low growth temperatures around 300 °C. 1393 The high structural and electronic quality of the heterostructures 1394 was also confirmed by the observation of the quantum Hall effect 1395 in graphene, see Figure 12g-i. This is a key step toward the 1396 realization of epitaxial vdW heterostructures with pure and sharp 1397 interfaces, where proximity-induced phenomena can be used as 1398 a tool for tailoring magnetism. In this regard it remains of 1399 particular interest to develop synthesis of atomically thin, all-1400 epitaxial heterostructures combining Fe_nGeTe₂ not only with 1401 graphene but also with wafer-scale 2D crystals such as TMDs 1402 and hBN to realize the vision of highly functional vdW 1403 heterostructures, in which proximity-induced coupling across 1404 atomically smooth interfaces of layered materials with different 1405 properties enable unique functionalities²²⁴ that can be further 1406 tuned by external applied fields.

2.9. 2D Magnets and Controversies. Magnetism in the 2D 1408 limit is a desired property to build an all 2D-integarated chip 1409 capable of performing logic operations as well as storing the 1410 information.²⁴⁴ Although, a variety of 2D materials have been 1411 predicted and experimentally realized as room temperature 1412

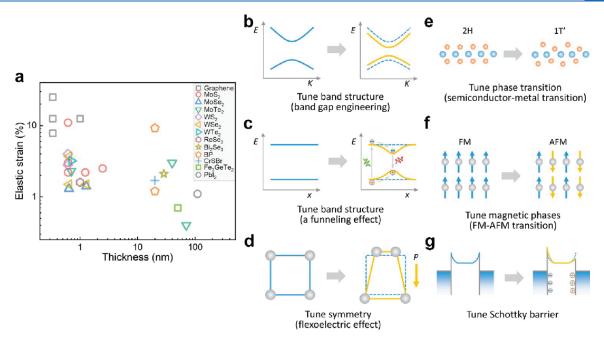


Figure 14. Large elastic strains and strain gradients in 2D materials. (a) Experimental measured elastic strains in representative 2D materials as a function of thickness. Here 2D materials include graphene, ${}^{261,262,266}_{261,262,266}$ MoS₂, ${}^{263,265,267,289}_{263,265,267,289}$ MoTe₂, ${}^{270-272}$ WS₂, ${}^{273,274}_{273,274}$ WSe₂, 268,275,276 WTe₂, 277 ReSe₂, 278 Bi₂Se₃, 279 BP, 280,281 CrSBr, 282 Fe₃GeTe₂, 283 and PbI₂, 295 Strain and strain gradient engineering in 2D materials. (a) Schematics of band structures (K for crystal momentum) before (left) and after (right) applying a strain (band gap engineering). Blue dashed curves represent the original bands. (b) Schematics of band structures (x for distance) before (left) and after (right) applying a local strain (a funneling effect). (c) Schematics of symmetries before (left) and after (right) applying a strain gradient. The strain gradient induces a spontaneous electrical polarization (P) (flexoelectric effect). (d) Atomic structures of transition metal dichalcogenides before (2H semiconducting phase, left) and after (AFM, right) applying a strain (FM–AFM transition). (f) Schematics of band diagrams before (left) after (right) applying a strain. (g) Schottky barrier heights formed at contacts are tuned by strain due to strain-induced polarization in piezoelectric materials.

1413 magnets, the origin of this magnetism is under intense debate in 1414 the community.^{245,246} The case of VSe₂ is one such example. 1415 Bonilla²⁴⁷ and Duvjir²⁴⁸ independently report magnetism in 1416 MBE grown VSe₂ monolayers on a variety of substrates, where 1417 magnetometry characterization using vibrating sample magneto-1418 meter (VSM) and superconducting quantum interference 1419 device (SQUID) showed magnetic hysteresis at room temper-1420 ature suggesting ferromagnetic order. However, later inves-1421 tigations by Batzill's group reported that pristine VSe₂ did not 1422 show magnetism. Instead, the magnetism arose following 1423 postgrowth annealing and Se vacancy formation in the 1424 film.^{245,249} This was confirmed in studies on pristine VSe₂ 1425 using a different characterization technique of X-ray magnetic 1426 circular dichroism (XMCD), which indicate the absence of any 1427 magnetic moments on the V atoms in pristine 2D VSe₂.^{250,251} 1428 Further evidence comes from angle-resolved photoemission 1429 spectroscopy (ARPES) measurements where no spin-polarized 1430 bands are found in 2D VSe₂.^{251,252} Lastly, the reported 1431 observation of a charge density wave (CDW) in monolayer 1432 VSe₂, which competes with the ferromagnetic ground state of ¹⁴³³ the system to suppress it, supports the claim of the nonmagnetic ¹⁴³⁴ nature of pristine VSe_2 .^{252,253} Thus, many reports demonstrate 1435 that the pristine VSe₂ is nonmagnetic. It is important to mention 1436 here that such a lack of intrinsic ferromagnetism is reported for 1437 other systems as well, where different artifacts such as edge 1438 states, surface adsorbates, and point defects were responsible for 1439 the magnetic effects.^{254,255}

1440 Magnetic impurity-doped semiconductors, commonly known 1441 as dilute magnetic semiconductors (DMS), have also been

suggested as another platform to search for RT 2D magnetism. 1442 Once again, the literature on 2D DMS is similarly filled with 1443 controversies and inconsistencies, in both theory and experi-1444 ments. For example, Tiwari et al.²⁵⁷ used first-principles 1445 calculations to predict that >18% atomic substitution of 1446 vanadium for W in a monolayer of WSe2 should give an out- 1447 of-plane RT ferromagnet. However, MBE grown 2D WSe₂ with 1448 about 30 atomic % V substitution does not show any magnetism 1449 for temperatures as low as 100 K (Figure 13a). In contrast, 1450 f13 several other groups have observed RT ferromagnetism for V 1451 doping levels in the range of 0.1-1% that are far below what 1452 DFT predicts for RT Curie temperatures.^{258,259} On the other 1453 hand, recently, point defects in the form of Se vacancies in CVD 1454 grown V-doped WSe2 created by thermal annealing were found 1455 to be responsible for magnetism in this system (Figure 13b,c).²⁵⁶ 1456 As the MBE growth is usually performed in a high chalcogen flux 1457 environment, Se vacancy concentrations are likely too low to 1458 show any vacancy induced magnetism and may explain why 1459 MBE V-doped WSe₂ films do not exhibit ferromagnetism. In 1460 short, while RT 2D magnets are coveted elements for memory 1461 and spintronic devices, the literature is rife with inconsistent and 1462 sometimes contradicting observations. 1463

3. Strain Engineering, Symmetry Breaking, and 1464 **Biosensing.** *3.1. Strain and Strain Gradient Engineering in* 1465 *2D Materials.* Strain engineering has been shown as a neat and 1466 effective approach in tuning or engineering the physical 1467 properties of 2D materials. The ability to reach large elastic 1468 strain in 2D materials has led to various scientific progresses in 1469 materials science, which include the editing of Berry 1470 1471 connection/curvature and topological Dirac states, tuning of 1472 metal—insulator and magnetic phase transition, direct—indirect 1473 electronic band structure evolution, and the realization of the 1474 flexo-photovoltaic effect, with details discussed in the paragraphs 1475 below.

1476 3.1.1. Colossal Strains and Strain Gradients in 2D 1477 Materials. In bulk materials, an elastic strain $\ll1\%$ can be 1478 sustained due to a large number of intrinsic defects (e.g, cracks 1479 and dislocations) either on the surface or inside the material.²⁶⁰ 1480 These defects multiplicate rapidly once deformation occurs 1481 (e.g., dislocation multiplicated by Frank-Read source). How-1482 ever, in low dimensional nanoscale materials, thermodynamic 1483 equilibrium shape can be easily reached and less defects are 1484 expected to be formed during the crystal growth. When 1485 deformed, for example, defect creation is largely dominated by 1486 surface dislocation nucleation, not by growth and propagation as 1487 the case of bulk crystals, making them much stronger than their 1488 bulk counterparts. Large elastic strains of above 1% have been 1489 widely demonstrated in low dimensional ceramic materials.

Figure 14a shows the experimental measured elastic strains in Figure 14a shows the experimental measured elastic strains in Pigure 14a shows the experimental measured elastic strains in Pigure 14a shows the experimental measured elastic strains in Pigure 14a shows the experimental measured elastic strains in Pigure 2 Garza et al.²⁶² reported elastic strains of above 10% in Pigure 2 Garza et al.²⁶² reported elastic strains of above 10% in Pigure 2 Garza et al.²⁶³ reported elastic strains in MoS₂ Pigure 2 Garza et al.²⁶³ reported that elastic strains in MoS₂ Pigure 2 Garza et al.²⁶³ reported that elastic strains in MoS₂ Pigure 2 Garza et al.²⁶³ reported that elastic strains in MoS₂ Pigure 2 Garza et al.²⁶³ reported that elastic strains in MoS₂ Pigure 2 Garza et al.²⁶⁴ and nanocones,²⁶⁴ bulking,²⁶⁵ and using Pigure 2 Garza et al.²⁶⁶ and nanocones,²⁶⁷ to generate elastic Pigure 2 Garza et al.^{268,275,276} WTe₂,²⁷⁷ ReSe₂,²⁷⁸ and Bi₂Se₃,²⁷⁹, Pigure 2 Carsa et al.^{268,281} layered magnets (CrSBr,²⁸² Pigure 2 Pigure

1507 strain limits increase with decreasing thicknesses of samples. 1508 Although elastic strain has been studied widely in most 2D 1509 materials, the strain gradient has received much less attention. In 1510 bulk crystals, the strain gradient can normally only reach below 1511 0.1 m⁻¹, which is often induced by mechanical bending.²⁶⁴ 1512 However, with reducing the sample thickness, a large elastic 1513 strain gradient can be created. Incredibly, large strain gradients 1514 of up to $\approx 10^6 \text{ m}^{-1}$ and $\approx 10^5 \text{ m}^{-1}$ are possible in MoS₂²⁸⁵ and 1515 freestanding film of BiFeO₃,²⁸⁶ respectively, whereas a bulk 1516 crystal such as MAPbBr₃²⁶⁴ can only manage strain gradients of 1517 <0.1 m⁻¹. Normally, when strains are generated in local regions 1518 in 2D materials (such as nanoindentation and buckling), strain 1519 gradients are formed simultaneously. These strain gradients 1520 should not be ignored and may play an important role on some 1521 physical properties. For example, strain gradient can break the 1522 inversion symmetry of a material and induce a spontaneous 1523 electrical polarization (flexoelectric effect), leading to intriguing 1524 phenomena such as flexo-photovoltaic effect (bulk photovoltaic 1525 effect coupled with flexoelectric effect).²⁸⁵⁻²⁸⁷ Therefore, 1526 relevant studies on strain gradient-property relations on 2D 1527 materials are highly desired.

By introducing strain in a material, one can modify the lattice sconstant, atom position, symmetry, and space group. All these used parameters determine the Hamiltonian of the system and thus state and the used to design or tune its electronic structure. For state example, by introducing compressive strain, a smaller lattice state constant could increase orbital overlapping, thus leading to a larger band gap. The tensor form of strain can be used to design 1534 or lower the symmetry of the system while symmetry breaking is 1535 sometimes accompanied by the emergence of interesting 1536 physical properties. Strain gradient naturally breaks the 1537 inversion symmetry of materials and could be used to design 1538 polarization or Berry connection.²⁸⁸ When spin—orbit coupling 1539 is considered, by tuning the symmetry of the crystal, strain or 1540 strain engineering could be used to design the topological 1541 properties of material. In 2D materials, strain and strain gradient 1542 have been demonstrated to be able to tune the electron—lattice 1543 interactions, band structure, phonon behaviors, magnetic 1544 ordering, spin-momentum coupling, and topological parame-1545 ters. 1546

The strain–band gap relation is one of the most widely 1547 investigated topics in 2D materials.^{265,274,280,289} By applying a 1548 uniaxial tensile mechanical strain ε in a monolayer MoS₂ (Figure 1549 14b), Conley et al.²⁸⁹ reported a nearly linear decrease of around 1550 45 meV/% in the optical band gap of the monolayer. A 1551 pronounced decrease in the PL intensity with increasing tensile 1552 strain suggests a possible direct-to-indirect transition in this 1553 material. If strain is applied at a local region, e.g., by 1554 nanoindentation using an AFM tip, a funneling effect can be 1555 induced (Figure 14c),²⁹⁰ where photoexcited electron and holes 1556 can migrate to the center and then they may recombine or they 1557 can be collected by electrodes. Based on this funneling effect, Li 1558 et al.²⁶⁷ designed and fabricated a 2D MoS₂ strained crystal by 1559 transferring MoS₂ monolayer onto a SiO₂ nanocone array. The 1560 authors demonstrated broadband light absorption and efficient 1561 funneling effect at maximum strain points in this strained 1562 crystal.²⁶⁷ Finally, this effect can lead to efficient funneling of 1563 excitons to generate single photon emission in nonuniformly 1564 strained monolayer $WSe_{22}^{291,292}$ and trions in nonuniformly 1565 strained monolayer WS_2^{273} Strain gradients can also tune the 1566 point group of a material (flexoelectric effect, Figure 14d). By 1567 using this method, Jiang et al.²⁸⁵ reported a large strain gradient 1568 of up to 10⁻⁶ m⁻¹ in a strain gradient-engineered MoS₂ sheet, 1569 leading to a flexo-photovoltaic effect. The 2D materials with 1570 nonuniform strains induced by nanoindentation, buckling and 1571 substrate with nanocones reported previously, also have strain 1572 gradients. The flexoelectric effect in these 2D materials may play 1573 in important role on some intriguing phenomena. By modifying 1574 the thermodynamic energy landscape, strain can tune phase 1575 transition temperature in 2D materials, such as a structural 2H- 1576 1T' phase transition (Figure 14e) with a proper strain in TMDs. 1577It is suggested that the activation energy for 2H-1T' phase 1578 transition can be modulated by strain: tensile strain lowers the 1579 energy barrier height.²⁹³ The structural phase transition is often 1580 accompanied by electronic phase transition-metal-semicon- 1581 ductor transition, important for the development of fast- 1582 switching transistors.²⁹³ By using strain-tuned phase transition 1583 in MoTe₂, Hou et al.²⁷¹ fabricated MoTe₂ phase change 1584 transistor and achieved nonvolatile conductivity change $G_{\rm on}/G_{\rm off}$ 1585 of near 10⁷. Through tuning the interlayer or intralayer magnetic 1586 exchange interaction, strain can control magnetic phases in 2D 1587 materials, including a ferromagnetic (FM) to antiferromagnetic 1588 (AFM) phase transition (Figure 14f).²⁸² As a final example of 1589 how strain impacts electronic properties, strain in piezoelectric 1590 2D materials can also be used to tune the Schottky barrier 1591 heights when Schottky contacts are formed (Figure 14g). Wu et 1592 al.²⁹⁴ reported the piezoelectricity in 2D MoS₂ and demon- 1593 strated an asymmetric carrier transport under strains in this 1594 device indicating a piezotronic effect in 2D MoS₂. Besides, strain 1595 can tune Dirac surface states and control exciton-phonon 1596

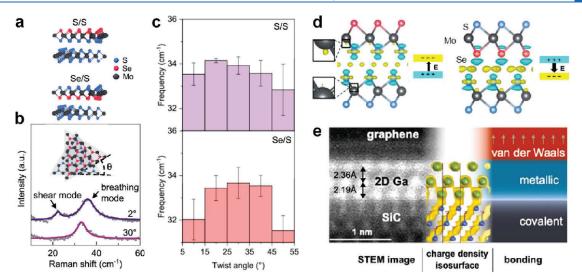


Figure 15. Emerging optical phenomena of asymmetric 2D materials. (a) Illustration of SeMoS/MoS₂ (SS) and SMoSe/MoS₂ (Se/S) heterobilayers. (b) The shear and breathing mode frequencies of interlayer shear and breathing modes of S/S heterobilayer at two twisted angles (θ), which is defined as the angle between the zigzag directions of SeMoS and MoS₂. (c) The breathing mode frequencies of S/S and Se/S heterobilayers fabricated by transfer stacking. (d) The charge density difference of the above Janus heterostructures with S/S and Se/S interfaces predicted by DFT calculations shows the direction of the interfacial electric field. Panels (a)–(d) were reproduced with permission from ref 317. Copyright 2021 American Chemical Society. (e) STEM image depicting the structure of 2D Ga PMet, consisting of three atomic layers of gallium on a SiC substrate capped with bilayer graphene, along with calculated charge density and schematic of bonding character. Reproduced with permission from ref 312. Copyright 2020 American Chemical Society.

1597 coupling in Bi₂Se₃ films, as reported by Flötotto et al.²⁷⁹ Strain 1598 can control exciton—phonon coupling in monolayer transition 1599 metal dichalcogenides, as reported by Niehues et al.²⁶⁸

1600 3.2. Second Harmonic Generation in 2D Materials. Here, we discuss recent research progress and challenges in the second 1601 1602 harmonic generation (SHG) of 2D materials. For a more 1603 comprehensive review of nonlinear properties, the readers are 1604 referred to several excellent previous reviews on 3D bulk²⁹⁶ and 1605 2D materials.²⁹⁷ SHG describes a coherent frequency-doubling 1606 process when intense light passes through a material. As a 1607 higher-order process compared with linear optical response, 1608 SHG involves more complexities in interpreting experimental 1609 measurements and theoretical calculations. However, the initial 1610 appeal of studying SHG in 2D materials was simple: SHG relies 1611 on inversion asymmetry, commonly found in monolayers and 1612 not their bulk layered parents.²⁹⁸ Within a monolayer with 1613 inversion asymmetry, any local disruptions to the lattice will also 1614 modulate $\chi^{(2),299-301}$ promoting SHG to be a defect character-1615 ization method that is more efficient and less destructive than 1616 transmission electron microscopy methods.³⁰⁰ One experimen-¹⁶¹⁷ tal difficulty is that there is no direct readout of $\chi^{(2)}$ from ¹⁶¹⁸ experiments: the extraction of $\chi^{(2)}$ from experimental measure-1619 ments of SHG requires a model of the second harmonic 1620 radiation field driven by the polarization of the material. One 1621 common "bulk" model originating from Boyd's classic text is to 1622 treat a monolayer as a bulk material with a thickness (e.g., 0.65 ¹⁶²³ nm per layer for MoS₂), as has been done for MoS₂, ³⁰² GaSe, ³⁰³ 1624 and InSe.³⁰⁴ This bulk model has been shown to severely 1625 overestimate $\chi^{(2)}$ compared with a more careful treatment using 1626 a "sheet" model.³⁰⁵ For example, $\chi^{(2)}$ for MoS₂ was over-1627 estimated to be 10^5 pm/V using the bulk model, while the sheet ¹⁶²⁹ resonance).³⁰⁶ Fortunately, Clark et al.³⁰⁶ also prescribes how 1630 to convert the bulk-model-derived $\chi^{(2)}$ to sheet-model-derived 1631 ones. Applying this conversion to GaSe, and InSe has achieved 1632 better agreement with theory results.³⁰⁷ Other methods were

reported too: a model based on the Green's function of a sheet 1633 source has estimated $\chi^{(2)}$ to be around 10⁴ pm/V for 2D 1634 TMDs³⁰⁸ at 800 nm excitation,³⁰⁹ 2 orders of magnitude larger 1635 than the on-resonance $\chi^{(2)}$ for TMDs extracted from the sheet 1636 model. At present it is not clear why these models yield $\chi^{(2)}$ 1637 values that appear inconsistent with both the bulk and sheet 1638 models.

The initial successful characterizations of SHG in 2D 1640 materials also brought focus to maximizing $\chi^{(2)}$ for potential 1641 applications in frequency doubling. Typically, measured $\chi^{(2)}$ 1642 were compared with that of industry-standard nonlinear crystals 1643 like barium borate (BBO) or potassium dihydrogen phosphate 1644 (KDP). However, $\chi^{(2)}$ is not the only metric of an ideal nonlinear 1645 crystal. A sufficiently large bandgap is required to ensure 1646 transparency and withstand laser-induced damage; adequate 1647 birefringence is necessary for phase matching; a crystal growth 1648 protocol that minimizes defect population is needed to reduce 1649 defect absorption. Even if one only considers two metrics— $\chi^{(2)}$ 1650 and bandgap—the known trade-off relationship³¹⁰ between 1651 them means that large $\chi^{(2)}$ values reported in the literature are 1652 frequently obtained at the implicit cost of a smaller bandgap.

A fairer metric should therefore be how far $\chi^{(2)}$ exceeds the 1654 $\chi^{(2)}$ - bandgap trade-off. One way to quantify this is to report $\chi^{(2)}$ 1655 normalized by the bandgap, as is done in Taghizadeh et al.³¹¹ 1656 Overall, we recommend that future research compare $\chi^{(2)}$ in the 1657 context of the material's bandgap. For example, in the case of 2D 1658 metals, in-plane $\chi^{(2)}$ components of 4.8 and 3.8 nm²/V were 1659 measured for 2D Ga and In intercalated between a SiC substrate 1660 and a graphene cap.³¹² These values, in a fair comparison with 1661 other zero-gap materials systems, are larger than the in-plane $\chi^{(2)}$ 1662 of metal surfaces such as Al(111), estimated to be 0.2 nm²/V. 1663 For the case of metal thiophosphates, He et al.³¹³ demonstrated 1664 that the bulk layered compound SnP₂S₆ achieves a large $\chi^{(2)}$ for 1665 its bandgap (2.3 eV). Its $\chi^{(2)}$ is on the order of 53 pm/V, larger 1666 than other common infrared nonlinear crystals with similar 1667

1669 laser-induced damage threshold, three times greater than that in 1670 ZnGeP₂, a commercially available nonlinear optical crystal.³¹³ 1671 Along with a large bandgap and laser damage threshold, the 1672 synthetic method is also important when considering 2D crystals 1673 for frequency doubling and other nonlinear optical applications. 1674 For example, it has recently been shown that few-layer MoS₂ 1675 exfoliated through a solution-phase redox process can exhibit 1676 saturable SHG and multiphoton absorption up to 10th order.³¹⁴ 1677 Polyoxometalate clusters which are formed during the redox 1678 exfoliation process and adsorb onto the 2D material flakes were 1679 implicated in the unusual nonlinear optical properties. Saturable 1680 SHG and multiphoton absorption were not observed in MoS₂ 1681 prepared by CVD, demonstrating that the choice of synthesis 1682 method can not only enhance or suppress the magnitude of 1683 existing nonlinear optical properties in 2D materials but also 1684 enable interesting phenomena.

3.3. Symmetry Breaking in 2D Materials. Symmetry 1685 1686 reduction can introduce exotic physical and chemical properties. 1687 For instance, the breaking of inversion symmetry in twisted BLG 1688 led to strongly correlated states due to moiré superlattice 1689 formation.³¹⁵ While low-symmetry 2D materials exist (e.g., SnS, 1690 $PdSe_2$, and WTe_2), there was a lack of 2D materials with mirror 1691 symmetry breaking because they were metastable. Thanks to 1692 recent advancement in synthesis methods for 2D materials, 1693 researchers can break the mirror symmetry of monolayers and 1694 unleash functionalities that cannot be achieved by traditional 1695 thin film techniques. This section covers two examples of 2D 1696 materials with structural symmetry breaking and their proper-1697 ties. First, Janus TMDs (e.g., SWSe, SeMoS) are one example of 1698 structural asymmetry enabled by surface treatments such as 1699 annealing with sulfur vapor³¹⁶ or low-energy selenium 1700 implantation¹³ performed on WSe₂ or MoS₂. The mirror 1701 symmetry breaking in Janus TMDs leads to an intrinsic vertical 1702 dipole moment that induces a wealth of unique properties that 1703 are not normally accessible and enhance the vdW coupling in 1704 heterostructures.³¹⁶ Second, air-stable 2D polar metals (e.g., Ga, 1705 In) in between epitaxial graphene and SiC with one side 1706 covalently binding to SiC and the other side that interacts with 1707 graphene by vdW forces are made possible by confined 1708 heteroepitaxy (CHet).⁵⁰ Due to different bond environments 1709 on both surfaces of half-vdW 2D metals, the out-of-plane metal-1710 metal bond changes by near 10%,³¹² resulting in symmetry 1711 breaking and a large nonlinear optical response. Both cases 1712 demonstrate the optical and photonic properties can be 1713 controlled precisely at the submonolayer level.

1714 3.3.1. Janus TMD Heterostructures. Janus TMDs is an 1715 example of broken mirror symmetry enabled by surface 1716 modification. It is a type of TMD material in which the 1717 transition metal is sandwiched between two different species of 1718 chalcogen. When Janus TMDs are assembled with other 2D 1719 materials into heterobilayers, different interfaces can be formed 1720 because of the structural asymmetry (Figure 15a). Zhang et 1721 al.³¹⁶ demonstrated that the dipole moment of Janus SeMoS 1722 enhanced the vdW coupling in a SeMoS/MoS₂ heterostructure 1723 synthesized by thermal selenization of bilayer MoS₂. The 1724 interlayer force constant of SeMoS/MoS₂ related to the 1725 interlayer shear and breathing modes was larger by 13.2% than 1726 that of as-grown bilayer MoS₂ due to the intrinsic dipole 1727 moment.³¹⁶ As the intrinsic dipole is perpendicular to the basal 1728 plane, the same group showed that this vdW coupling is 1729 dependent on which side of Janus TMDs was interacting with 1730 their pristine counterparts as well as their twisted angles (Figure 1731 15b).³¹⁷ For a Janus TMD transferred onto a pristine TMD, the

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MoS₂ exhibited a better vdW interaction with the sulfur side of 1732 SeMoS, as shown by the higher interlayer phonon frequencies in 1733 Figure 15c, due to a shorter interlayer spacing. DFT calculations 1734 also revealed that the intrinsic dipole led to an interfacial electric 1735 field (Figure 15d), promoting charge transfer between layers 1736 when MoS_2 was in contact with the sulfur side of MoSSe.³¹⁷ The 1737 modulated vdW coupling and charge transfer of Janus TMDs 1738 showcase the great potential for manipulation of electron 1739 dynamics in a variety of optoelectronic devices. Besides the 1740 experimentally probed optical properties, the intrinsic dipole 1741 moment was predicted to contribute to robust Rashba spin 1742 splitting independent of the applied electric field and strain,³¹⁸ 1743 which is important for spintronic devices, such as spin filters, 1744 spin FETs, and spin-resolved photodetectors. Theoretical 1745 predictions also suggested that Janus TMDs displayed great 1746 potential for applications including photocatalytic water- 1747 splitting, hydrogen evolution reaction, and gas sensing. 1748

3.3.2. 2D Polar Metal Heterostructures. While nano- 1749 structured metals are ubiquitous in technologies for sensing, 1750 catalysis, and nonlinear optics, 2D elemental metals are 1751 understudied compared to other 2D materials. The reduced 1752 dimensionality of 2D metals may offer advantages for highly 1753 tunable plasmonics,³¹⁹ photocatalysis,⁶ enhanced magnetism,⁵ 1754 and superconductivity.³²⁰ However, unlike other materials 1755 which are well-known in both 2D and 3D forms, traditional 1756 metals do not have an intrinsically layered bulk structure. 1757 Therefore, 2D metals are difficult to synthesize and often 1758 unstable, which has limited them to small lateral dimensions and 1759 high vacuum environments, hindering their applicability.³²¹ 1760 Epitaxial graphene grown on SiC can be physically decoupled 1761 from the SiC by intercalating atoms, such as F, O, and H,³²² to 1762 the graphene/SiC interface. Although this interface can improve 1763 the stability of intercalated ultrathin metals,¹⁴ metal intercala- 1764 tion has not been studied actively. 1765

Recently, atomically thin, air-stable metals have been realized 1766 through CHet.⁵⁰ These 2D polar metal heterostructures (2D- 1767 PMets) consist of a few atomic layers of metal that are epitaxial 1768 to a SiC substrate and capped with bilayer graphene (Figure 1769 15e). The components of the heterostructure are crucial to the 1770 properties of the 2D metals: registry to the SiC substrate results 1771 in the metal layers adopting a strained hexagonal lattice, while 1772 the graphene protects the metal from oxidation. As a result, 2D- 1773 PMets offer opportunities for both fundamental studies of the 1774 properties of crystalline metals in lattice configurations not 1775 achievable in bulk and expanded studies of 2D metals beyond 1776 gold under ambient conditions. Since the introduction of 2D- 1777 PMets, their properties including superconductivity,⁵⁰ nonlinear 1778 optical phenomena,³¹² potential epsilon-near-zero modes,³²³ 1779 and tunable optical resonances and energy dissipation have been 1780 reported.³²⁴ 2D-PMets, such as Ga and In, exhibit extremely 1781 efficient nonlinear optical transduction, with $\chi^{(2)}$ of 3 to 5 nm/ 1782 V.³¹² 2D-Ga and -In also outperform other metal SHG sources 1783 like gold nanorods and graphene-coated gold films (1000 and 1784 100× higher $\chi^{(2)}$, respectively) and industry standards like 1785 LiNbO₃ (100× higher $\chi^{(2)}$).³²⁵ Nonlinear optical microscopy 1786 has revealed in-plane and out-of-plane symmetry breaking in 1787 2D-PMets which allows the large second-order response and 1788 determines the polarization plane of the emission.³¹²

As the family of 2D-PMets grows to include more elements, 1790 nonlinear optical microscopy will continue to enable fast, 1791 noninvasive characterization of the quality and crystal structure 1792 of intercalated metals. The structural information obtained 1793 through polarization-resolved SHG microscopy may be 1794

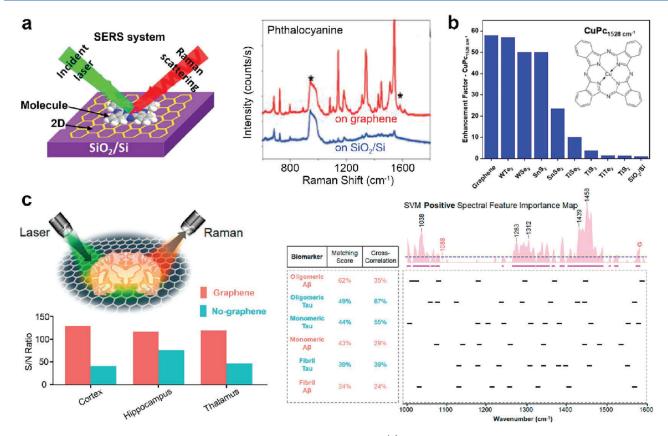


Figure 16. Biosensing based on Raman enhancement through 2D materials. (a) GERS of Phthalocyanine. Adapted and modified with permission from ref 333. Copyright 2015 American Chemical Society. (b) Raman enhancement of CuPc using different 2D materials. Adapted and modified with permission from ref 335. Copyright 2019 American Chemical Society. (c) The Raman signals obtained from different brain regions showed a better signal-to-noise ratio when graphene was in contact with the brain slice. Different ML classifiers showed higher accuracy in distinguishing mice with and without Alzheimer's disease. Adapted and modified with permission from ref 338. Copyright 2022 American Chemical Society.

1795 complemented by wide-field hyperspectral nonlinear imaging, 1796 which can be performed with diffraction-limited and subdif-1797 fraction spatial resolution through Fourier transform nonlinear 1798 optical microscopy.^{326,327} These combined modalities may 1799 address further remaining questions about 2D-PMets, such as 1800 the influence of metal thickness on the properties of the 2D 1801 metal heterostructures and the possibility of enhancing the 1802 intrinsically strong light-matter interactions of 2D-PMets 1803 through the formation of hybrid resonances.

3.4. Biosensing Applications. 2D materials' surfaces have low 1804 1805 roughness and are dangling bond-free, which are more desirable 1806 than 3D substrates to host small molecules and biological 1807 materials to avoid unnecessary material binding and improve 1808 surface adsorption. Additionally, 2D materials exhibit character-1809 istic Raman peaks (e.g., G band and 2D band of graphene and $_{1810}$ E_{2g} band and A_{1g} band of 2D MoS₂) whose position and width 1811 are very sensitive to changes in doping, strain, environment 1812 effects, and materials heterogeneity (e.g., substitutional doping, 1813 alloying, and vdW heterostructure formation). Therefore, 1814 Raman peaks of 2D materials and in some cases PL of 2D 1815 semiconductors are used as indicators in nondestructive sensing 1816 including photodetectors, strain sensors, and biosensing. In the 1817 following, we discuss biosensing of small molecules and 1818 biomolecules on 2D surfaces using Raman characterization³²⁸ 1819 and learn from Ignatova et al.^{329°} about using multi-imaging 1820 techniques to understand the nonuniformities in MoS₂/ 1821 graphene bilayers. Since 2D materials are scalable, transferrable,

and air-stable thanks to the continuous improvement of their 1822 manufacturing, it is possible to realize them as large-area 1823 biosensors in the near future. 1824

3.4.1. Raman Enhancement through 2D Surfaces. 2D 1825 materials have attracted substantial interest in the field of 1826 biological sensing because of their large surface-to-volume ratio, 1827 superior electrical transport, strong surface adsorption, and 1828 biocompatibility.³³⁰ These excellent attributes meet the 1829 demands of rapid and accurate biomolecular sensing, which 1830 requires high multiplexity and specificity. For the detection of 1831 infectious diseases, the challenge is to detect rapidly and 1832 remotely to minimize unnecessary contacts and reduce the 1833 transmission rate.³³¹ While for other diseases with unknown 1834 origin, Alzheimer's disease, for instance, it is challenging to 1835 provide additional information that pinpoints reliable disease 1836 biomarkers for early detection.³³² However, realizing such 1837 sensing functionality needs a reliable technique tool to obtain 1838 fingerprinting signals of biological samples and efficient 1839 interaction between the sensing media and biomolecules. Facing 1840 these challenges, Raman enhancement through 2D materials 1841 offers an effective approach for chemical sensing of biomolecules 1842 with high multiplexity, specificity, and signal-to-noise ratios.³²⁸ 1843 An example of Raman enhancement through 2D materials is the 1844 surface-enhanced Raman scattering (SERS),³³³ in which the 1845 Raman signals of analyte molecules can be significantly 1846 enhanced by contacting graphene and other 2D crystals (Figure 1847 16a). This sensing mechanism relies on the dipole-dipole 1848 f16

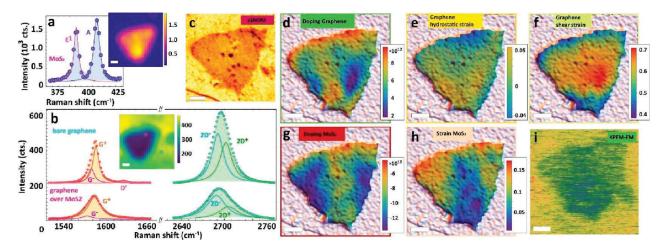


Figure 17. Multidimensional imaging on MoS_2 /graphene. (a) MoS_2 Raman spectrum, fitted with E1 and A-bands, (inset) A-band intensity map; (b) Raman spectra for graphene off/on MoS_2 island, fitted by G (orange), D' (pink) and 2D (green) bands, (inset) Raman map of 2D-amplitude showing the island location; (c) KPFM (a) KPFM image; (d–f) calculated graphene doping, hydrostatic and shear strain maps, overlaid with scanning electron microscopy image; (g, h) doping and strain for MoS_2 layer overlaid with SEM image; (i) sSNOM phase image of the same area. All scale bars are 1 μ m. Reproduced with permission from ref 329. Copyright 2022 American Chemical Society.

1849 interaction and charge transfer between 2D materials and 1850 molecules.³³⁴ Since the discovery of graphene-enhanced Raman 1851 scattering (GERS), a plethora of 2D materials including 1852 graphene and TMDs (WSe₂, SnS₂, WTe₂) have exhibited the 1853 capability to strengthen the Raman signals of a wide range of 1854 small molecules (Figure 16b).^{330,328,335,336}

The application of Raman enhancement through 2D materials 1855 1856 is not limited to small molecules. It can be widely applied to a 1857 range of biological samples, such as macromolecules,³³⁷
 1858 tissues,³³⁸ and cerebrospinal fluid.³³⁹ Huang et al. demonstrated 1859 the enhancement of blood constituent proteins, including 1860 hemoglobin and albumin based on their unique structures and 1861 oxidation states.³⁴⁰ Wang et al.³³⁸ showed that 2D materials can 1862 also be used to enhance the signal-to-noise ratio of Raman 1863 signals in mouse brains with Alzheimer's disease (Figure 16c). 1864 The accuracy of machine learning (ML) classification for brain 1865 tissues with and without Alzheimer's disease was also increased 1866 from 77 to 98% by applying graphene.³³⁸ Moreover, this work 1867 identified biomarkers specific to Alzheimer's disease, including 1868 Amyloid- β and Tau, and other potential biomarkers that have 1869 been confirmed by other biochemical studies. Equipped with 1870 ML analysis,³³⁸ enhanced Raman response can accelerate the 1871 understanding of disease pathology, the control of viral 1872 transmission, and the development of therapeutics. Aside from 1873 being applied to biochemical sensing, 2D materials have been 1874 extensively explored in the landscape of other biomedical 1875 applications, such as bioimaging,³⁴¹ tissue engineering,³⁴² and 1876 drug delivery,³⁴³ continuing to attract interdisciplinary research 1877 interest.

1878 **3.4.2.** The Role of Optical Nonuniformities in vdW 1879 Heterostructures for Multidimensional Imaging. 2D hetero-1880 structures were shown to operate in a multimodal regime— 1881 producing several signals in response to a single analyte, allowing 1882 for reporting the analyte in a complex media.¹⁰ Multiplexed 1883 sensing of doxorubicin, a common cancer drug, was demon-1884 strated by Ignatova et al.³²⁹ using a 2D material vertical 1885 heterostructure. A biosensor composed of monolayer MoS₂ 1886 coated with graphene utilized GERS, MoS₂ photoluminescence 1887 (PL), and graphene Raman shift signals to report drug molecules 1888 with a 60 nM threshold. A multiplexing approach has enabled 1889 reporting the drug in the mixed solution with a "contaminant"

organic molecule.³⁴⁴ However, this method could suffer from 1890 the above-mentioned local fluctuations of material properties at 1891 the nanoscale. The nonuniformities that influence device 1892 performance can be divided in two groups: inherited during 1893 synthesis (intrinsic) and acquired during device fabrication 1894 process. Intrinsic nonuniformities include atomic impurities, 1895 lattice defects,^{46,52,345} GBs, wrinkles and ruptures that result in 1896 strain, doping and/or charge transfer, often possessing variation 1897 at the nanometer scale. Acquired nonuniformities that come 1898 from the transfer process and nanofabrication can be partially 1899 eliminated by post-transfer cleaning procedures (annealing) or 1900 by using Soxhlet extractor³⁴⁶ for improving quality of transfer. 1901 Despite efforts to remove contaminants, typical resultant 1902 materials are not perfect, leading to variability in optical 1903 signaling and high noise in biosensors. 1904

Ignatova et al.³²⁹ applied multidimensional imaging analysis 1905 to unveil mechanisms of the local fluctuations of optical 1906 response (PL, Raman) of a biosensor. Typical Raman spectra of 1907 graphene-MoS₂ heterostructure are shown in Figure 17a,b 1908 f17 (insets show maps of a MoS₂ island and locations of single-point 1909 spectra of the main plot). Advanced fitting procedure described 1910 previously^{347,348} was used to determine the local values of strain 1911 and doping for graphene and MoS₂ materials across the whole 1912 heterostructure. Furthermore, the splitting of the G- and 2D- 1913 Raman bands of graphene yields the shear (nonisotropic) 1914 component of the strain (Figure 17b). Generated maps in Figure 1915 17d-h show correlation between the sources of local optical 1916 fluctuation and morphology of the sample, as determined by 1917 high resolution infrared scattering scanning near-field optical 1918 microscopy (sSNOM) image (Figure 17c). Charge doping and 1919 components of graphene strain clearly vary across the MoS₂ 1920 island, consistent with the Kelvin probe force microscopy 1921 (KPFM) results (Figure 17i) and sSNOM (not shown). The 1922 cross-correlation of KPFM and sSNOM data allows quantifica- 1923 tion of the variation of in Fermi level of graphene above the 1924 MoS₂ island at nanoscale resolution impossible for KPFM or 1925 Raman microscopy along. The presented study suggests that to 1926 improve the performance of devices and sensors based on 2D 1927 heterostructures, nonuniformity of doping and strain-two 1928 major mechanisms for optical signal variation-must be 1929

1930 addressed. Strain-free and doping-free transfer methods are also 1931 needed.

1932 4. Multidimensional Heterostructures. 4.1. 0D/2D 1933 Heterostructures. Mixed-dimensional 0D/2D heterostructures 1934 formed by the stacking of 2D materials with 0D nanoparticles 1935 constitute a class of nanomaterials that offers multifunctionality 1936 that goes beyond those of 2D heterostructure systems.³⁴⁹ The 1937 class of 0D materials that can be stacked on 2D materials 1938 primarily consist of fullerenes, organic molecules, quantum dots 1939 (QD), atomic clusters, and atoms.³⁵⁰ In principle, due to the 1940 lack of lattice matching and processing compatibility limitations, 1941 a large panel of radically different materials can be stacked to 1942 form mixed-dimensional 0D/2D heterostructures with diverse 1943 properties.³⁴⁹ Mixed-dimensional 0D/2D heterostructures have 1944 attracted attention in the fields of catalysis, molecular sensing, 1945 quantum information, optoelectronics, and energy conversion 1946 and storage due to their unique properties.^{351,352}

The recent work by Kolli et al.³⁵³ is a typical example 1947 1948 representing a mixed-dimensional 0D/2D heterostructure 1949 between SnS₂ QDs and 2D MoS₂. The SnS₂-QDs prepared 1950 using solution-processing method were spin coated on MoS₂ 1951 monolayers grown on SiO₂/Si by the CVD technique, to form 1952 the mixed-dimensional 0D/2D SnS2-QDs/MoS2 heterostruc-1953 ture. The 0D/2D heterostructure of SnS₂-QDs/monolayer 1954 MoS₂ was fabricated for high-performance and broadband 1955 (UV-visible-near-infrared (NIR)) photodetector, with photo-1956 responsivity for UV, visible, and NIR regions of ~278, ~435, 1957 and ~189 A/W, respectively. Monolayer MoS₂ is visible- and 1958 NIR-light-sensitive, and discretely distributed SnS2-QDs ex-1959 tends the photodetection range to the UV region, thus 1960 broadening the photodetection range of SnS₂-QDs/MoS₂ 1961 from UV to NIR. The excellent performance of the fabricated 1962 SnS₂-QDs/monolayer MoS₂ hybrid photodetector is attributed 1963 to the band bending and built-in potential created at the junction 1964 of SnS₂-QDs and MoS₂ (Figure 18a), which enhances the 1965 injection and separation efficiency of the photoexcited charge 1966 carriers.

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Metallic nanoclusters and/or atomically dispersed metal 1967 1968 atoms confined on 2D materials is also a promising avenue for 1969 mixed dimensional heterostructures for catalysis, molecular 1970 sensing, and energy storage due to their highly efficient metal 1971 utilization.³⁵⁴ Reducing the metallic particle size to metallic 1972 nanoclusters and single metal atoms increases the exposed 1973 surface atoms, modifies the surface electronic and atomic 1974 structure, and creates defects.,³⁵⁵ The strong metal–2D material 1975 support interaction and quantum size effects can lead to 1976 exceptionally distinct chemical, physical and electronic proper-1977 ties relative to nanoparticles and bulk metals. Lei et al.³⁴ showed a typical example of a mixed-dimensional 0D/2D hetero-1978 1979 structure based on metallic nanoclusters and atomically 1980 dispersed metal atoms confined on 2D materials between hexagonal boron nitride (hBN) and various metals including, Fe, 1981 Cu, Au, Ag, and Pt. In this report, the hBN/AgPt nanoclusters 1982 (Figure 18b) demonstrated excellent hydrogen evolution 1983 reaction (HER) activity, with an onset potential better than all 1984 1985 other heterostructures (87 mV) due to the robust anchoring of 1986 atomically dispersed Pt atoms, improved electrical conductivity from the Ag, and the synergetic effects between hBN and AgPt. 1987 Single metal atom sites attached on a 2D material matrix in a 1988 1989 mixed-dimensional 0D/2D heterostructure can also be used to 1990 tune the electronic structure of the 2D material host matrix. A 1991 typical example representing a 0D/2D heterostructure in which 1992 attaching single metal atoms are attached onto a 2D matrix to

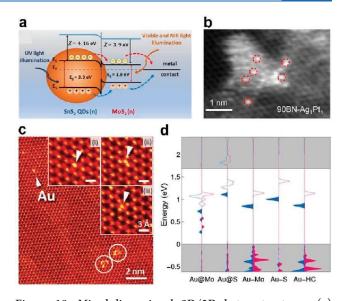


Figure 18. Mixed-dimensional 0D/2D heterostructures. (a) Schematic illustration of SnS2-QDs and monolayer MoS2 band structure after the formation of heterojunction with proposed e-h pair separation. Reproduced with permission from ref 353. Copyright 2022 American Chemical Society. (b) Representative high magnifications STEM-ADF images of hBN-AgPt where the atomically dispersed Pt atoms in the Ag-Pt cluster are highlighted with red dashed circles. Reproduced with permission under a Creative Commons Attribution 4.0 International license (CC BY 4.0) from ref 34. Copyright 2021 Elsevier. (c) An annular dark-field TEM image of a ~0.6 at. % Au-doped MoS₂ monolayer. Au adatom (indicated by arrows) were found to be located on top of the Mo (i), S (ii), and hollow-center site (iii), respectively. (d) LDOS of the Au dopant atoms at their considered atomic structures. The blue and red plots are for the spin up and spin down components, respectively. The filled curves indicate occupied states. Panels (c) and (d) were adapted and modified with permission from ref 356. Copyright 2014 John Wiley & Sons, Inc.

tune the electronic structure of the host matrix is an Au single $_{1993}$ atom/monolayer $\rm MoS_2$ hybrid. 356,357 For example, Lin et al. $_{1994}$ prepared Au dopants on the surface of a MoS₂ monolayer and 1995 confirmed the position of Au adatoms can be on top of the Mo, 1996 S, and hollow-centers (HC) of MoS_2 in the TEM image (Figure 1997 18c). To investigate the impact of Au adatoms on the electronic 1998 structure of 2D MoS₂, the authors simulated local density of 1999 states (LDOS) around Au adatoms on MoS₂ (Figure 18d). The 2000 LDOS around Au adatoms at the Mo, S, and HC sites exhibit the 2001 gap states inside the bandgap of MoS₂, which can act as p-type 2002 doping sources to compensate the n-type nature of MoS₂. 2003 Recently, Liu et al.³⁵⁷ reported a spontaneous defect-free 2004 functionalization method consisting of attaching Au single 2005 atoms to monolayers of semiconducting MoS2 by using S-Au-Cl 2006 coordination complexes and confirmed the doping effect of Au 2007 single atoms with MoS₂ FETs. The output characteristics of the 2008 Au-MoS₂ BGFETs showed that the Au single atoms led to the 2009 transfer of electrons from MoS₂ to Au, as the threshold voltage 2010 was shifted toward negative voltages with Au dopants, which 2011 introduced p-type doping to the functionalized MoS₂ mono- 2012 layers.³⁵⁷ Moreover, the degree of n- and p-type doping in the 2013 MoS₂ matrix can be finetuned by choosing the transition metal 2014 single atom attached and by varying their concentrations, thus 2015 controlling the electronic band structure of MoS₂.³⁵⁸ 2016

4.2. 2D/3D Heterojunction Devices. The advent of 2D 2017 materials has attracted considerable attention in design 2018

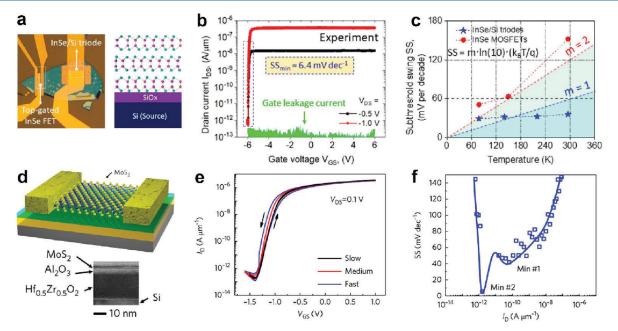


Figure 19. 2D/3D heterojunctions for logic devices. (a) 3D schematic of a 2D/3D TFET based on 2D n-type InSe and 3D p++ Si. (b) the 2D/3D heterojunction TFET was observed to have as an average SS of 34 mV/decade over four decades of drain current with a minimum SS of as low as 6.4 mV/decade. (c) Extracted SS versus temperature in InSe/Si 2D/3D heterojunction TFET. Panels (a)–(c) were reproduced with permission from ref 366. Copyright 2022 Springer Nature. (d) Schematic view of HZO/MOS₂ NCFET. (e) Transfer characteristics of the HZO/MOS₂ NCFET measured at room temperature and at drain voltage of 0.1 V at different gate voltage sweep speeds. (f) Extracted SS versus drain current in the HZO/MOS₂ NCFET. Panels (d)–(f) were reproduced with permission from ref 369. Copyright 2018 Springer Nature.

2019 exploration for highly scaled FETs, thanks to the enhanced 2020 electrostatic control over bulk 3D semiconductors due to their 2021 atomically thin bodies and self-passivated surfaces.^{359,360}

2022 However, introduction of 2D materials is quite challenging 2023 since high material quality, stable, complementary doping are 2024 not readily available for them, while Si and III-V technology is 2025 very much established in terms of doping type and doping 2026 density control.^{361,362} Hence, it is natural to explore 2D 2027 semiconductors and 3D bulk semiconductors as complementary 2028 counterparts in next-generation logic device architectures. In 2029 this regard there have been considerable efforts by the 2030 community for the exploration of 2D/3D heterojunctions for 2031 next-generation logic and memory devices.

4.2.1. Logic Devices. A fundamental thermionic limit defined 2032 2033 by the so-called Boltzmann tyranny of the subthreshold slope 2034 (SS) at 60 mV dec⁻¹ in single band transport devices such as 2035 metal-oxide-semiconductor FET (MOSFETs) not only pre-2036 cludes further scaling down the supply voltage but also increases 2037 overall power density and consumption in MOSFET-based 2038 circuits.³⁶³ Tunneling field-effect transistors (TFETs) is the 2039 primary approach to overcome the fundamental thermionic 2040 limits, in which the current conducts through band-to-band 2041 tunneling (BTBT) rather than the thermionic emission in single 2042 band transport devices.³⁶⁴ To allow strong direct BTBT 2043 transport, TFET devices are normally made of p-i-n homo or 2044 heterojunctions in which the intrinsic layer should have superior 2045 tunability subject to electrostatic modulation and ease of 2046 miniaturization in lateral dimensions.³⁶⁵ 2D semiconductors 2047 have great electrostatic control due to their ultrathin body and 2048 low static dielectric constants, which makes them ideal 2049 candidates for the intrinsic region of the TFET devices. 2050 However, unlike 3D semiconductors, the lack of stable and 2051 complementary doping in 2D materials makes the "all-2D" vdW 2052 heterojunction not compelling for the TFET device config-

uration. Hence, it is natural to combine 2D semiconductors with 2053 3D bulk semiconductors for exploring next-generation TFET 2054 architectures, in which 2D semiconductors work as the intrinsic 2055 region and the heavily doped regions are made of 3D bulk 2056 semiconductors. Miao et al.³⁶⁶ recently reported a 2D/3D 2057 heterojunction TFET as shown in Figure 19a, in which the 2058 f19 heterojunction was made of unintentionally n-doped 2D-InSe 2059 and heavily doped (p++) Si. As shown in Figure 19b, the 2D/3D 2060 heterojunction TFET was observed to have as an average SS of 2061 34 mV/decade over four decades of drain current with a 2062 minimum SS of as low as 6.4 mV/decade, which are both below 2063 the fundamental thermionic limit at 60 mV/decade. Further, the 2064 devices showed a high current on/off ratio of 10^5 for sub-60 mV/ 2065 decade and a high on-state current density of 0.3 μ A/ μ m, while 2066 most other TFETs including ones made using 2D/3D junctions 2067 have long been limited by low on/off ratios for sub-60 mV/ 2068 decade operation and low on-current density.^{367,368} The 2069 extracted SS slope in Miao et al. is nearly independent of 2070 temperature (Figure 19c),³⁶⁶ which unambiguously confirmed 2071 that the observed transport in the InSe/Si heterojunction 2072 TFETs was dominated by BTBT. 2073

Another mechanism for inducing steep SS (<60 mV/dec) 2074 switching is by adding a ferroelectric thin layer to the gate stack 2075 of a MOSFET, which is so-called negative-capacitance FET 2076 (NCFET).³⁷⁰ In a NCFET, the semiconductor channel surface 2077 potential can be amplified more than the gate voltage as the 2078 ferroelectric thin layer contributes a negative capacitance, which 2079 leads to a SS < 60 mV dec⁻¹ at room temperature in the 2080 device.^{369,370} However, it remains challenging to design a stable 2081 NCFET by proper design of capacitance matching to 2082 simultaneously achieve the steep SS and the nonhysteretic I– 2083 V characteristics. 2D semiconductors may offer a promising 2084 solution to those challenges, thanks to their low static dielectric 2085 constants, flatness of the body capacitance, and compatibility to 2086

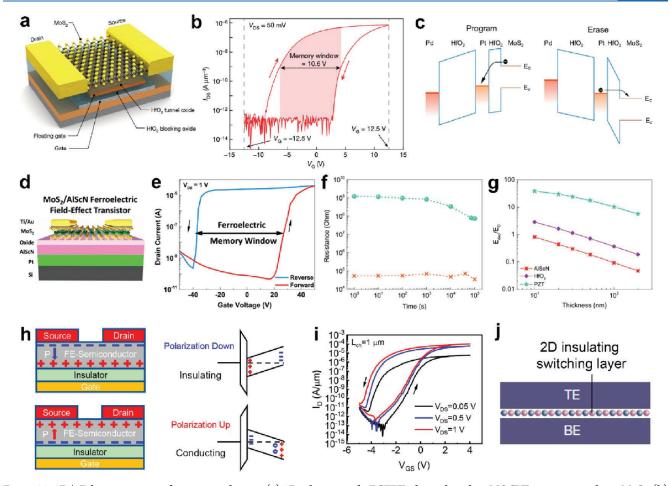


Figure 20. 2D/3D heterojunctions for memory devices. (a) 3D schematic of a FGFETs device based on MOCVD-grown monolayer MoS₂. (b) Transfer characteristic of the FGFET acquired for two different gate voltage sweep directions, showing a memory window of 10.6 V when observing at 1 nA constant current. (c) Simplified band diagrams of MoS₂ FGFETs for both programming (left panel) and erasing (right panel). Reproduced with permission from ref 374. Copyright 2020 Springer Nature. (d) Schematic view of a AlScN/MoS₂ FE-FET. (e) Transfer characteristic of the AlScN/MoS₂ FE-FET acquired for two different gate voltage sweep directions, showing a memory window more than 4 MV/cm. (f) Retention measurement on AlScN/MoS₂ FE-FET by monitoring the drain current for varying time intervals up to 10⁵ s. (g) Calculated ratio of depolarization field over coercive field in three different MoS₂ FE-FET cases: (1) AlScN/MoS₂; (2) HfO₂/MoS₂; (3) PZT/MoS₂. Reproduced with permission from ref 375. Copyright 2020 American Chemical Society. (h) Polarization charges distribution (left) and band diagram (right) in a FeS-FET in polarization down and polarization up states. (i) The demonstrated FeS-FETs showed a high on/off ratio of over 10⁸ and a large memory window of over 1 MV/cm. Reproduced with permission from ref 376. Copyright 2019 Springer Nature. (j) Illustration of an atomristor consisting of a mono or few layer TMD or h-BN sandwiched between conducting electrodes. The structure can produce nonvolatile memory effect. Reproduced with permission from ref 377. Copyright 2019 Springer Nature.

2087 the junction-less transistor architecture. Recently, Si et al.³⁶⁹ 2088 reported a 2D steep-slope transistor by using MoS₂ as a 2089 semiconductor channel and a 2D ferroelectric hafnium 2090 zirconium oxide layer (HZO) in the gate dielectric stack (Figure 19d). As shown in Figure 19e, the demonstrated MoS₂ NCFET 2091 2092 showed a steep-slope in both forward sweep and reverse sweep and it was also observed to exhibit near hysteresis-free transfer 2.093 characteristics, which indicates a good capacitance matching by 2094 2095 using an atomic thin channel in a NCFET. The SS was extracted 2096 for both forward sweep (average SS \approx 52.3 mV dec⁻¹) and reverse sweep (average SS \approx 57.6 mV dec⁻¹) and those two 2097 values <60 mV dec⁻¹ indicated subthermionic subthreshold 2098 2099 slope has been overcome and provided strong evidence that the 2100 observed steep SS is the result of a NC effect (Figure 19f).

2101 *4.2.2. Memory Devices.* The discussed advantages of 2D 2102 semiconductors not only manifest themselves in highly scaled 2103 and energy efficient logic devices and circuits but also make 2104 them appealing for transistor-backboned emerging memory

technologies such as Static Random-Access Memory (SRAM), 2105 Dynamic RAM (DRAM), and Floating-Gate FET 2106 (FGFET).^{371–373} Marega et al.³⁷⁴ reported a floating-gate 2107 memory device based on a junction-less transistor architecture 2108 with wafer-scale 2D MoS₂ as the channel and an additional metal 2109 gate as the floating gate in the gate stack, as shown in Figure 20a. 2110 f20 The gate stack (from the bottom to the top) was comprising of a 2111 bottom control gate, a 30 nm-thick 3D HfO₂ blocking oxide 2112 layer, the floating gate, a 7 nm-thick HfO₂ tunnel oxide layer, and 2113 the MoS₂ channel. The distinguishable memory states in 2114 FGFET memory are achieved by the programmable transistor 2115 threshold voltage controlled by the amount of charge stored in 2116 the 3D charge trap layer. The total shift of the memory threshold 2117 voltage was estimated to be a memory window of 10.6 V, when 2118 observed at 1 nA (Figure 20b). Further, the authors also 2119 demonstrated that various logic operations can be directly 2120 performed using the reconfigurable memory elements. Pro- 2121 gramming of the FGFETs (positive shift in the threshold 2122

2123 voltage) is achieved by injecting electrons into the floating gate 2124 with the application of a positive voltage pulse on the gate; erase 2125 of the FGFETs (negative shift in the threshold voltage) is 2126 achieved by extracting electrons from the floating gate with the 2127 application of a negative voltage pulse on the gate (Figure 20c). 2128 The ferroelectric FET (FE-FET) is another emerging 2129 memory technology that could take advantage of the 2D 2130 semiconductor-based junction-less transistor architecture when 2131 integrated with 3D crystalline ferroelectric dielectrics. In FE-2132 FETs, the information is stored by the amount of remnant 2133 polarization in a ferroelectric layer, which controls the transistor ²¹³⁴ threshold voltage in the device.³⁷⁸ Despite their emergence in 2135 1963, subsequent efforts to produce a practical, compact FE-2136 FET have been plagued by poor retention due to large 2137 depolarization fields and incompatibility with CMOS process 2138 integration.³⁷⁹ By implementing 2D semiconductors as the 2139 channel to the FE-FETs, the depolarization fields can be 2140 minimized because of their low dielectric constants, fully 2141 depleted ultrathin bodies, and the flatness of the body 2142 capacitance. In addition, due to the absence of the surface 2143 dangling bonds, vdW 2D semiconductors such as MoS₂ can be 2144 transferred via wet- or dry-transfer schemes onto arbitrary 2145 substrates at room temperature, which makes them a great 2146 candidate for transistor channel in CMOS front end of line 2147 (FEOL) and BEOL process compatible technology. Among 2148 2D/3D FE-FETs, Liu et al.³⁷⁵ has recently reported high-2149 performance devices that integrates an atomically thin MoS₂ 2150 channel on top of a 3D wurtzite structure AlScN ferroelectric 2151 (Figure 20d). The devices showed a normalized memory 2152 window of 3 MV/cm and concurrently a current on/off ratio of 2153 near 10⁶, stable memory states up to 10⁴ cycles and state 2154 retention up to 10⁵ s as shown in Figure 20e,f. 2D semiconductor 2155 channel combined with large coercive field 3D ferroelec-2156 trics^{380,381} can present as an ideal scenario for long retention 2157 in FE-FETs, as shown by the calculated ratio of depolarization 2158 field over coercive field in three different FE-FET cases in Figure 2159 20g. By theoretical simulations, Liu et al.³⁷⁵ also show that the 2160 ratio of the depolarization field over the coercive field can be less 2161 than 1, while keeping a wide and stable memory window, even 2162 the AlScN ferroelectric layer is scaled down to 10 nm, which 2163 makes them ideal also for high voltage scaled devices.

As discussed above, the depolarization field combined with 2164 2165 cycling endurance are two of the main issues slowing down the 2166 commercialization of FE-FETs in nonvolatile memory applica-2167 tions. Another option to potentially minimize the effects of the 2168 depolarization field is by using ultrathin ferroelectric semi-2169 conductors as the channel material in the ferroelectric transistor 2170 rather than using ferroelectric dielectric as gate material. Si et 2171 al.³⁷⁶ reported a ferroelectric semiconductor FET (FeS-FET), in 2172 which the polarization that stores the information in the FeS-2173 FETs exists in the α -In₂Se₃ ferroelectric semiconductor. 2174 Although FE-FET and FeS-FET have similar counter-clock 2175 hysteresis loops in their transfer curve, the operation mechanism 2176 of a FeS-FET (Figure 20h) fundamentally differs from a FE-2177 FET: in a FeS-FET, the polarization charges accumulate at both 2178 the bottom- and top-surface of the 2D ferroelectric semi-2179 conductor, and they simultaneously determine the drain current 2180 due to the ultrathin body of the 2D ferroelectrics semiconductor, 2181 while only the polarization charges at the ferroelectric/ 2182 semiconductor interface play a role in the electrostatics. The ²¹⁸³ demonstrated FeS-FETs showed a high on/off ratio of over 10⁸ 2184 and a large memory window of over 1 MV/cm with a low 2185 operation voltage as shown in Figure 20i.

In addition, 2D materials such as TMDs and h-BN are suitable 2186 to realize vertical memristors consisting of one or more layers 2187 sandwiched between 3D conductive electrodes.³⁸²⁻³⁸⁴ These 2188 memristors are sometimes referred to as atomristors (Figure 2189 20j), a colloquial term to describe resistance switching effect in 2190 an atomically thin material, with monolayer h-BN representing 2191 the thinnest memristor active layer.³⁸⁵ Since the initial 2192 atomristor report in 2017,³⁸² there have been much progress 2193 in advancing the understanding, performance, and applications 2194 of these memory devices. Atomic-resolution studies reveal that 2195 metal ion adsorption into native vacancy defects in 2D 2196 monolayers are responsible for nonvolatile resistance switching 2197 effect, arising from a phenomenon termed virtual conductive 2198 point effect,³⁸⁶ an atomic scale version of conductive bridge 2199 effect in conductive bridging random access memory (CBRAM) 2200 devices. Hence, the atomristor effect can be considered an 2201 application of defect, otherwise known as defectronics, where 2202 defect engineering can be utilized to optimize device perform- 2203 ance.³⁸⁷ It is likely alternative mechanisms could also result in a 2204 memristor effect including conductive-bridge formation from 2205 metal diffusion along GBs in few-layer 2D materials to more 2206 exotic atomic distortions that can trigger resistance switch- 2207 ing.^{388–391} 2208

The performance of 2D memristors has similarly progressed 2209 over the past years with demonstrations of low switching 2210 energies, low switching voltages, and low switching currents 2211 suitable for diverse applications.^{384,392–394} In terms of reliability, 2212 a months-long retention has been demonstrated with the 2213 potential for indefinite retention with engineered devices and 2214 interfaces.³⁹⁵ The endurance of 2D memristors is still at a 2215 nascent stage with current cyclability in the 100 to 1000 s of 2216 switching cycles for mono or few layers.³⁹² Thicker films of 2217 TMDs with partial oxidation have afforded more than a million 2218 cycles.³⁹⁶ For applications, wafer-scale demonstration of cross- 2219 bar arrays for artificial neural networks for neuromorphic 2220 computing have been reported with character recognition 2221 approaching the accuracy limit.³⁹² Likewise, nonvolatile 2222 switches for high-frequency applications in the 5G and 6G 2223 communication spectrum with a bandwidth up to around 500 2224 GHz and data transmission of 100 Gb/s has been 2225 reported.395,397 2226

5. Magnetic Topological Insulators and Twisted vdW 2227 Heterostructures. 5.1. MnBi₂Te₄: An Intrinsic Magnetic 2228 Topological Insulator. Research on quantum materials has 2229 been at the frontiers of materials science and condensed matter 2230 physics since exotic functional properties of quantum materials 2231 are not only fundamentally important but also have wide 2232 prospects for applications in information and energy tech- 2233 nologies. Magnetic topological insulators are a type of recently 2234 discovered quantum materials in which a combination of 2235 magnetism and nontrivial band topology can create a variety of 2236 topological quantum states, such as a quantum anomalous Hall 2237 insulator (QAHI) and an axion insulator.³⁹⁸ Since QAHI can 2238 support dissipationless charge transport without an external 2239 magnetic field, it carries great promise for applications in energy- 2240 saving electronic and spintronic devices. Although magnetic 2241 doping into topological insulators (TIs) and the interface 2242 magnetic proximity effect in heterostructures have been 2243 employed to demonstrate the QAHI, the chemical inhomoge- 2244 neity of magnetic doping leads to small exchange gaps,^{399,400} 2245 thus limiting the working temperature of the quantum 2246 anomalous Hall state. This disadvantage has inspired the search 2247 for topological materials with intrinsic magnetism. 2248

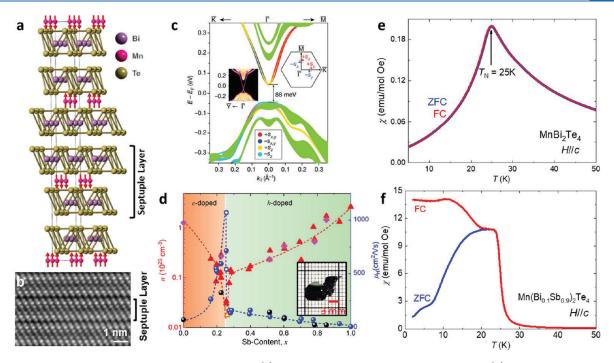


Figure 21. Crystal and magnetic properties of magnetic TIs. (a) Crystal and magnetic structure of MnBi₂Te₄. (b) HAADF-STEM image taken from the [100] zone axis of MnBi₂Te₄. Reproduced with permission under a Creative Commons Attribution 4.0 International license from ref 404. Copyright 2019 American Physical Society. (c) Spin-resolved electronic structure of the MnBi₂Te₄ (0001) surface. Reproduced with permission from ref 401. Copyright 2019 Springer Nature. (d) Composition dependence of carrier density *n* and transport mobility $\mu_{\rm H}$ of Mn(Bi_{1-x}Sb_x)₂Te₄. Inset: Flux-grown crystals' image. Reproduced with permission under a Creative Commons Attribution 4.0 International license from ref 410. Copyright 2021 American Physical Society (e, f) Field-cooled (FC) and zero-field-cooled (ZFC) temperature dependences of magnetic susceptibility χ with magnetic field aligned parallel to the *c*-axis (H//c) for (e) MnBi₂Te₄⁴⁰⁴ and (f) Mn(Bi_{0.1}Sb_{0.9})₂Te₄, respectively. Panel (f) was reproduced with permission from ref 411. Copyright 2020 American Physical Society.

 $_{2249}$ $MnBi_{2}Te_{4}$ has recently been investigated as an emerging $_{2250}$ intrinsic magnetic TI. $^{401-403}$ It is a layered ternary tetradymite compound, crystallizing in a rhombohedral structure with the 2251 space group R3m, and its structure is built of the stacking of Te-2252 Bi-Te-Mn-Te-Bi-Te septuple layers (SLs) along the c-axis 2253 2254 (Figure 21a,b). Given that the SLs are coupled through the 2255 vdW force, MnBi₂Te₄ can be easily exfoliated into thin flakes. 2256 This material exhibits an antiferromagnetic (AFM) order below $_{2257}$ T_N = 25 K (Figure 21e), with in-plane ferromagnetic (FM) 2258 coupling and out-of-plane AFM coupling.⁴⁰⁴ Such a magnetic 2259 order is intimately coupled with band topology, which was 2260 predicted to yield a large exchange gap (Figure 21c) and various 2261 topological quantum states, as discussed below. Since MnBi₂Te₄ 2262 is a metastable phase, its crystal can be obtained only by 2263 quenching the crystals grown in the slowly cooling down process of the melt with a stoichiometric composition.^{401,404} However, 2264 2265 single crystals grown using this method are small and thin. The 2266 other problem with this method is the presence of intergrowth 2267 between MnBi₂Te₄ and Bi₂Te₃. Soon after, Yan et al.⁴⁰⁵ 2268 developed an effective growth protocol for growing large 2269 MnBi₂Te₄ crystals. They used Bi₂Te₃ as a flux to grow MnBi₂Te₄ 2270 crystals. Crystals grown using this flux method have significantly 2271 larger lateral dimensions (up to a few millimeters) and can be easily exfoliated, which is critical to nanodevice fabrications and 2272 exploration of emerging topological quantum states in its 2D 2273 2274 limit. The availability of such high-quality crystals has enabled 2275 observation of various topological quantum states in MnBi₂Te₄, 2276 including the QAHI, the axion insulator, the high number of 2277 Chern insulators (C = 2), as well as the layer Hall effect.⁴⁰⁶⁻⁴⁰⁹

In addition to the 2D topological states noted above, 2278 $MnBi_2Te_4$ is also predicted to host a long-sought, ideal time- 2279 reversal symmetry breaking Weyl semimetal (WSM) with one 2280 pair of Weyl nodes in bulk when its AFM order is coerced into 2281 FM order by a magnetic field parallel to the *c*-axis.^{402,403} Zhang 2282 et al.⁴⁰² suggest that this FM WSM can be either type-I or type- 2283 II, depending on the lattice parameters. Recent theoretical 2284 studies further predict that such a Weyl state can be tuned by the 2285 field orientation but disappears as the field is rotated to the in- 2286 plane direction.⁴¹² However, there has been no experimental 2287 evidence that supports the presence of the Weyl state in the FM 2288 phase driven by the *c*-axis magnetic field in $MnBi_2Te_4$. This is 2289 because the Weyl nodes are far from the Fermi surface due to 2290 self-doping effects in pristine $MnBi_2Te_4$.^{404,405} 2291

Several groups have shown that it is possible to tune the 2292 chemical potential of MnBi₂Te₄ by doping Sb to the Bi site, 2293 similar to the (Bi,Sb)₂Te₃ system.^{410,413,414} Lee et al.⁴¹⁰ have 2294 shown that single crystals of Mn(Bi_{1-x}Sb_x)₂Te₄ (MBST, $0 \le x \le 2295$ 1) with controlled chemical potentials can be grown using 2296 Sb₂Te₃-Bi₂Te₃ as a flux, similar to the growth protocol reported 2297 by Yan et al.⁴¹⁴ To achieve a desired chemical potential, the Sb 2298 concentration and the temperature for centrifuging need to be 2299 tuned to appropriate values. Empirically, large MBST single 2300 crystals with lateral dimensions being up to 10 mm can be grown 2301 using the molar ratio of Mn:Sb:Bi:Te in 1:5*x*:5(1-*x*):16.^{410,413} 2302 Carefully tuning of the centrifugation temperatures for each *x* is 2303 critically important since the melting points of both fluxes and 2304 Mn(Bi_{1-x}Sb_x)₂Te₄ are very close. Given that the melting points 2305 of Bi₂Te₃ and Sb₂Te₃ are 585 and 620 °C, respectively, the 2306 excessive flux is separated by centrifuging in the range of 590 to 2307

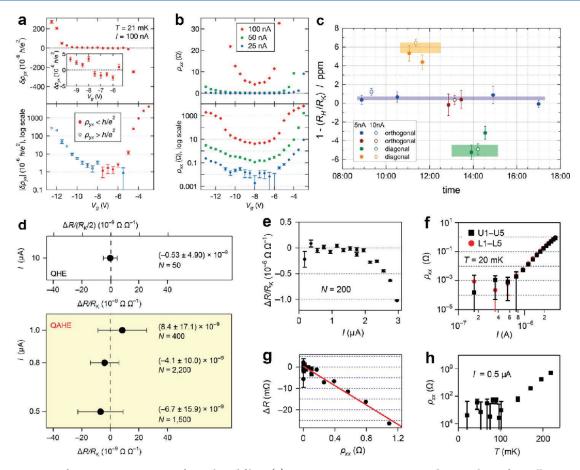


Figure 22. Summary of QAHE measurements of MTI-based films. (a) Cryogenic current comparator data are shown for Hall measurements in an example device using a 100 nA current at 21 mK. The plateau in the upper panel shows the deviation from $R_{\rm v}$. The inset shows a magnified view of the Hall resistance deviations in the center of the plateau ($\nu = 1$). The bottom panel shows the logarithmic behavior of the deviations as one departs from the optimal gate voltage. (b) The longitudinal resistivity for the same device. Data are displayed on a linear and log scale in the top and bottom panels, respectively. All error bars show the standard uncertainty and are omitted when they are smaller than the data point. Reproduced with permission from ref 424. Copyright 2018 by the American Physical Society. (c) Topological insulator at the $\nu = 1$ plateau data. Currents of 5 and 10 nA were used in both orthogonal and diagonal configurations. The colored rectangles represent the weighted average and standard deviation of the data from those configurations. Reproduced from ref 422 with the permission of AIP Publishing. (d-h) Quantization accuracy of the QAHE-based resistance standard. (d) The normalized deviation $\Delta R/R_{\rm K}$ are shown (top panel shows conventional quantum Hall effect). The error bars correspond to the combined standard uncertainty and N denotes the number of data points used for averaging. (e) The dependence of $\Delta R/R_{\rm K}$ on the source-drain current (I) is shown, with the error bars corresponding to the standard deviation of N = 200 measurements. (f) The current dependence of the longitudinal resistance (ρ_{xx}) is shown at a temperature of 20 mK. The longitudinal resistivity was measured by using the upper (U1-U5) and lower (L1-L5) pairs of voltage contacts. The error bars are the standard deviation of N = 20measurements. (g) The relationship between ΔR and ρ_{xx} shown with a red line as the linear fitting result. (h) Temperature dependence of ρ_{xx} measured at 0.5 μ A using the upper pair of voltage contacts (U1–U5). The error bars are the standard deviation of N = 20 measurements. Reproduced with permission from ref 423. Copyright 2022 Springer Nature.

2308 620 °C, depending on *x*. Higher centrifugation temperatures are 2309 used for the samples with higher Sb content. It is worth noting 2310 that ramping down quickly below the solidification temperatures 2311 and then ramping up to the desired centrifugation temperature 2312 in higher Sb-content alloy can lead to high density of Mn 2313 occupation at the Sb sites (e.g., antisite defects), which favors a 2314 ferromagnetic exchange between Mn layers.^{411,415–417}

2315 While MnBi₂Te₄ is electron-doped, as the Sb concentration 2316 increases, the chemical potential of Mn(Bi_{1-x}Sb_x)₂Te₄ is tuned 2317 from the bulk conduction band to the bulk valence band passing 2318 through the charge neutral point near *x* equal to 0.3. Through 2319 fine-tuning of chemical potential by Sb substitution for Bi, Lee et 2320 al.⁴¹⁰ observed transport hallmarks of the predicted ideal Weyl 2321 state in the lightly hole-doped samples with *x* = 0.26 (Figure 2322 21d), including a large intrinsic anomalous Hall effect and chiral 2323 anomaly. The Weyl state in Mn(Bi_{1-x}Sb_x)₂Te₄ is of particular interest because it is the least complicated possible manifestation 2324 of a Weyl phase, hosting only one pair of Weyl nodes at the 2325 Fermi level and having no interference from other trivial bands 2326 near the Fermi level. Therefore, it is an ideal model system for 2327 further study of Weyl Fermion physics. The magnetic phase of 2328 $Mn(Bi_{1-x}Sb_x)_2Te_4$ is also dependent on Sb concentration. For *x* 2329 < 0.9, the systems exhibit an *A*-type AFM order similar to that 2330 seen in the pristine compound MnBi₂Te₄. However, for $0.9 \le x$ 2331 ≤ 1.0 , an FM phase with $T_c = 26-46$ K (Figure 21f) is accessible 2332 due to the Mn-Sb antisite defect-mediated layered FM coupling, 2333 as noted above.⁴¹⁵⁻⁴¹⁷ The realization of the FM phase in MBST 2334 is an important step toward understanding intrinsic ferromagnetic topological insulators, which opens up opportunities for 2336 engineering topological states in this vdW ferromagnet and 2337 related family members MnBi₂nTe_{3n+1}. 238

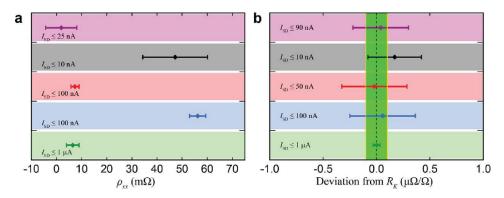


Figure 23. Summary of the precision measurements of (a) ρ_{xx} and (b) the QAHE over the previous few years. Applied currents vary, and the following MTI measurements are represented: 2018 NIST/Stanford (purple),⁴²⁴ PTB/UW (black),⁴²² 2022 NIST/Stanford (red and blue),⁴²⁷ and 2022 NMIJ and partners (olive).⁴²³ The light green region in panel (b) marks the boundary for data points going beneath one part in 10⁷. All error bars represent k = 1 type A and B combined uncertainties. Adapted with permission under Creative Commons Attribution 4.0 International license from ref 427. Copyright 2022 American Physical Society.

5.2. Quantum Anomalous Hall Effect in Magnetically 2339 2340 Doped Topological Insulators. The quantum Hall effect has 2341 been in the eye of the scientific community for nearly half a 2342 century, and materials hosting a 2D electron system could 2343 exhibit it. Graphene and gallium arsenide heterostructures were 2344 among the more popular material systems for performing 2345 quantum Hall research. Many applications of the quantum Hall 2346 effect, notably electrical metrology, have required strong 2347 magnetic fields for the quantized plateaus to be exhibited in a 2348 robust way.⁴¹⁸ This requirement has limited the extent to which 2349 an experimental apparatus may be simplified, namely in the 2350 necessity of an electromagnet. Emerging thin materials, like 2351 magnetically doped topological insulators (MTIs), are known to 2352 exhibit the quantum Hall effect at zero magnetic field. This 2353 phenomenon, known as the quantum anomalous Hall effect (QAHE), is linked to the breaking of time-reversal symmetry 2354 2355 and the opening of an energy gap that can accommodate the 2356 existence of topological surface states.^{419–421}

Under typical circumstances, the formed energy gap closes in 2357 2358 physical locations where the component of the magnetization 2359 normal to the surface changes direction. This implies that for 2360 material systems nearing the 2D limit, assuming they have 2361 relatively uniform out-of-plane magnetization, this transition 2362 occurs at the edges of the material system. Therefore, the edges 2363 of a suitable material system would then enable the OAHE to be 2364 exhibited and observed. Electrically, its longitudinal transport 2365 would be ideally dissipationless given that its corresponding 2366 quantization conditions are $\sigma_{xy} = e^2/h$ and $\sigma_{xx} = 0$. Thus, in the 2367 context of metrology, the QAHE could become the basis for a 2368 future resistance standard, at most needing only a small ²³⁶⁹ permanent magnet to activate a quantized resistance ²³⁷⁰ value.⁴²²⁻⁴²⁴ Ultimately, such metrologically suitable devices 2371 could operate at zero-field for measurements, making the 2372 dissemination of the ohm more economical and portable.

²³⁷³ The details of how the QAHE arises are obviously more ²³⁷⁴ nuanced when compared with the conventional integer ²³⁷⁵ quantum Hall effect. As summarized by Kou et al.,⁴²⁵ there are ²³⁷⁶ two main approaches for introducing magnetic exchange that ²³⁷⁷ allows one to break surface states' time-reversal symmetry. The ²³⁷⁸ first approach is by means of magnetic proximity, typically ²³⁷⁹ achieved by adding in a topologically trivial magnetic material, ²³⁸⁰ which locally aligns the relevant electrons' spin moments out of ²³⁸¹ plane. The second approach involves the incorporation of ²³⁸² magnetic ions into the host material system.⁴¹⁹ Currently, MTIs that are used in electrical metrology have been grown by 2383 MBE, ⁴²⁶ presumably due to the method's advantages vis-à-vis its 2384 nonequilibrium physical deposition, accurate layer thickness and 2385 doping control, and wafer-scale growth capability. 2386

As mentioned earlier, most quantum Hall applications based 2387 on graphene devices will generally need a sufficiently strong 2388 magnetic field to observe any robust quantum behavior. This 2389 limitation is inherently tied to the band structure of graphene. 2390 However, with the QAHE, one may observe a physical 2391 manifestation of a material's topologically nontrivial electronic 2392 structure without needing an electromagnet to break time- 2393 reversal symmetry. There are several types of materials that 2394 exhibit the QAHE, with some being classified among the 2395 following categories: doped MTIs, intrinsic MTIs, and twisted 2396 vdW layered systems. Some key recent results involve materials 2397 that display a quantized resistance plateau at zero-field suitable 2398 for metrology measurements, with some recent work already 2399 mentioned.^{422,424} 2400

Recent work by Fox et al.⁴²⁴ explored the metrological 2401 applicability of the QAHE in a MTI-based thin film. Using a 2402 cryogenic current comparator, or an apparatus that allows for the 2403 precise comparison of two electrical currents (and thus, two 2404 resistances), the group measured the quantization of the Hall 2405 resistance to within one part per million and, at smaller electrical 2406 currents, measured the longitudinal resistivity to be under 10 2407 m Ω at zero magnetic field. Some of these acquired data are 2408 shown in Figure 22a.b. A breakdown of the quantized state was 2409 f22 induced by gradually increasing the current density past a critical 2410 value. It was thought that this effect was due to electron heating 2411 in parallel bulk current flow. This work furthered the 2412 understanding of MTIs by gaining comprehension for the 2413 physical mechanisms that ultimately contribute to these devices' 2414 limitations, including thermal activation, bulk dissipation, and 2415 variable-range hopping. Gotz et al.⁴²² also sought to present a 2416 metrologically comprehensive measurement at zero-field of a 2417 MTI (in this case, it was V-doped (Bi,Sb)₂Te₃). When the 2418 difference of the QAHE resistance was measured as compared to 2419 the von Klitzing constant ($R_{\rm K}$), a value of 0.176 $\mu\Omega/\Omega \pm 0.25_{2420}$ $\mu\Omega/\Omega$ was obtained. Some of these data are shown in Figure 2421 22c. 2422

Two other recent works surrounding MTIs and the quality of 2423 their exhibited QAHE plateaus come from Okazaki et al. and 2424 Rodenbach et al.^{423,427} In the former, the group demonstrates a 2425 precision of 10 n Ω/Ω for the $\nu = 1$ plateau of the QAHE. 2426

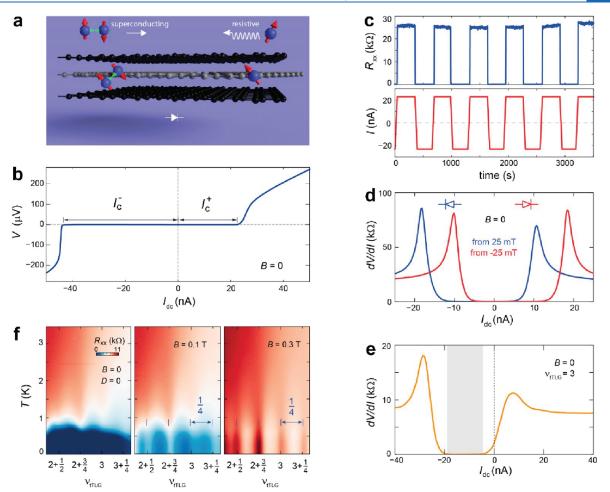


Figure 24. Nonreciprocity and superconducting diode effect. (a) Schematic diagram showing the superconducting diode effect. Cooper pairing is only stable when current flows from left to right. As a result, the transport response across the sample is dissipationless when current flows from left to right, whereas a resistive behavior is observed when current direction is reversed. (b) Differential resistance as a function of DC current bias of the superconducting phase at B = 0. I_c^+ and I_c^- are the critical current with positive and negative DC current bias, respectively. The asymmetry in I_c^+ and I_c^- shows the nonreciprocity. (c) Demonstration of robust zero-field superconducting diode effect. (d, e) Field-training of the superconducting diode: (d) After a positive (negative) field training, the superconducting diode remains as a reverse (forward) diode as shown in the blue (red) curve. (e) Extremely high diode efficiency at large doping, as the zero-resistance regime (shaded part) has shifted totally to the negative current side. (f) Interplay between superconductivity and density-wave state. Longitudinal resistance as a function of temperature and doping, at different magnetic fields. As the magnetic field increases, superconductivity is suppressed and density-wave state (resistance oscillations with 1/4 periodicity) takes over at the low temperature range. Adapted with permission from ref 440. Copyright 2022 Springer Nature.

2428 from a conventional device to confirm their observations. These results are shown in Figure 22d-h. In Rodenbach et al.,427 extensive analyses on the surrounding elements of metrological 2430 2431 measurements, namely noise measurements, are summarized 2432 and shown in Figure 23. These works are crucial to understand for eventually realizing a zero-field quantum resistance standard. 2433 One of the last remaining limitations to be lifted are the stringent 2434 2435 temperature requirements, which are currently in the 10 to 100 2436 mK range. Fijalkowski et al.428 show that the chiral edge channels associated with the QAHE continue to exist without 2437 applied magnetic field up to the Curie temperature (about 20 K) 2438 2439 of bulk ferromagnetism in their TI system. This conclusion was 2440 reached through a careful analysis of nonlocal voltages in 2441 Corbino-type devices. It was also found that thermally activated 2442 bulk conductance was mostly responsible for quantization 2443 breakdown.⁴²⁸ These results show promise on the availability of

2427 Furthermore, they directly compared both the QAHE and QHE

topological protection from MTI edge channels for developing a 2444 resistance standard. 2445

5.3. Superconducting Diode Effect in Twisted Trilayer- 2446 Graphene Homojunctions. Within BCS theory and for most 2447 known superconductors, time-reversal symmetry is a key 2448 ingredient to the formation of Cooper pairs. ^{429,430} Nonetheless, 2449 superconductivity can survive moderate time-reversal symmetry 2450 breaking perturbations, e.g., resulting from the proximity to a 2451 ferromagnet or from an applied external magnetic field. The 2452 microscopic coexistence between superconductivity and 2453 ferromagnetism in a single electron liquid, however, is very 2454 rare in nature. ⁴³¹⁻⁴³³ Time-reversal symmetry also implies that 2455 the critical current for forward, I_c^+ , and backward direct current 2456 (DC) bias, I_c^- , are identical. If, however, it is broken in the 2457 superconductor along with inversion symmetry, $I_c^+ \neq I_c^-$ becomes 2458 possible. In that case, applying a DC current I_{DC} with $|I_{DC}|$ 2459 between I_c^- and I_{c}^+ , will lead to dissipationless superconducting 2460 transport for one sign of I_{DC} and resistive behavior for the other. 2461

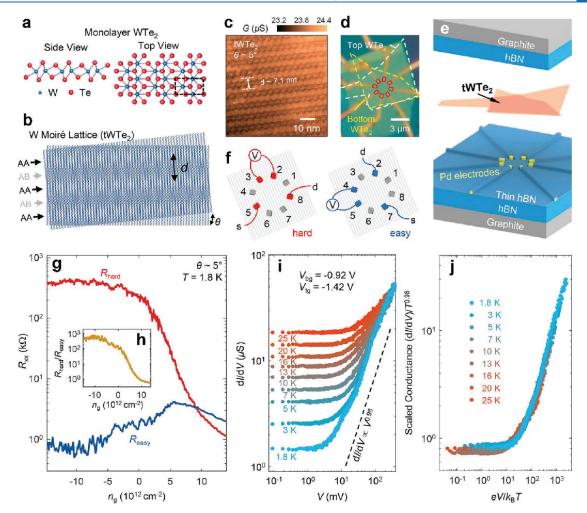


Figure 25. Luttinger liquid behavior in tWTe₂ moiré system. (a) The crystal structure for monolayer WTe₂. The W atoms are sandwiched by two Te atom layers. From the top view, the W atoms (blue) form zigzag chains. The dashed square denotes the unit cell. (b) Moiré superlattice of tWTe₂, where only the W atoms are shown. The alternating AA and AB 1D stripes are illustrated. (c) conductive AFM image of a tWTe₂ sample. (d) Optical image of a typical device, with the contact regions marked with red solid lines and the two layers of WTe₂ with yellow and white dashed lines, respectively. (e) Cartoon illustration of the device structure. From bottom to top: bottom graphite, bottom hBN, electrodes, thin hBN, tWTe₂, top hBN, and top graphite. (f) Measurement configuration for the hard and easy directions. The squares denote the contacts, and the gray lines indicate the moiré stripes. s, source; d, drain. (g) Four-probe resistance of the hard and easy direction shown in panel (f), measured at 1.8 K, as a function of the gate-induced doping density n_g of the device. (h) The anisotropy ratio, R_{hard}/R_{easy} with R_{hard} and R_{easy} in g, versus n_g . (i) The across-wire differential conductance dI/dV measured under different d.c. bias and temperature, with the doping fixed on the hole side. (j) Scaled differential conductance $(dI/dV)/T^a$, plot against eV/k_BT (same data in panel (i)), showing that all the data collapse into one curve. Adapted with permission from ref 453. Copyright 2022 Springer Nature.

Such "superconducting diode" behavior has been reported in previous works where time-reversal symmetry is explicitly 2463 broken by applying an external magnetic field or proximitizing 2464 with a magnetic material.⁴³⁴⁻⁴³⁶ Alternatively, diode effect has 2465 2466 been demonstrated in Josephson junctions. 437-439 Notably, the 2467 superconducting diode effect at zero-field in a uniform, junction-2468 free sample would be a strong indication of the microscopic 2469 coexistence between superconductivity and spontaneous time-2470 reversal symmetry breaking. Such a zero-field superconducting 2471 diode effect was recently observed in small twisted angle trilayer graphene,⁴⁴⁰ where the authors demonstrated a prominent 2472 diode effect that was intrinsic to the superconducting phase and 2473 could reach reasonably large current asymmetries, with $|I_c^+ - I_c^-|/$ 2474 2475 $(I_c^+ + I_c^-)$ approaching 1.

2476 In the mirror-symmetric twisted trilayer graphene (tTLG) 2477 sample (Figure 24a), the middle graphene layer is rotationally 2478 misaligned with the outer layers by an angle of θ = 1.25°, which is detuned from the magic angle of 1.55° .⁴⁴⁰ The zero-field 2479 superconducting diode is evidenced by the nonreciprocal 2480 current–voltage characteristic, as shown in Figure 24b. At B = 24810, the superconducting critical current, defined as the peak 2482 position in the differential resistance dV/dI, is around 10 nA 2483 with forward biased current flow but increases dramatically to 2484 around 90 nA when the current flow is reversed. Such 2485 nonreciprocity enables a diode-like switching between dis- 2486 sipationless and resistive transport behaviors, when a DC 2487 current of 22 nA alternates between forward and reverse bias 2488 directions, as shown in Figure 24c. Notably, the alternating 2489 behavior remains robust for more than an hour, indicating that 2490 the zero-field superconducting diode effect is nonvolatile. 2491

As shown in Figure 24d, the sign of nonreciprocity at zero- $_{2492}$ field can be reversed by training with an external magnetic field. $_{2493}$ After training with a negative magnetic field of -25 mT, which is $_{2494}$ then set to zero, the superconducting phase behaves like a $_{2495}$

2496 forward diode, with the critical current being larger with a 2497 positive DC current bias. Conversely, a reverse diode behavior is 2498 observed after training with a positive magnetic field of 25 mT. 2499 The dependence on the magnetic field history offers 2500 unambiguous evidence for an underlying spontaneous time-2501 reversal symmetry breaking. Moreover, a prominent diode effect 2502 is observed throughout the density regime of the super-2503 conducting phase, indicating an origin that is intrinsic to the 2504 moiré system.⁴⁴⁰ An extreme nonreciprocal behavior can be 2505 achieved by tuning the carrier concentration of the system by 2506 electrostatic doping. As shown in Figure 24e, the sample is 2507 resistive at zero current bias but becomes superconducting in the 2508 presence of a negative DC current bias.

Since the presence of either time-reversal or 2-fold rotation/ 2509 2510 inversion symmetry guarantees reciprocal superconducting 2511 transport, the zero-field superconducting diode effect implies 2512 that both time-reversal and 2-fold rotation symmetry are broken 2513 in the superconducting state of the tTLG sample. The 2514 mechanism underlying the superconducting diode effect is 2515 therefore constrained by these broken symmetries, which can be 2516 understood by considering the possible symmetry-breaking 2517 instabilities of moiré electrons.⁴⁴⁰ The simplest possible scenario 2518 is that the system spontaneously develops an imbalance of its 2519 two valleys, which breaks both of the aforementioned 2520 symmetries. Then, a superconducting phase emerging from a 2521 valley-imbalanced Fermi surface will exhibit a zero-field 2522 superconducting diode effect. Due to the multitude of internal 2523 "flavor" degrees of freedom—resulting from the spin, valley, and 2524 conduction-valence-band quantum numbers of the band ²⁵²⁵ structure—there is a whole plethora of such possible candidate ²⁵²⁶ instabilities in tTLG.^{440,441} A careful consideration of the ²⁵²⁷ trainability of the observed diode effect⁴⁴⁰ leaves only a single 2528 candidate phase that is symmetry-equivalent to the valley-2529 imbalance case discussed above.

The zero-field superconducting diode effect is observed in the 2530 2531 so-called small twisted angle regime. In stark contrast with the 2532 magic-angle regime, the phenomenon of Dirac revival is mostly 2533 absent in the small twist angle regime. Instead of correlated 2534 insulators appearing at every integer moiré filling, the moiré 2535 band is populated with density wave states that exhibit a density 2536 modulation of 1/2 and 1/4 moiré fillings. This gives rise to an 2537 interesting coexistence between the superconducting and 2538 density wave states. As superconductivity is suppressed by the 2539 application of an external magnetic field, a series of density wave 2540 states are evidenced by the observation of resistance peaks 2541 appearing at integer multiple of 1/4 moiré filling,⁴⁴⁰ as shown in 2542 Figure 24f. The onset temperature of these resistance peaks, 2543 which defines the melting transition of the underlying density 2544 wave order, coincides with the transition temperature of the 2545 superconducting phase. It is argued that these density-wave 2546 states likely compete against the superconducting state, since the 2547 critical temperature of the superconducting phase do not show 2548 the same density modulation as the density wave order. 2549 Nevertheless, the simultaneous presence of the density wave 2550 order and the superconducting phase in the phase space of the 2551 small-angle tTLG provides more constraints for theoretical 2552 models aiming to understand the origin of superconductivity in a 2553 graphene moiré band.

In summary, the intrinsic zero-field superconducting diode sss effect in small-angle tTLG demonstrates the microscopic coexistence of superconductivity and spontaneous time-reversal ssr symmetry breaking. This discovery not only provides a platform sss with superconducting diode effect for potential applications but also draws our attention to the unique behavior of the 2559 superconductivity in this system and hopefully brings us closer 2560 to deciphering the nature of strongly correlated moiré physics. 2561

5.4. Moiré Luttinger Liquids in Twisted WTe₂ Bilayers. The 2562 Luttinger liquid (LL) model^{442,443} offers a powerful tool to 2563 study interacting electrons in 1D metals, which are distinct from 2564 2D or 3D metals that are typically captured by the Fermi liquid 2565 theory. An interesting question is whether the LL physics could 2566 be stabilized down to the lowest temperature in some strongly 2567 correlated 2D or 3D systems, as investigated by Philip W. 2568 Anderson.⁴⁴⁴ Approaches based on coupled-wire models,⁴⁴⁵ 2569 which consist of a 2D array of 1D LLs, have been developed to 2570 investigate this fundamental question theoretically. $^{445-449}$ The $_{\rm 2571}$ experimental realization of high-quality arrays of 1D wires 2572 necessary for investigating various coupled wire models remains 2573 challenging as they require many identical wires to be strictly 2574 arranged with crystalline quality at both nano and microscopic 2575 scales. Experimental tests of many interesting ideas^{450–452} along 2576 this direction remain uncharted. 2577

Significant experimental progress has been made recently 2578 based on 2D moiré quantum engineering. The study utilizes a 2579 unique moiré material consisting of twisted bilayer WTe₂ 2580 (tWTe₂).⁴⁵³ With an elongated rectangular unit cell, monolayer 2581 WTe₂ is known to exhibit rich physics including top- 2582 ology,⁴⁵⁴⁻⁴⁵⁶ superconductivity,^{457,458} and strong correla- 2583 ology, $^{454-456}$ superconductivity, 457,458 and strong correla- 2583 tions. 459,460 As shown in Figure 25a, 2D WTe₂ has a sandwiched 2584 f25 structure, in which the middle layer hosts the W atoms that form 2585 1D zigzag chains. Figure 25b illustrates the moiré superlattice of 2586 the tWTe₂ twisted at a small angle of near 5° (for simplicity, only 2587 the two layers of W atoms of tWTe₂ are shown). Clearly, the 2588 moiré supercell is an enlarged rectangle, with a size tunable by 2589 twist angles. Figure 25c confirms the formation of such an 2590 anisotropic moiré pattern via a conductive atomic force 2591 microscopy image. Transport studies indeed revealed a highly 2592 anisotropic phase and LL behaviors in the hole-rich state of 2593 tWTe₂ devices near this twist angle.⁴⁵³ With carefully designed 2594 and fabricated devices (Figure 25d,e), Wang et al.453 showed 2595 that an exceptionally large transport anisotropy with a four- 2596 probe resistance ratio of close to 10^3 along the two orthogonal 2597 directions (Figure 25f) was observed in the hole-doped regime 2598 (Figure 25g,h) but not in the electron-doped regime. Moreover, 2599 the across-wire conductance obeys power-law dependence on 2600 temperature down to 1.8 K, and the differential conductance 2601 under varying applied d.c. bias and temperature shows the 2602 universal power-law scaling behavior (Figure 25i,j) expected for 2603 LL physics.⁴⁴² Both the anisotropy and the interaction strength 2604 are highly tunable in the tWTe₂ moiré structure, by knobs, e.g., 2605 doping density and twisted angle.⁴⁵³ The tWTe₂ system offers a 2606 high-quality, high-controllable platform for studying the 2607 intriguing physics related to various coupled-LL models.

An immediate question from the moiré LLs in the tWTe₂ is 2609 whether such a 2D anisotropic LL behavior could be stabilized 2610 down to millikelvin temperature, one crucial question in the 2611 study of non-Fermi liquid physics.^{446–448} An exciting future 2612 direction is to search for unconventional quantum oscillations 2613 and quantum Hall states in such a non-Fermi liquid 2614 system.^{449–451} The physics of spin-charge separation^{442,443} is 2615 another interesting direction to pursue here in such a 2D setting. 2616 Other predictions in coupled wire models, including topological 2617 phases⁴⁶¹ and quantum spin liquids,⁴⁶² are also of potential 2618 future interest. On the material side, ventures in other 2619 rectangular moiré lattices, such as twisted GeSe,⁴⁶³ twisted T_{d} - 2620 MoTe₂, twisted phosphorene, T_{d} -MoTe₂/ T_{d} -WTe₂ hetero- 2621

2622 structure, also deserve careful studies as they may develop 2623 similar phenomena.

2624 PERSPECTIVES AND FUTURE WORK

2625 This review provides the recent progress of theory, synthesis, 2626 heterostructures, characterization, sensing, devices, and physical 2627 properties of 2D materials. There continue to be many 2628 interesting breakthroughs in recent months and years, including 2629 MD simulations and machine learning for 2D materials synthesis 2630 and applications. Theory is becoming inseparable from 2631 experimental studies and is now key to design materials, predict 2632 device performances, and optimize processing. Additionally, 2633 remote epitaxy using 2D materials as the intermediate layer and 2634 wafer-scale synthesis of 2D TMDs by MOCVD also established 2635 their own fields and continue to emerge. However, as we are 2636 moving forward in 2D materials' science and technology, many 2637 challenges still require interdisciplinary efforts and collabo-2638 rations to be addressed. For examples, some challenges 2639 regarding synthesis of high-quality 2D films and introduction 2640 of magnetic properties into TMDs have been mentioned in 2641 sections 2.7 and 2.9, respectively. Here, we provide perspectives 2642 on the future research directions that we may pursue.

2643 **Material Theory.** Computationally we find that intercala-2644 tion, doping, and defects provide an efficient platform for 2645 tailoring 2D materials' properties. However, for intercalation, 2646 there are still open questions about staging and cointercalation 2647 in common materials such as multilayer graphene, which could 2648 potentially provide further property control. Defects, on the 2649 other hand, can be difficult to simulate at the atomic level, 2650 especially when working with charged point defects, where long-2651 range artificial interactions occur. There are several schemes that 2652 have been proposed to correct for this; however, it is still an 2653 unanswered question and requires continuous investigation.

Artificial Intelligence and Machine Learning for 2D 2654 2655 Materials. While many solutions have been devised in the 2D 2656 material world with the utilization of ML, the field of condensed 2657 matter still has a lot of room to grow with these mathematical 2658 tools. As demonstrated in recent publications,⁵⁸ it becomes 2659 apparent that ML algorithms could conceivably be trained to 2660 refine potential energies in DFT calculations, suggesting a 2661 feasibility to derive a generalized exchange correlations through 2662 ML-arguably the holy grail of DFT work-thus reducing 2663 computational load and greatly increasing accuracy. In synthesis, 2664 Bayesian optimization (BO) seems to be the prevailing 2665 technique. Though, it could be noted that-with a high 2666 computational cost-it would be beneficial to migrate away 2667 from BO and toward neural networks. Unfortunately, without 2668 any training data or a large quantity of pre-existing samples, this 2669 is not possible. Therefore, a proposed solution could be to 2670 mimic the theoretical community in devising an open, 2671 centralized, and normalized database structure. In case of 2672 applications, availability of diverse ML tools on 2D materials and 2673 devices provides the exciting possibility that not only will be we 2674 able to improve traditional applications but also explore 2675 autonomous material synthesis and processing.

2676 **Optimizing ReaxFF Parameters with Guidance from** 2677 **Machine Learning.** Developing the ReaxFF force field, like 2678 other empirical potentials, has been challenging due to the 2679 many-body character of the potential energy function and the 2680 high dimensionality of the force field parametrization. Obtaining 2681 an accurate, transferable, and efficient ReaxFF is therefore 2682 critical to atomic scale simulations. Molecular dynamics 2683 simulations are an effective method to test the performance of a force field at hand. In the future, a data-driven approach that 2684 combines ML, DFT, *ab initio*, and classic MD simulations needs 2685 to be developed for active learning of force field. Besides the ML 2686 algorithm, inclusion of *ab initio* MD simulations to this 2687 framework will significantly accelerate the force field develop- 2688 ment process, particularly for gas-phase reactions. ML will 2689 automate the force field training work flow which consists of the 2690 evaluation of models taken from MD simulations in comparison 2691 with DFT and the identification of the non-DFT matched data, 2692 followed by the generation of DFT data and their addition to 2693 training set in order to reoptimize force field parameters. Thus, it 2694 is necessary to enhance the accuracy and quality of force field 2695 parameters by active learning.

Automatic Analysis of ReaxFF Simulations with 2697 Machine Learning. Studies using MD simulations usually 2698 require large-size and long-time runs that generate large 2699 amounts of data. Their postprocessing, especially when the 2700 investigation is coupled with rare events of interest like chemical 2701 reactions, costs significant efforts. Machine learning methods 2702 can automate analysis of ReaxFF simulations, helping with 2703 extracting and classifying outliers and unique features in 2704 simulations of materials. Our future work will focus on ML 2705 automated postprocessing of ReaxFF simulations to better 2706 manage and interpret our data, then connecting them to 2707 experimental efforts. 2708

Continuous Exploration of MXenes Properties. In 2709 section 2.1, we learn that the family of MXenes is enormously 2710 large. There is still significant work to be done to understand the 2711 relationship between their chemistry and properties. While more 2712 than 30 stoichiometric MXenes have been discovered, in 2713 addition to a variety of solid-solution MXenes, there is still 2714 ample room for exploring MXenes. Computationally it is 2715 expected that there will be more ordered and solid-solution 2716 MXenes discovered for each structure: M_2XT_x , $M_3X_2T_x$, 2717 $M_4X_3T_x$, and $M_5X_4T_x$.^{464,465} For some specific chemistries, 2718 there are predictions of ferromagnetism, topological semi- 2719 conductors, and others, depending on the specific chemistry and 2720 surface chemistry.^{466,467} Additional effort must be placed on the 2721 synthesis and discovery of these materials. Generally, multiple- 2722 M chemistry represents the future of MXenes with desired 2723 properties. Thus, additional systematic studies are needed to 2724 determine the specific relationships and effects different 2725 chemistries have on MXene properties and need incorporated 2726 into computational models to further guide experimental 2727 studies. 2728

Making Magnetic Layered Compounds with High 2729 Curie Temperatures. Adding more Fe into Fe_nGeTe_2 is 2730 expected to enhance the strength of the exchange interaction 2731 present and consequently allows one to push toward higher 2732 Curie temperatures (T_c) . Indeed, from Fe₃GeTe₂ to Fe₅GeTe₂ 2733 with thicknesses around 10 nm or thicker, $T_{\rm C}$ was found to 2734 generally increase from about 220 K to about 300 K. These 2735 promising $T_{\rm C}$ values are expected to further increase with 2736 increasing Fe content to values up to and even beyond 500 K.⁴⁶⁸ 2737 Recent theoretical studies also predicted that Fe₆GeTe₂ and 2738 Fe₇GeTe₂ are stable 2D phases.⁴⁶⁸ However, experimental 2739 validation is lacking. In-depth studies that correlate structure, 2740 specifically the precise atomic arrangement of nearest neighbor 2741 Fe facilitating the magnetic coupling, and the resulting magnetic 2742 properties at the mesoscopic scale, in particular $T_{\rm C}$, magneto- 2743 crystalline anisotropy, coercive fields, remanence and magnetic 2744 domain structure, will establish the structure-property relation- 2745 ship in these material systems and help form a comprehensive 2746

2747 understanding of magnetic phenomena in these material 2748 systems.

Strain Engineering for 2D Materials. To tune the 2749 2750 structural or electronic phases of materials, strain is as important 2751 as temperature. The six independent strain components and 18 2752 independent strain gradients provide a vast design space to 2753 explore or engineer the thermodynamic landscape of materials 2754 and their properties. So far, most strain engineering or strain 2755 gradient engineering studies have been focused on utilizing one 2756 or two independent components. There are a plenty of 2757 uncharted spaces yet to be explored. Experimental challenges 2758 exist in realizing a multistrain or multistrain gradient tuned 2759 system. While both mechanical bending/stretching and epitaxial 2760 growth can lead to the design of one or two independent strain 2761 or strain gradient components, there is no reliable experimental 2762 approach to realize a complex designed strain or strain gradient 2763 pattern. Further, the vdW or quasi vdW bonding nature of these 2764 2D materials makes it difficult to introduce long-lasting strain 2765 without delamination subject to thermal or mechanical cycling. To reproduce the technical successes of strain engineering in 2766 2767 Si transistors or III-V quantum well layers, one also must be able 2768 to produce the strain and strain gradients at the large or wafer 2769 scale. For this, mechanical stretching or similar local approaches 2770 involving the use of a sharp mechanical tip or structure may be 2771 replaced by large scale strain engineering approaches such as epitaxy using lattice mismatched substrates that are widely used 2772 2773 in commercial III-V quantum well systems. Most works on the 2774 epilayer-substrate interaction in 2D materials have been 2775 focused on graphene or MoS₂. When the interlayer interactions 2776 in 2D materials become strong, it has been found that some 2777 epitaxial 2D layers may take epitaxial strains as high as a few percent.^{469,470} However, it is unclear how and why such large 2778 2779 strain even exists. Further efforts are needed to understand the 2780 materials chemistry and epitaxy science of 2D materials for strain engineering. Though strain, in theory, can be produced at a large 2781 2782 scale for 2D systems, the strain gradient, by its nature, prevents 2783 its development beyond the nanometer scale. Due to this reason, 2784 works on strain gradient engineering of 2D materials have been 2785 focused on the small scale. A potential strategy in the mass 2786 production of the strain gradient is to separate a large piece of 2787 2D materials into many nanoscale pieces with each serving as an 2788 active component carrying a large enough strain gradient. This 2789 approach, though, may bring complexity in devices fabrication, 2790 especially if the out-of-plane dimension is needed in designing 2791 the strain gradient.

SHG in 2D Materials. One future challenge is seeking a 2792 2793 rational design principle for materials with large $\chi^{(2)}$ that could 2794 exceed the current apparent upper boundaries of the $\chi^{(2)}$ -2795 bandgap trade-off, with initial efforts focusing on cataloging 2796 materials data for $\chi^{(2)}$ and bandgap through high-throughput 2797 computation, as has been carried out for 3D bulk materials in 2798 Naccarato et al.⁴⁷¹ One empirical observation related to 2799 dimensionality is that, among materials with similar bandgaps, 2800 $\chi^{(2)}$ tend to be larger for lower-dimensional materials since they 2801 host more pronounced singularities in their low-energy 2802 excitation spectra that contribute to a nonresonant nonlinear 2803 response.⁴⁷² It is unclear to what degree this strategy would 2804 apply since, by extrapolation, one may expect molecular systems 2805 to achieve the largest $\chi^{(2)}$, yet there have been no reports 2806 demonstrating this.

2807 **2D/3D Electronic Devices.** The marriage of 2D semi-2808 conductors with crystalline 3D materials is a rich area of 2809 exploration not just from the perspective of basic interface physics but also in terms of high-performance device 2810 applications. In terms of logic devices, the appeal of TFETs 2811 with a steep SS concurrently with a high on/off current ratio and 2812 a high on-current density is a worthy and impactful goal. Further 2813 studies and investigations are warranted to scale the devices and 2814 optimize contact, junction, and dielectric-semiconductor 2815 interfaces in addition to pursuing high quality, near-intrinsic, 2816 phase pure and scalable growth of 2D semiconductors. From the 2817 perspective of memory devices, the appeal of low-depolarization 2818 fields in atomically thin bodies combined with transferrable, 2819 high quality layered semiconductors makes it worthwhile to 2820 pursue interfaces between 2D semiconductors and 3D ferro- 2821 electrics. Additionally, 3D ferroelectrics that have low-static 2822 dielectric constants and high remnant polarizations that can be 2823 integrated with the 2D semiconductors are equally important to 2824 attain long retention. The grand challenges in this area, pertain 2825 once again to scaling the 2D materials to wafer scales as well as 2826 retaining device performance for highly voltage and area-scaled 2827 devices. Finally, 2D ferroelectric semiconductors are another 2828 very promising class of materials, and their junctions with 3D 2829 semiconductors and 3D ferroelectric dielectrics will be beneficial 2830 to device design and applications. 2831

MTI Devices. In the ideal case, MTI-based devices will make 2832 disseminating the ohm more economical and portable and will, 2833 more importantly, serve as a basis for a compact quantum 2834 ampere, an electrical standard that has been even more limited in 2835 its versatility than resistance or voltage standards, primarily 2836 because they are based on single electron transistors. For 2837 instance, at present, the global accessibility of the quantum 2838 ampere is constrained to mostly National Metrology Insti- 2839 tutes.⁴⁷³ Other limitations that may possibly be overcome by 2840 using MTIs include the sub-nA currents typically associated 2841 from the aforementioned single electron transistors and the 2842 Josephson voltage standard's aversion to magnetism, which 2843 would complicate its integration with a graphene-based 2844 resistance standard in a single cryostat. The work that comes 2845 from MTIs and any other 2D material system that exhibits the 2846 QAHE will help to move forward the realization of the quantum 2847 SI in terms of electrical standards. The realization of a compact 2848 quantum ampere through integration of devices operable in a 2849 zero-field environment will impact how calibration services are 2850 provided for industry. 2851

Going forward, three research directions can emerge from 2852 among following efforts: (1) Identification of the physical 2853 limitations of the many promising materials, both through 2854 experimental and theoretical means. For instance, computing 2855 the defect behavior and the impact of disorder on Hall 2856 quantization would provide invaluable knowledge to materials 2857 growers. (2) Optimization of the best QAHE materials for 2858 device applications. In theory, knowledge from the first listed 2859 research direction (1) would provide a feedback loop with which 2860 one could narrow down the list of systems with immediate 2861 promise, allowing researchers the ability to determine dominant 2862 sources of nonideal behavior (e.g., point defects, magnetic order 2863 inhomogeneity such as domain walls, etc.). (3) Testing of 2864 applied QAHE technologies. Although the QAHE has been 2865 understood much more in recent times, there are still vast 2866 amounts of interdisciplinary work required to harness the effect 2867 in a way that enables the adoption of relevant 2D material 2868 systems for future technological advances. 2869

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3124 VOCABULARY

3125 2D materials: A class of crystalline solids consisting of a single

layer of atoms or molecules that are covalently bonded withinthe 2D plane and held together by weak van der Waals forces

3128 between adjacent layers.

ReaxFF:The reactive force-field (ReaxFF) interatomic potential is a computational method used to study chemical

3131 reactions in large-scale systems over long time scales bridging

together the accuracy of *ab initio* methods with the computational efficiency of classical force field methods.

van der Waals Epitaxy: A heteroepitaxy method for growth of

high-quality 2D materials that relies on van der Waals forces

between the substrate and the epilayer, thereby lifting lattice mismatch and thermal mismatch constraints of traditional

3138 heteroepitaxy.

MXenes: A family of 2D materials composed of transition metal carbides, nitrides, and carbonitrides with the general formula $M_{n+1}X_nT_x$, where M is an early transition metal, X is either C and/or N, n = 1-4, and T_x represents surface

³¹⁴³ functional groups such as -OH, -O, -F, and -Cl.

3144 Strain Engineering: A method to tune the structural, 3145 electronic, and optical properties of 2D materials by applying

3146 a mechanical stress.

3147 Multidimensional Heterostructures: Systems in which materi-

als of mixed dimensionality are placed in contact to take
 advantage of rich interface physics. This review will focus on
 examples of 2D crystals integrated with materials of different

dimensionality to realize mixed-dimensional vdW hetero-

3152 structures of the form 2D + nD (n = 0, 1, and 3).

3153 MTIs:Magnetic topological insulators (MTIs) are a recently

3154 discovered quantum materials class in which a combination of 3155 magnetism and nontrivial band topology can create a variety

3155 magnetism and nontrivial band topology can create a variety
 3156 of topological phenomena such as the quantum anomalous

Hall effect and topological axion insulating states.

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